

# Surfaces in the Real World - Adsorption

## Lesson 2

MSE 304

Nako Nakatsuka

[Nako.Nakatsuka@epfl.ch](mailto:Nako.Nakatsuka@epfl.ch)

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# Plan of the Course: Fundamentals, Characterization, and Applications

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1: Intro to Surfaces & Interfaces

2: Surfaces in the Real World - Adsorption

3: Surface Fundamentals – Energy & Structure

4: Solid-Solid Interfaces

5: Characterization of Real Surfaces

6: Solid-Liquid Interfaces + Techniques

7: Interfacial Phenomena

8: Charged Solid-Liquid Interfaces

9: Surface Chemistry

10: Biological Processes at Surfaces

11: Electronic Properties of Surfaces

12: Thin Film Technologies

13: Biosensor Fundamentals

14: Biosensing applications

Things may be adapted in real time – thank you for your patience!  
Midterm feedback (Week 5) – Recap session Week 7?



# Recap from Lesson 1

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- Surface science is not a mature field
- Why study surfaces and interfaces?
- Challenges of studying surfaces and interfaces
- Keeping surfaces clean is very challenging – UHV can help

What's really on a surface and how do we deal with it?



# Outline of Lesson 2

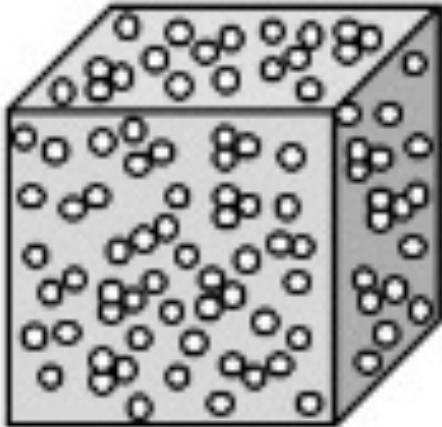
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- Basics of physisorption and chemisorption
- Short recap of crystal structures
- Visualizing surfaces at the atomic level – scanning tunneling microscopy (STM)
- Surface contamination sources & problems
- How to obtain clean surfaces – cleaning hierarchy



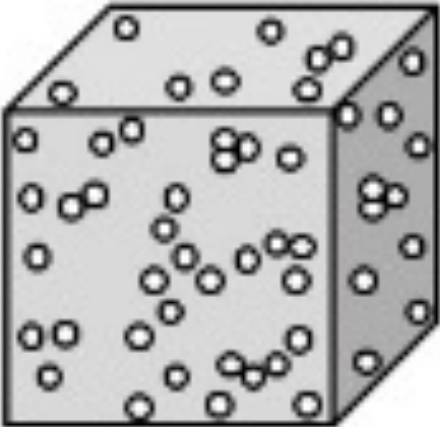
# Instantaneous Contamination on Surfaces

**Rough Vacuum**  
 1 atm –  $10^{-3}$  Torr



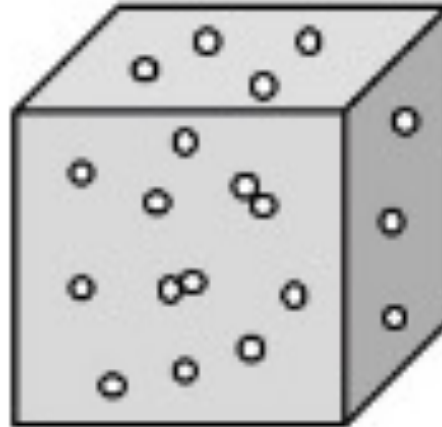
$1 \times 10^{-3}$  Torr  
 $10^{13}$  atoms/cm<sup>3</sup>

**High Vacuum**  
 $10^{-3}$  Torr -  $10^{-8}$  Torr



$1 \times 10^{-6}$  Torr  
 $10^{10}$  atoms/cm<sup>3</sup>

**Ultra High Vacuum**  
 $10^{-8}$  Torr -  $10^{-12}$  Torr

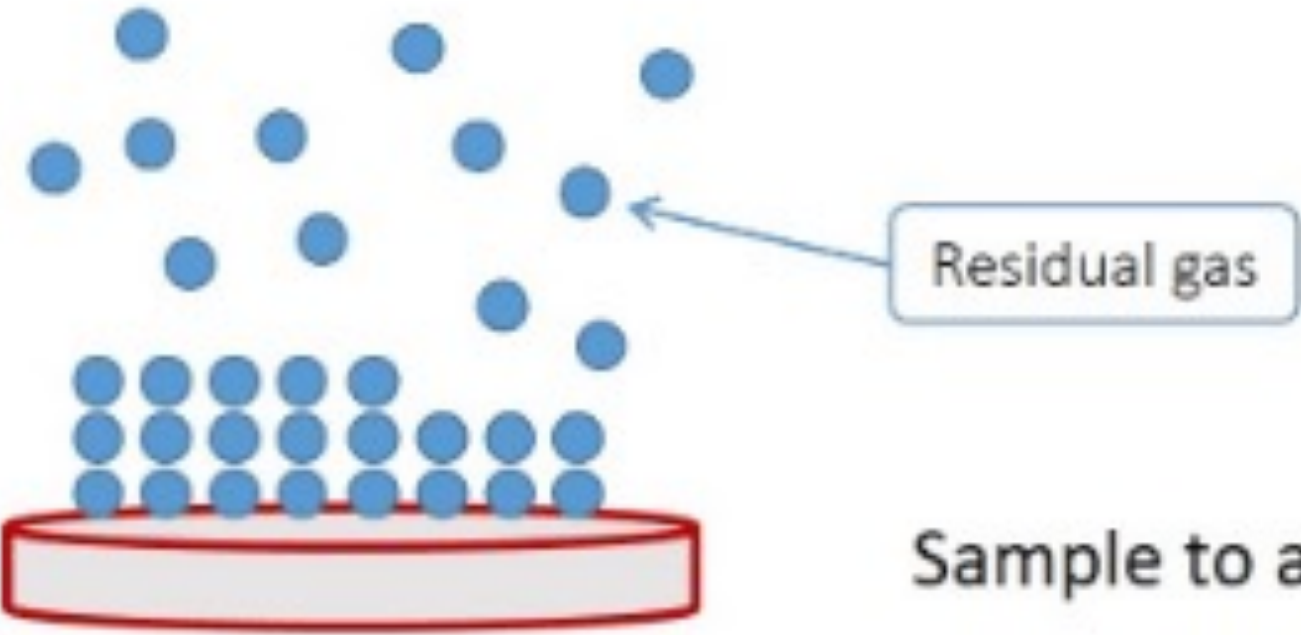


$1 \times 10^{-11}$  Torr  
 $10^5$  atoms/cm<sup>3</sup>

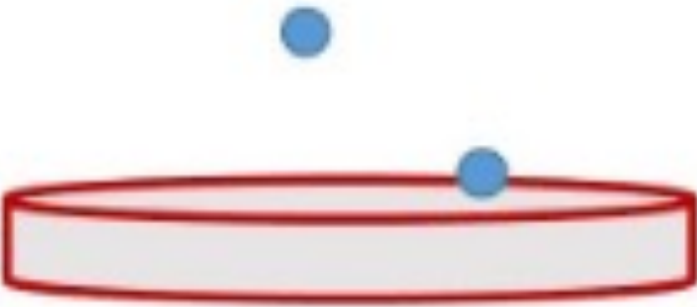
**1 residual gas monolayer**  
 every **4 SECONDS**

**1 residual gas monolayer**  
 every **4 DAYS**

**High Vacuum**



**UHV**



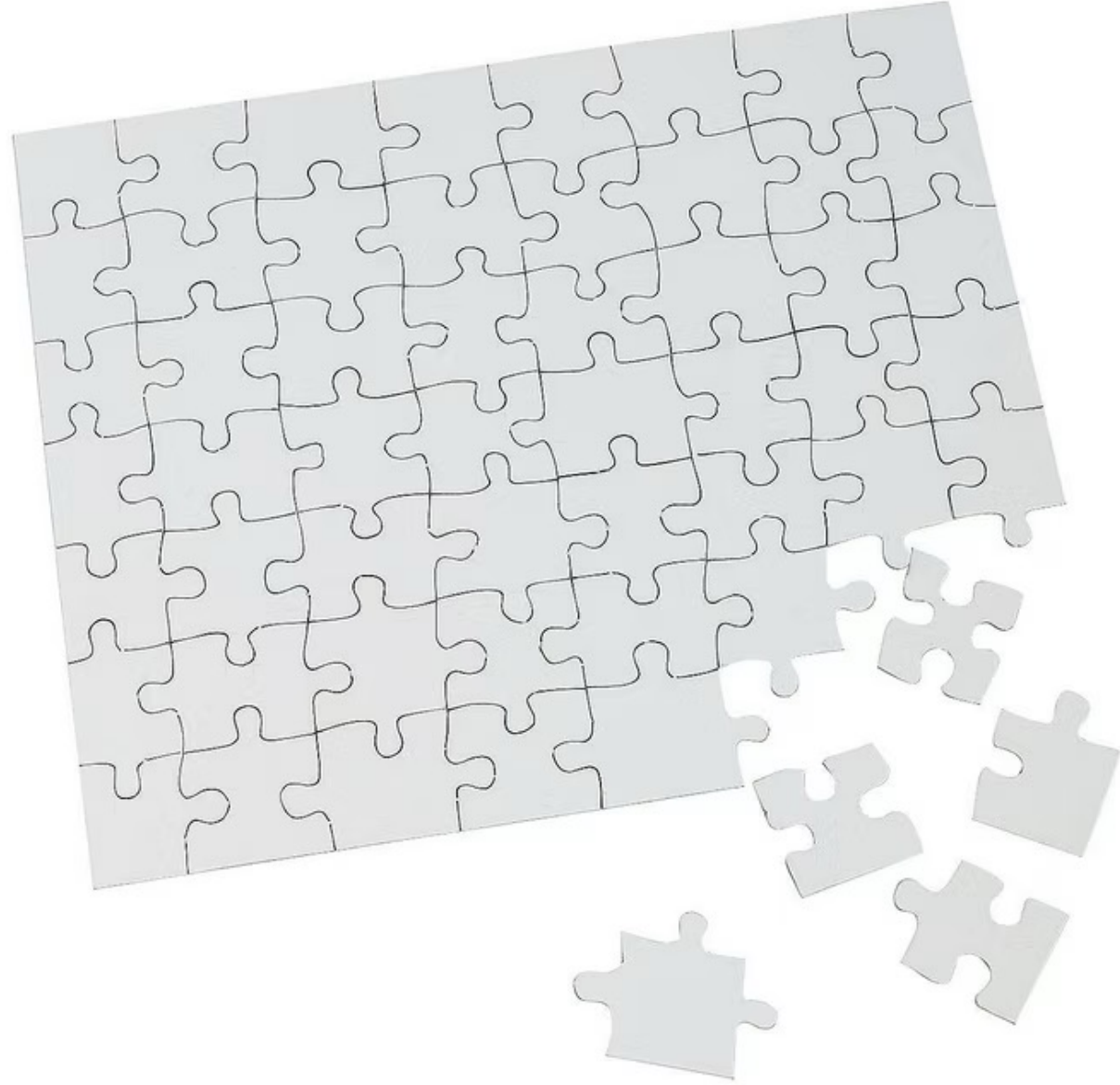
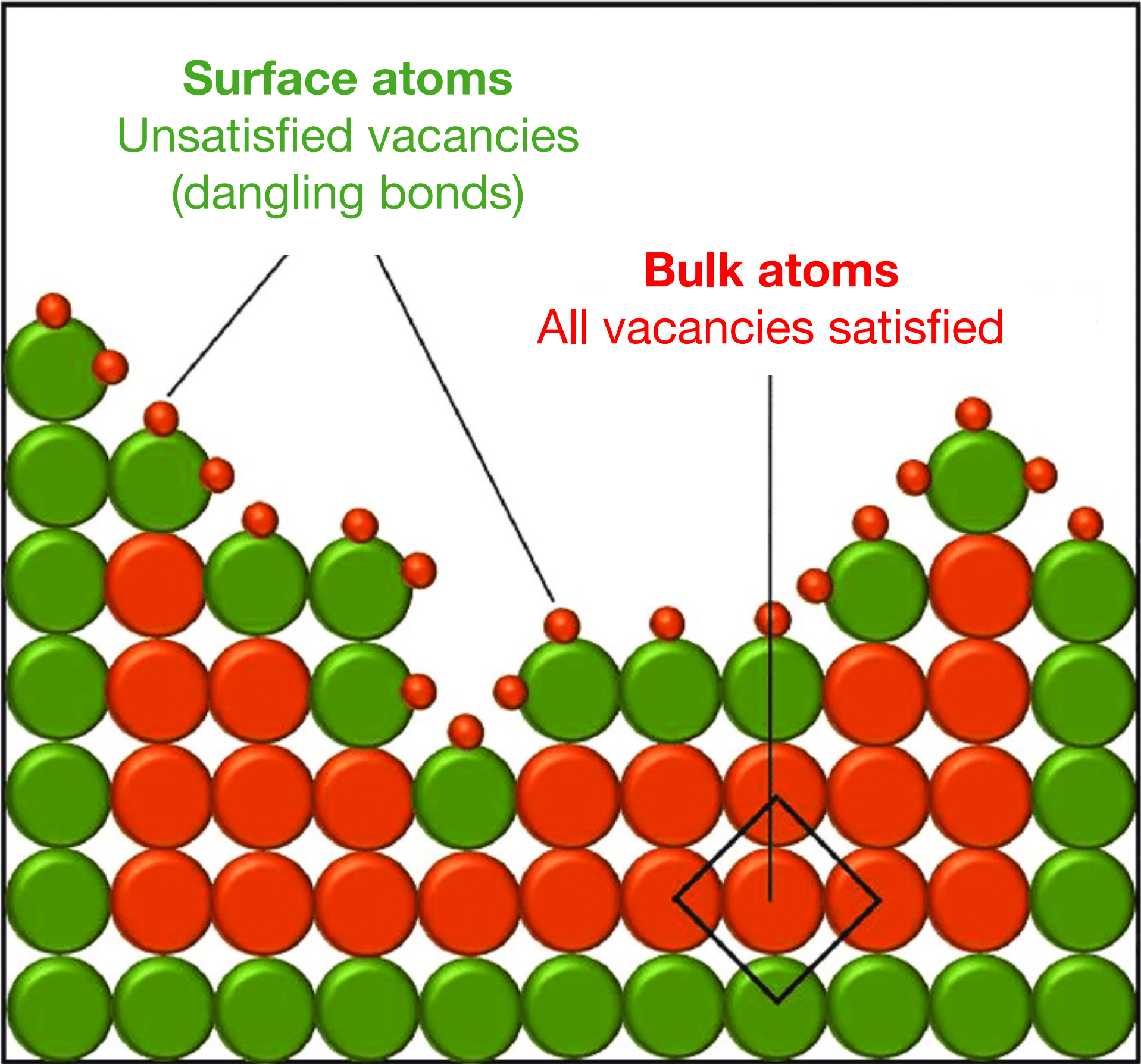
VAC COAT

CHEMNA

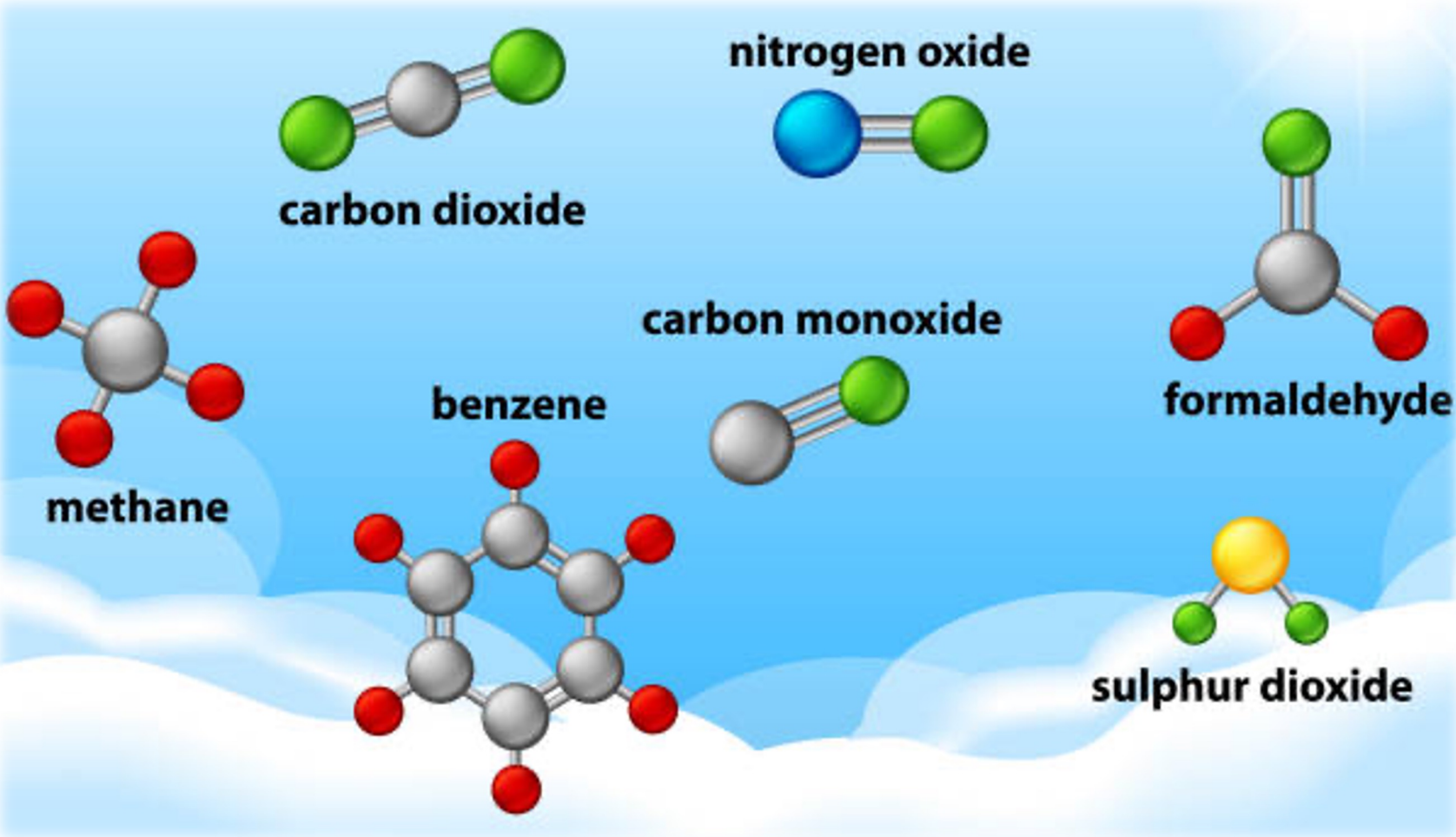
# Clean Surfaces are High Energy – Coatings Lower Energy

Surface energetically unfavorable compared to bulk

Clean surface has a high surface energy and wants to reduce this



# Sources of Surface Contamination



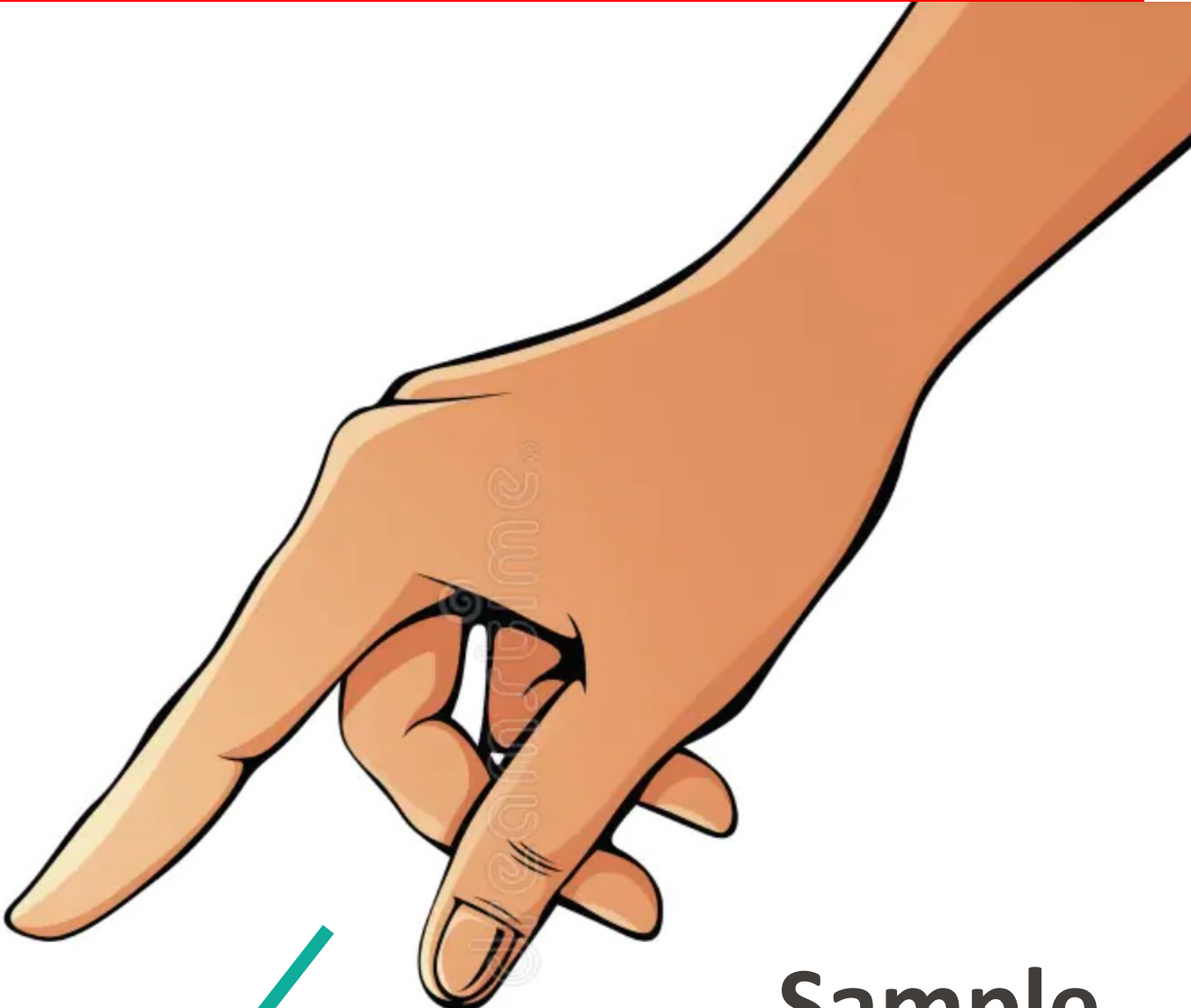
Air contaminants



Humidity



Chemical residue



Sample handling

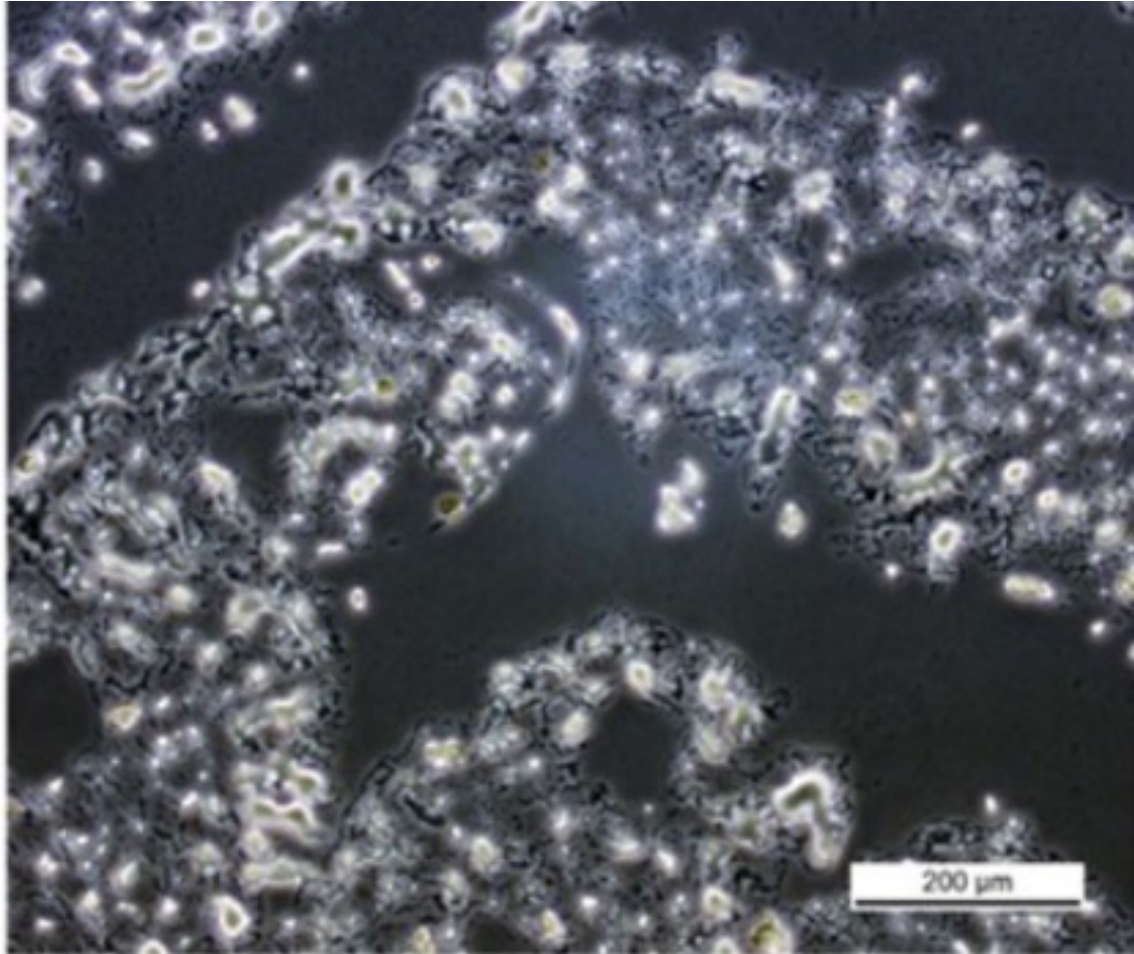


Dust

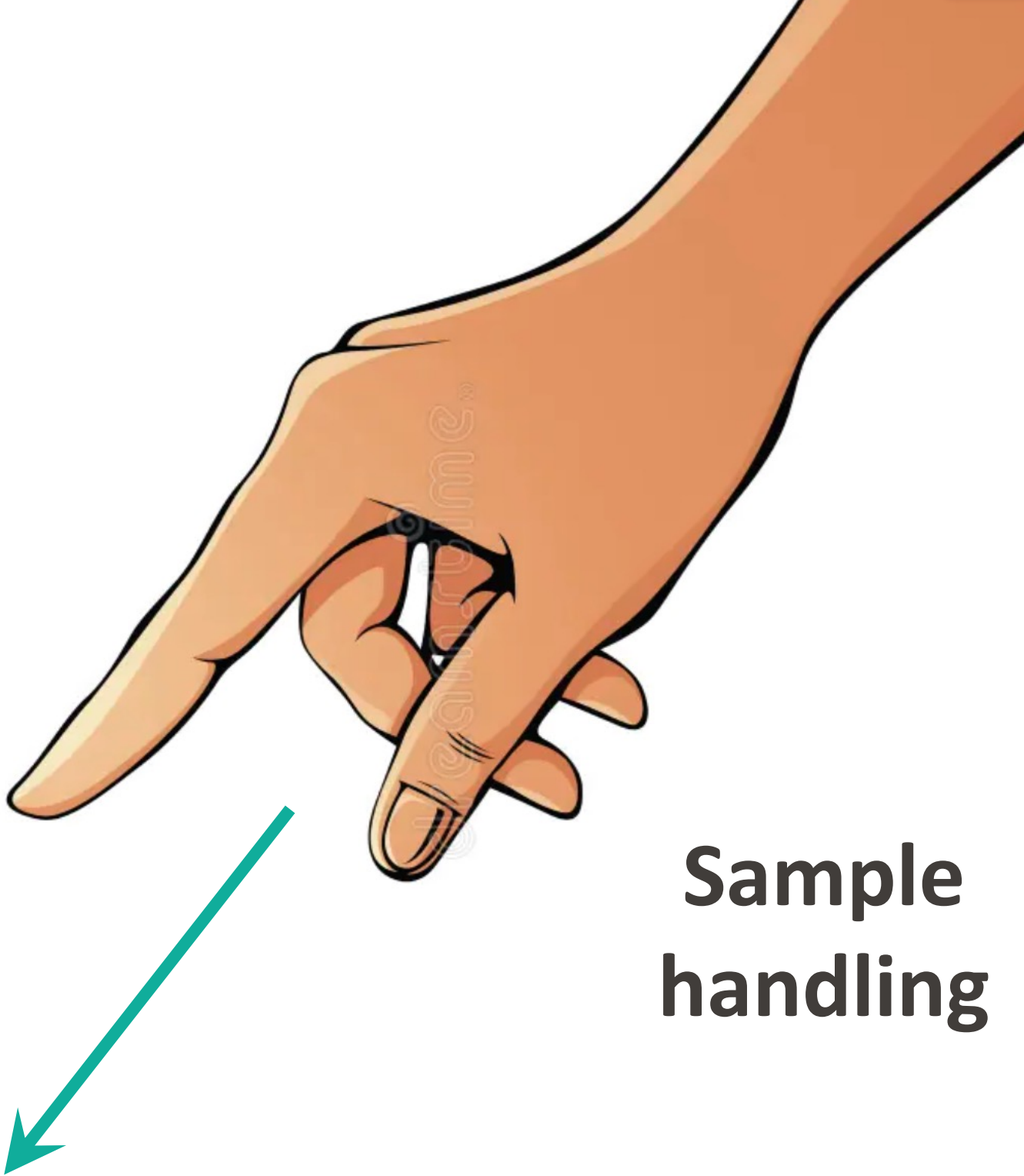
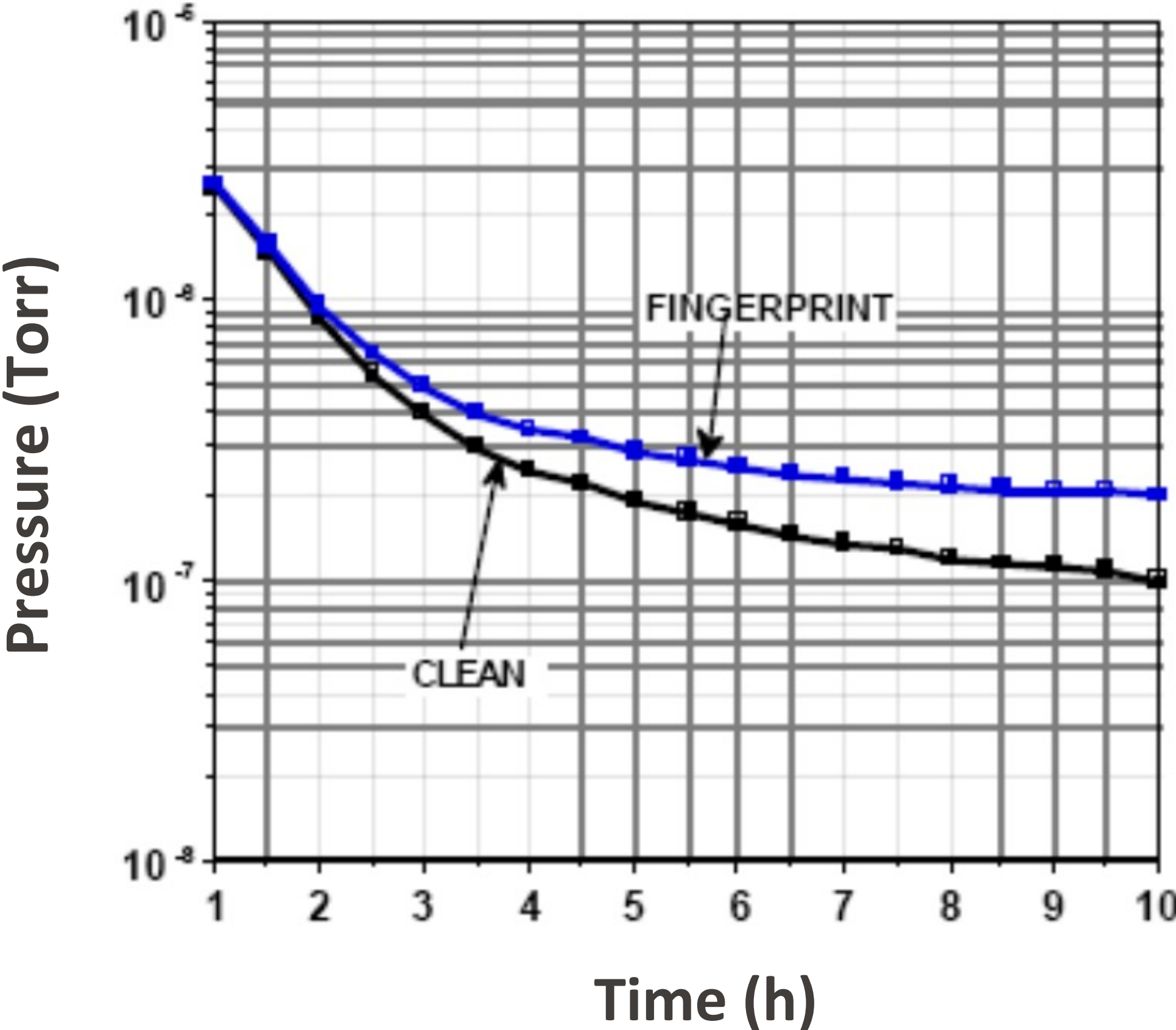


# Single Fingerprint Has a Large Effect on Vacuum Pumpdown

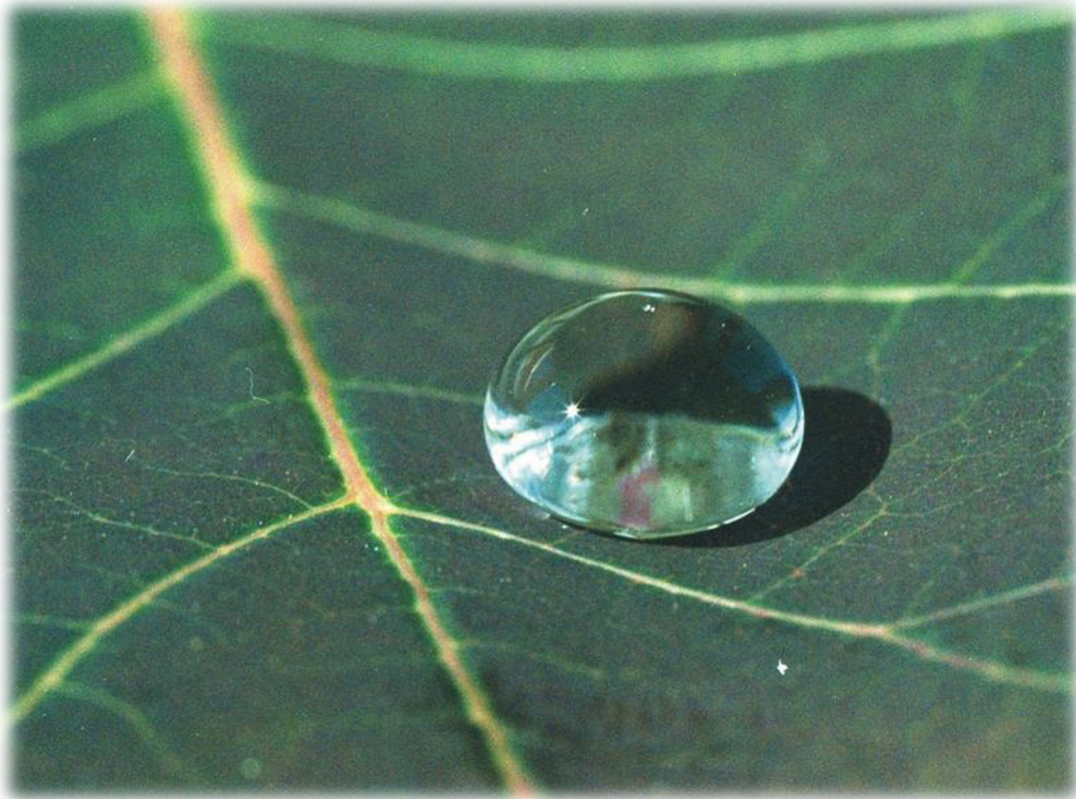
1 fingerprint =  $1 \times 10^{19}$  molecules!



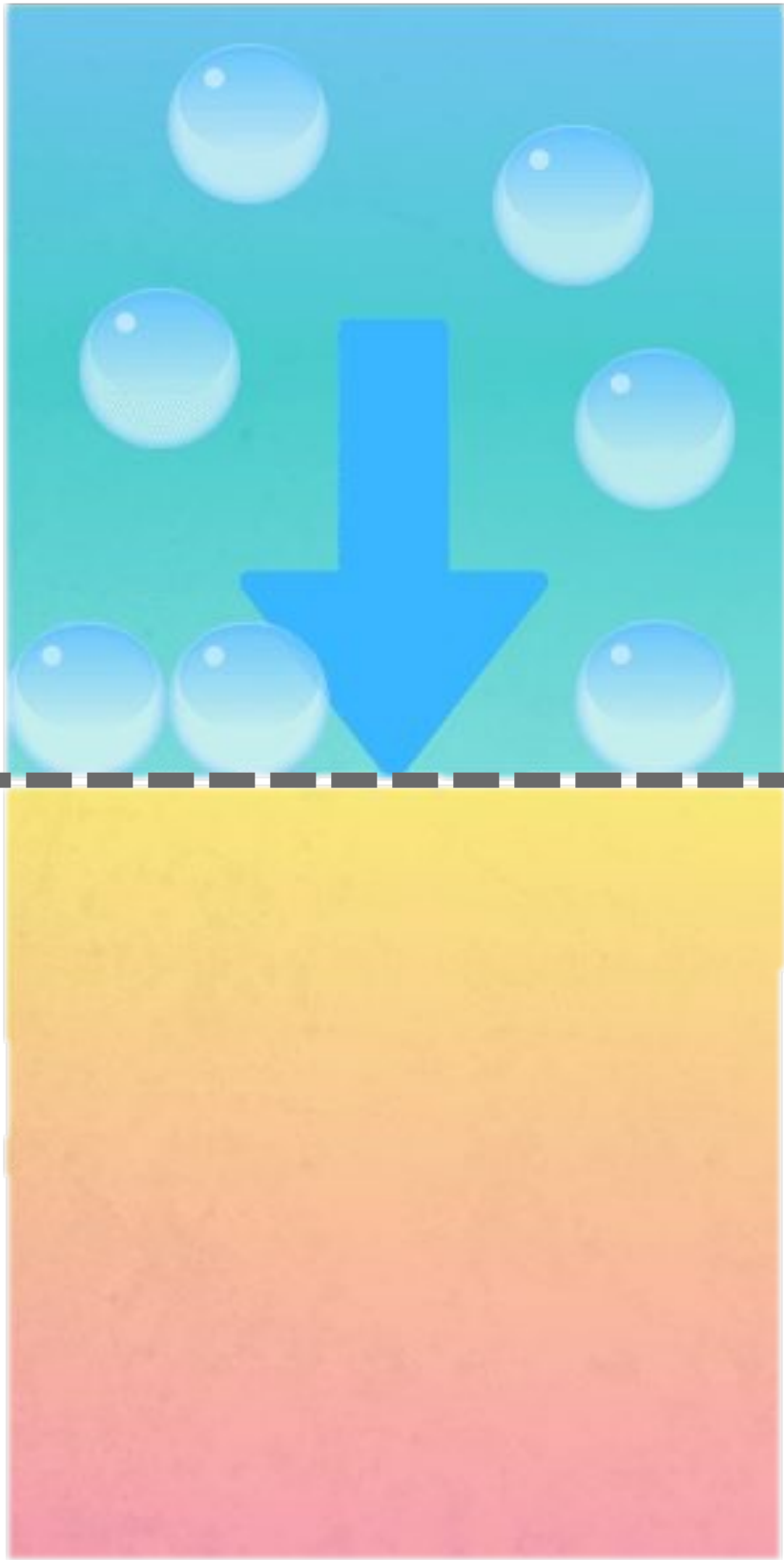
Moret et al. | Forensic Sci. Int. | 2018



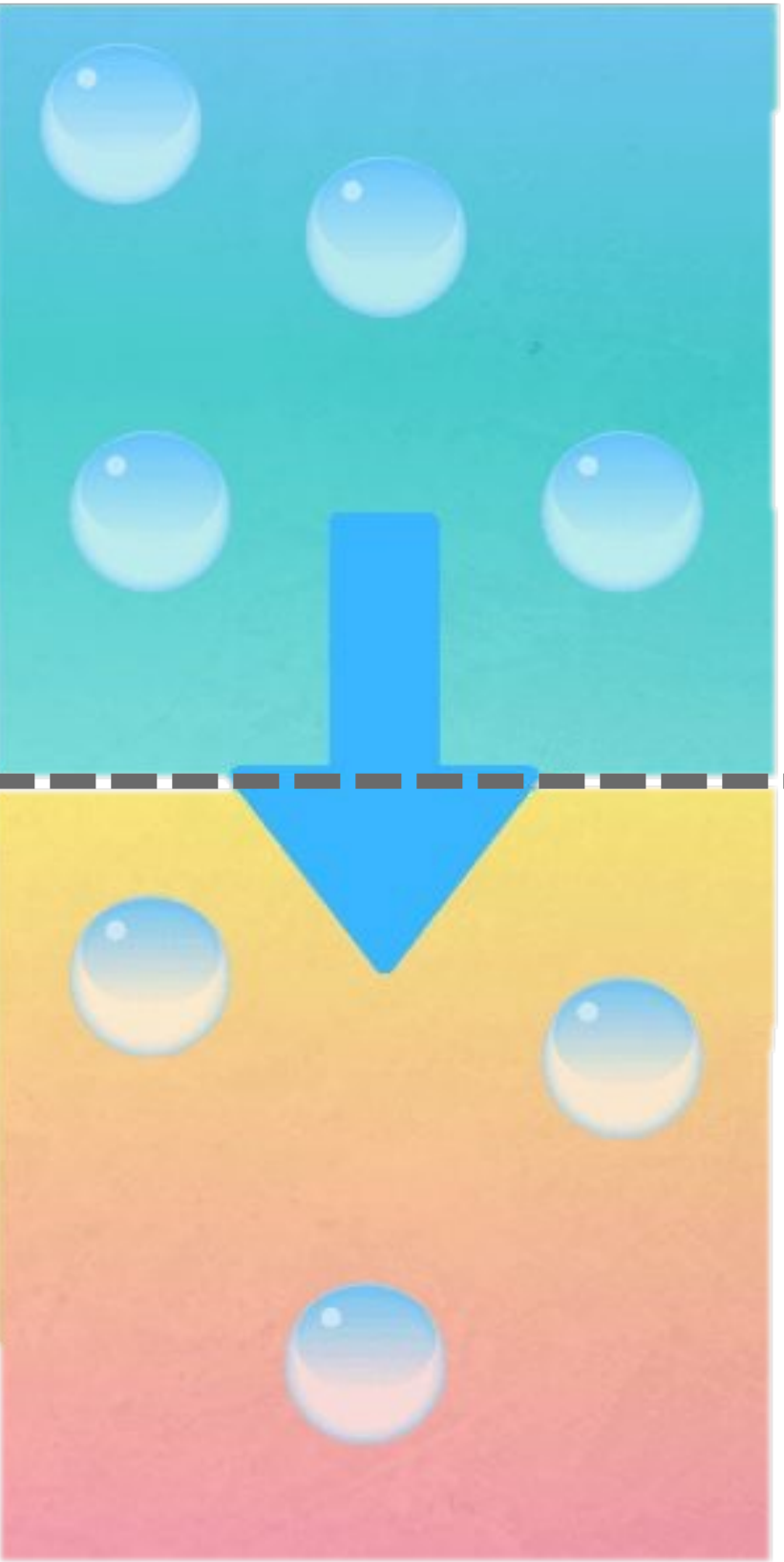
# Careful: Adsorption vs. Absorption



**Adsorption**  
Sticking to the surface  
of the other phase



**Absorption**  
Soaking into the bulk  
of the other phase



Mass transfer **into**  
another material

**SCIENCE NOTES**

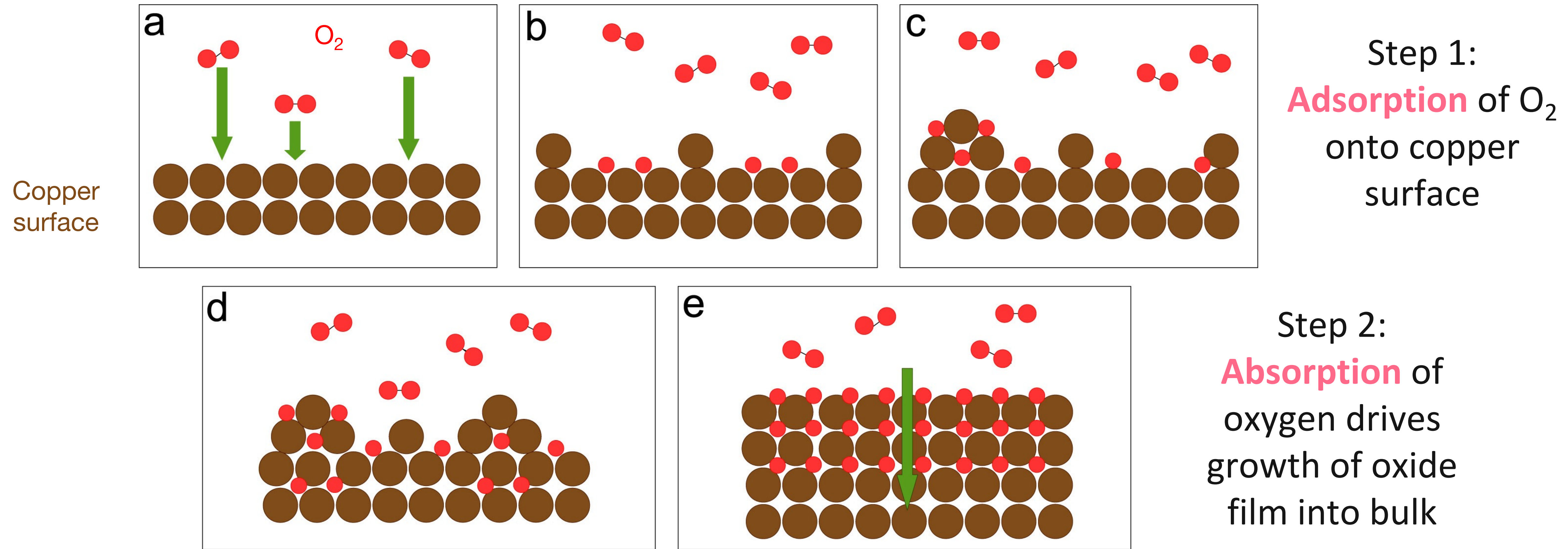
# Careful: Adsorption vs. Absorption

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<b>Adsorption</b>	<b>Absorption</b>
Accumulation onto surface	Accumulation into another substance
Surface phenomenon	Bulk phenomenon
Exothermic process	Endothermic process
Favored by lower temperature	Mostly unaffected by temperature
Rate dependent on surface sites until equilibrium reached	Occurs at uniform rate
Surface concentration differs from internal concentration	Concentration eventually becomes the same throughout material

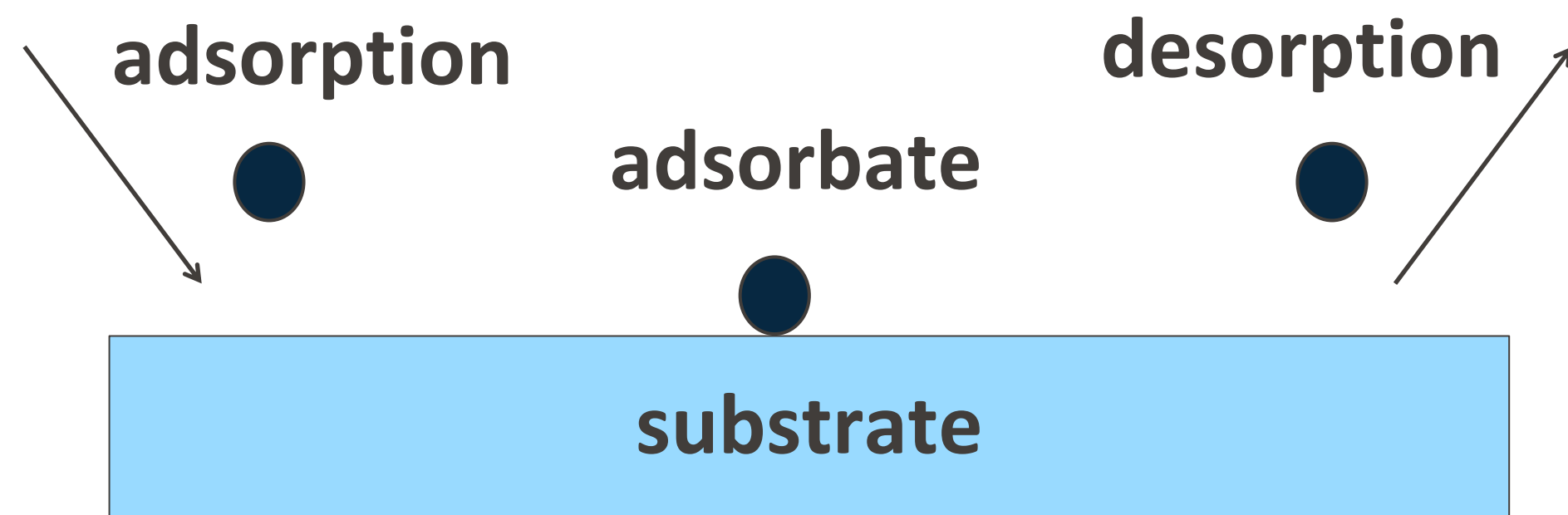
# Metal Oxidation – Adsorption + Absorption

Surfaces in air are mostly covered with multilayers of molecules from the gas phase (H<sub>2</sub>O, hydrocarbons, air components)



Gattinoni & Michaelides | *Surf. Sci. Rep.* | 2015

# The Different Forms of Adsorption on Surfaces



$$\theta = \frac{\text{Number of occupied adsorption sites}}{\text{Number of adsorption sites present}}$$

$\theta = 0$  clean surface

$\theta = 1$  monolayer

## Physisorption

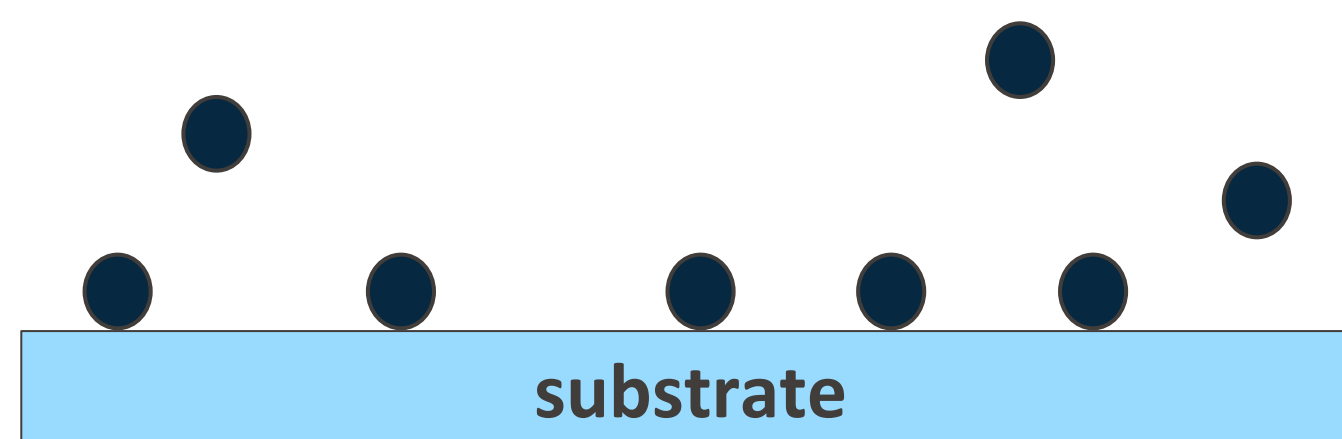
Van der Waals interactions between adsorbate and substrate

non-specific and weak

$$\Delta H_{\text{des}} \approx 20 \text{ kJ/mol}$$

multilayer growth possible

observed mostly at low temperatures



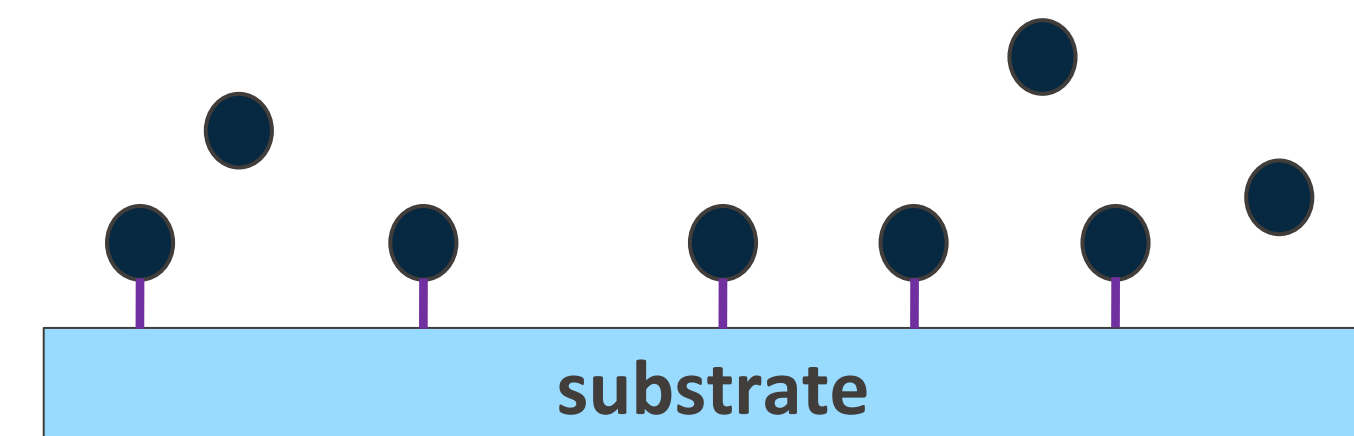
## Chemisorption

Chemical bond between adsorbate and substrate

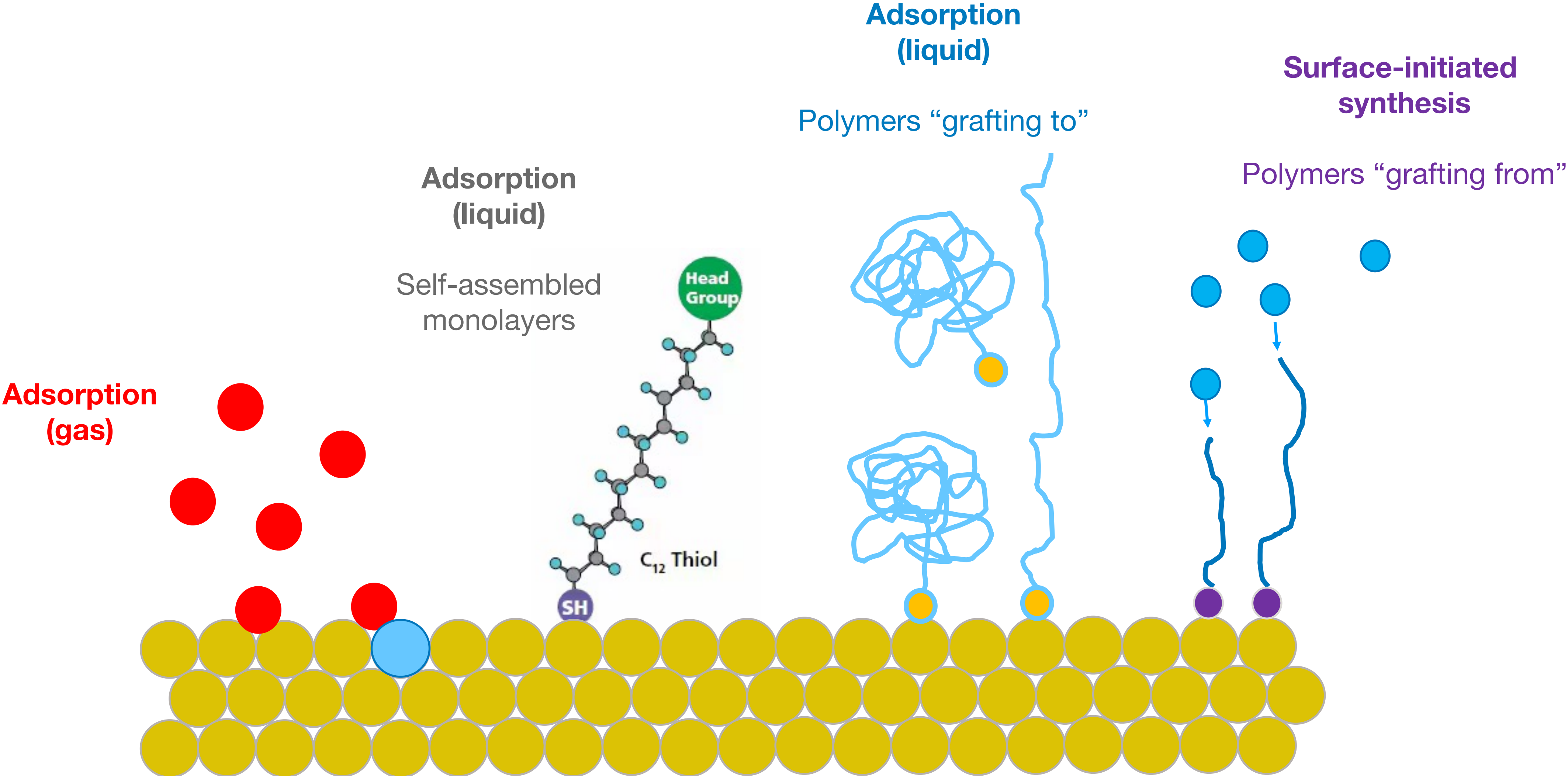
Generally kinetically stable at RT

$$\Delta H_{\text{des}} \approx 200 \text{ kJ/mol}$$

maximum coverage is 1 monolayer ( $\theta = 1$ )



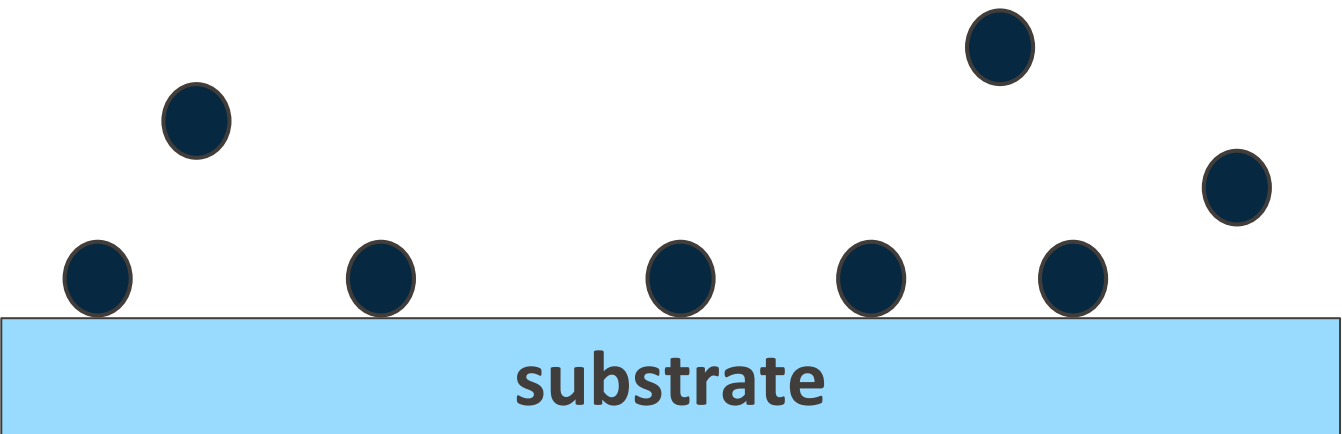
# Chemisorption (Surface Chemistry) In Future Lessons



# Potential Energy Change for Physisorption vs. Chemisorption

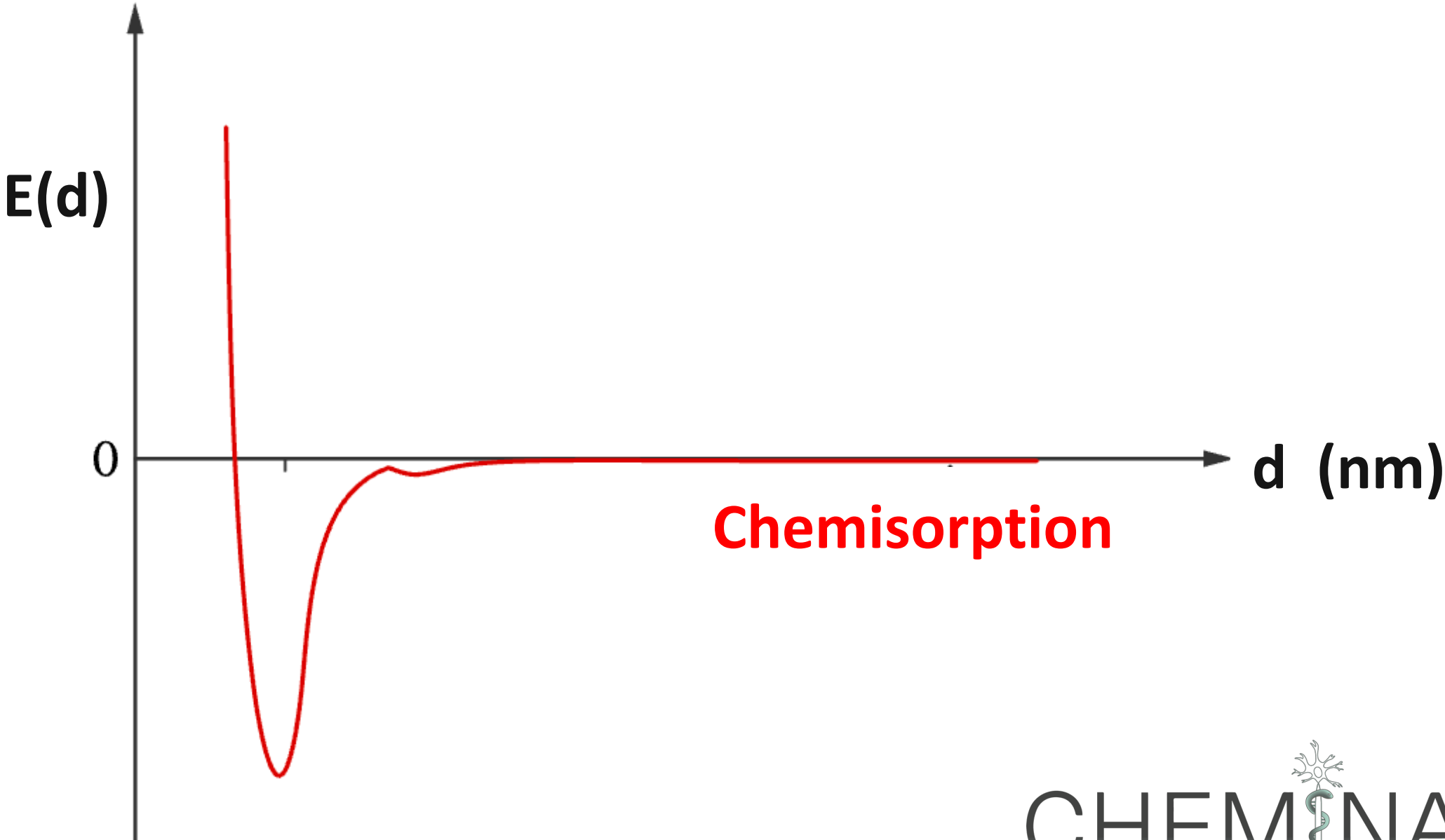
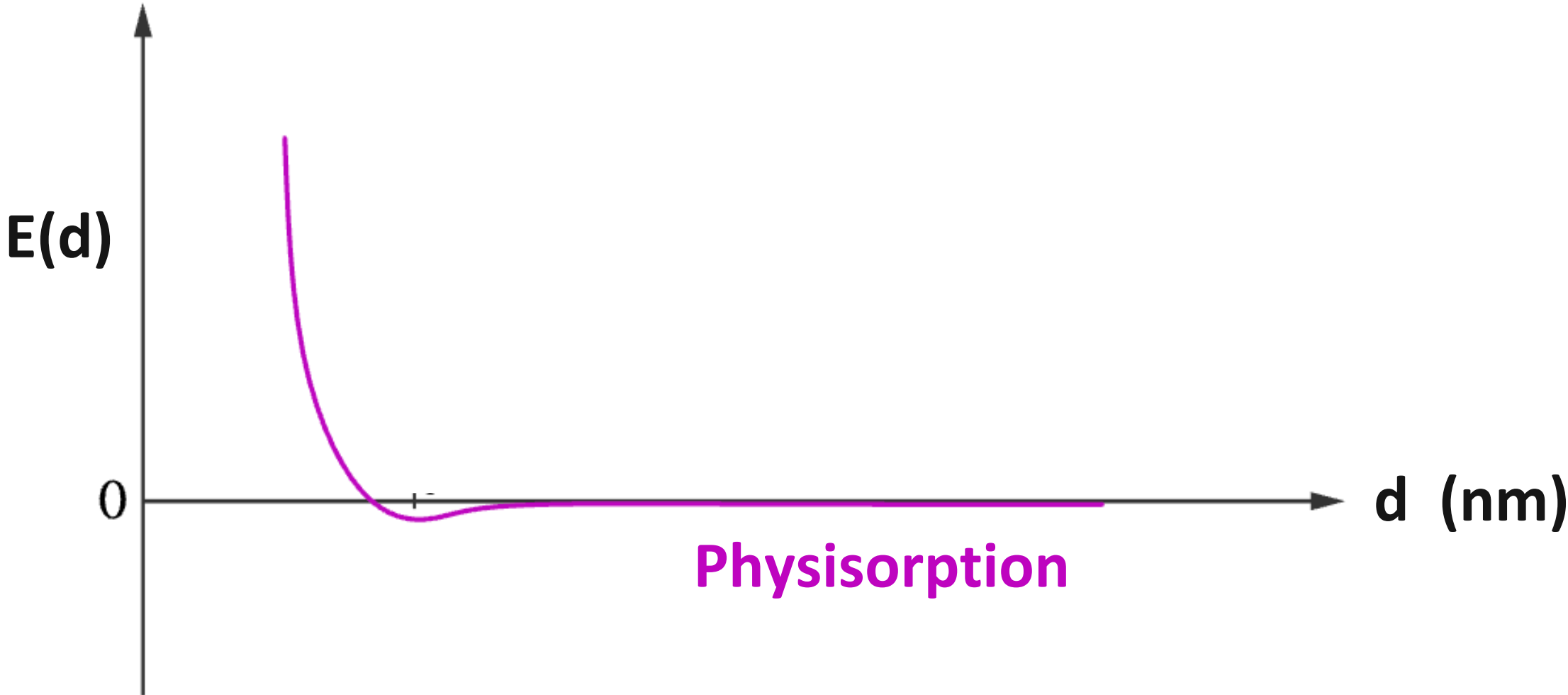
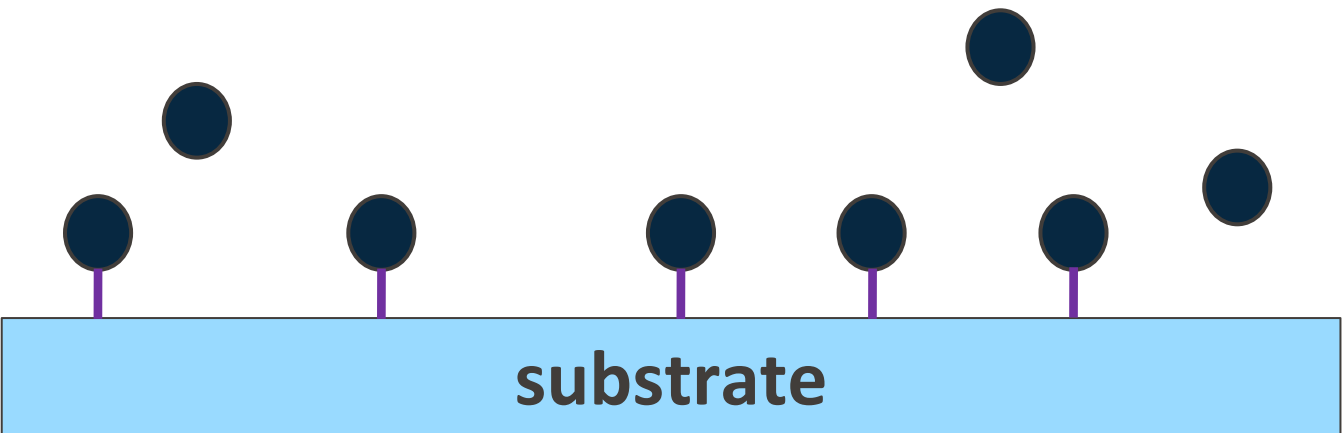
## Physisorption

Van der Waals interactions between adsorbate and substrate



## Chemisorption

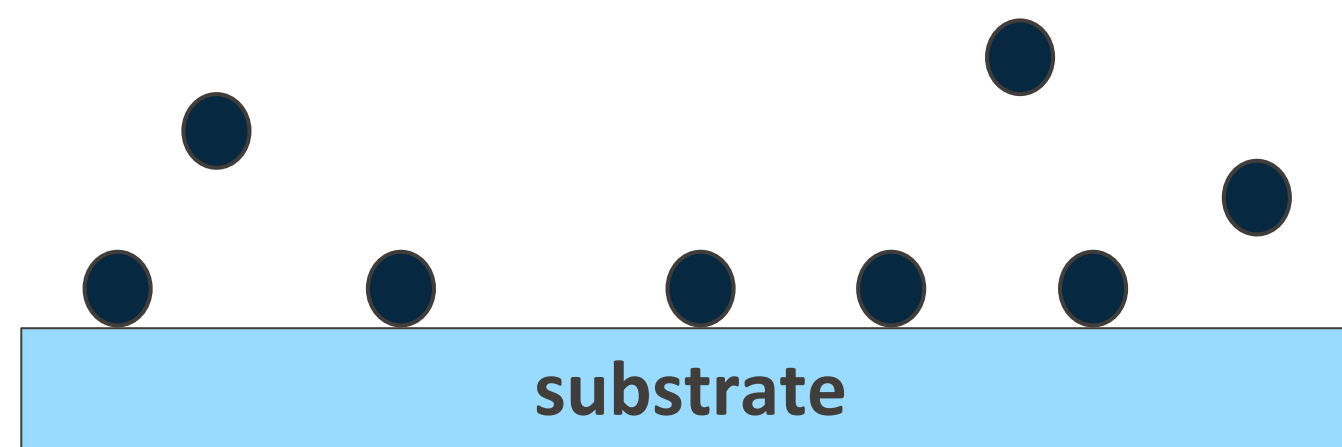
Chemical bond between adsorbate and substrate



# Chemisorption Typically Slower Due to Activation Barrier

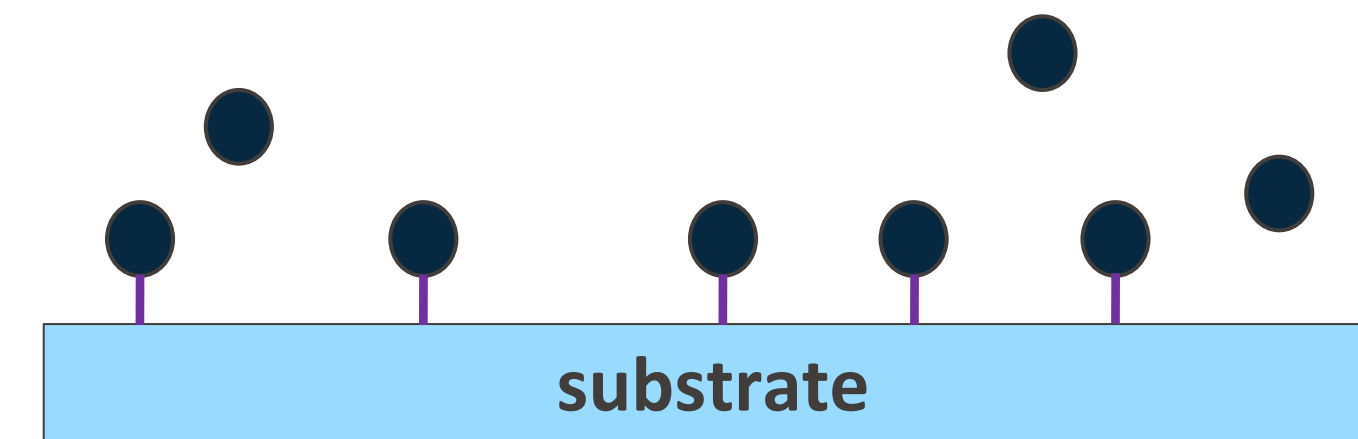
## Physisorption

Van der Waals interactions between adsorbate and substrate

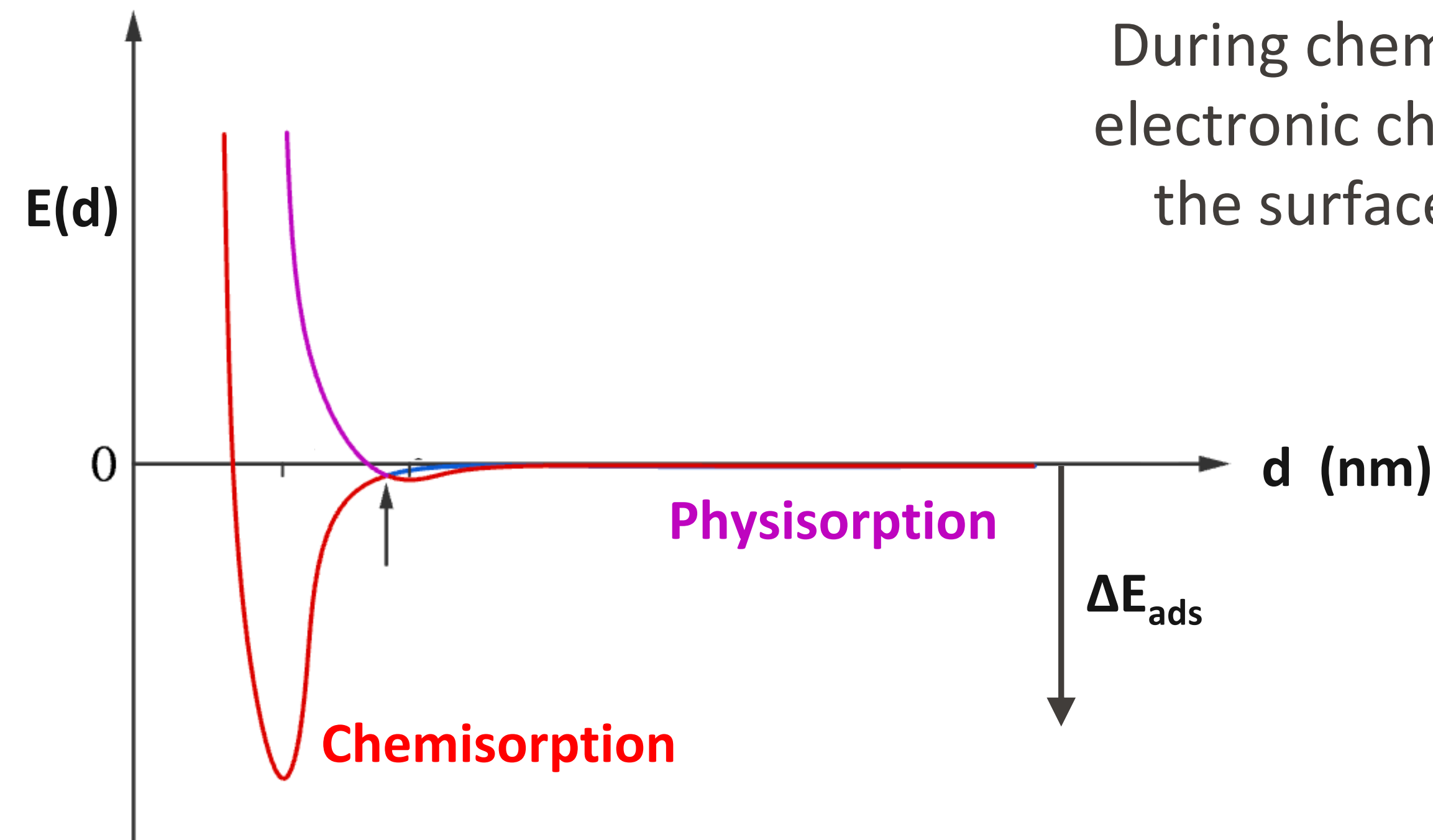
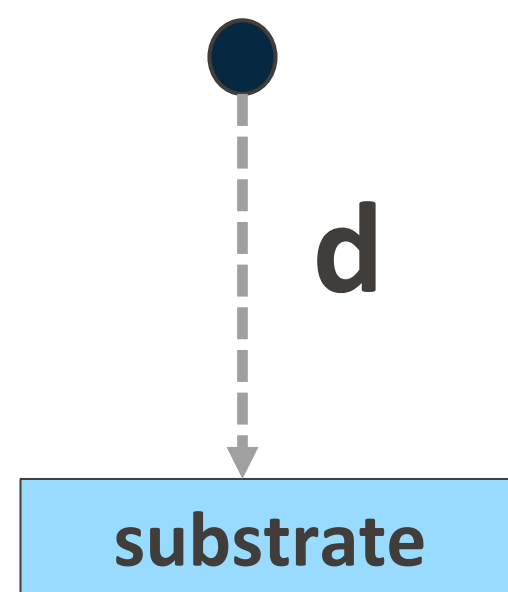


## Chemisorption

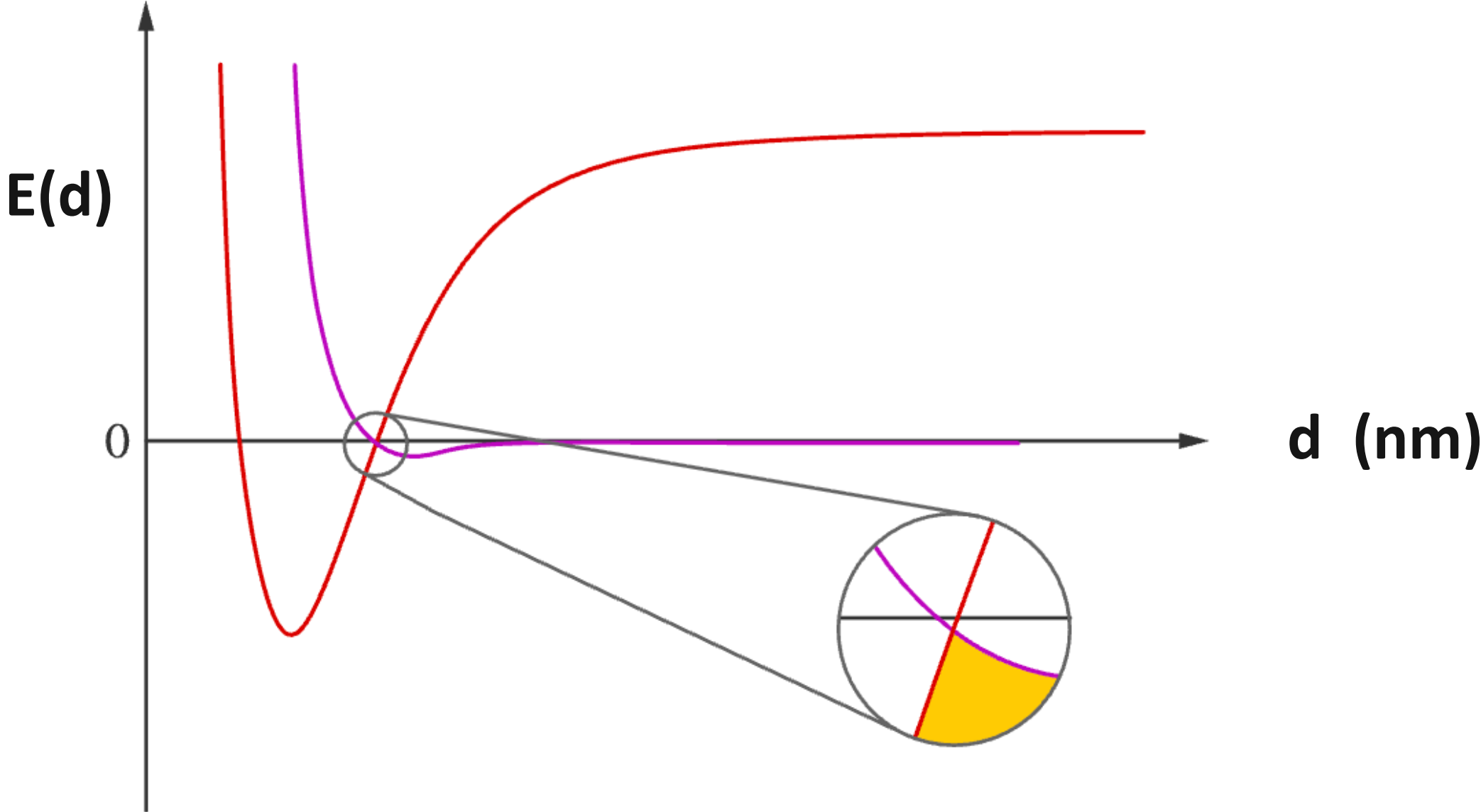
Chemical bond between adsorbate and substrate



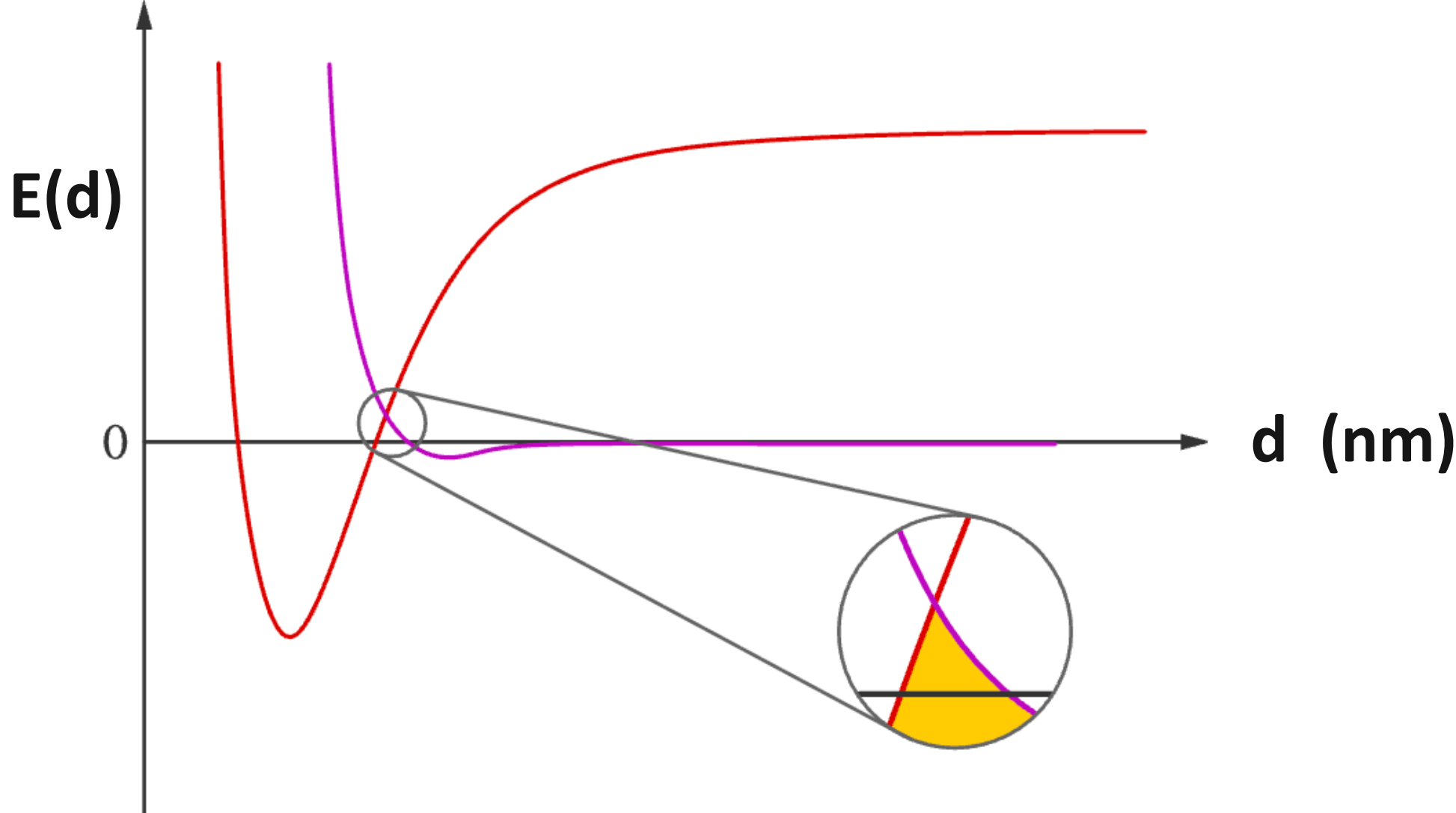
During chemisorption, the electronic characteristics of the surface can change



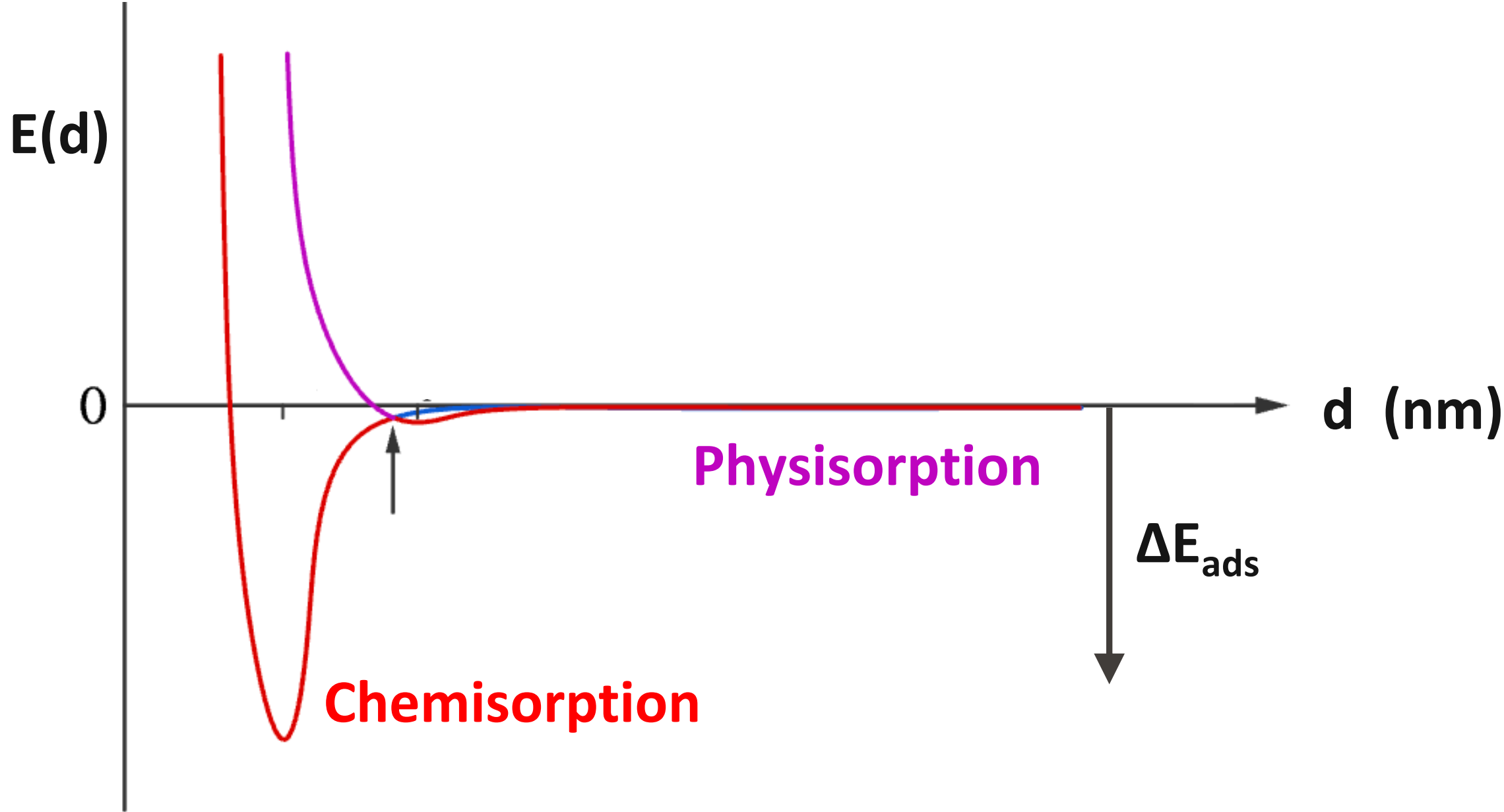
# Crossover Point of Chemisorption/Physisorption Curves



No direct activation barrier for chemisorption to happen



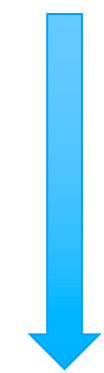
Activation barrier for chemisorption to happen



# Chemisorption on Surfaces Often Occur After Physisorption

Spontaneous process:  $\Delta G < 0$

Adsorbate loses degrees of freedom upon adsorption:  $\Delta S < 0$

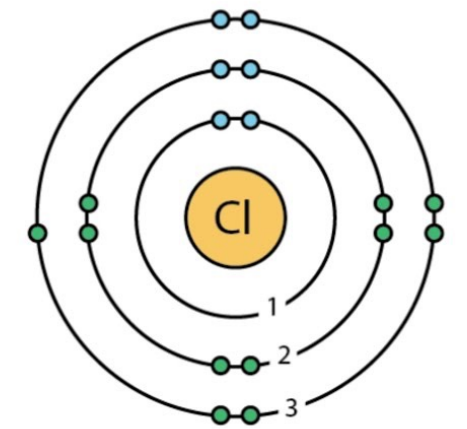


$$\Delta G = \Delta H - T\Delta S \rightarrow +$$

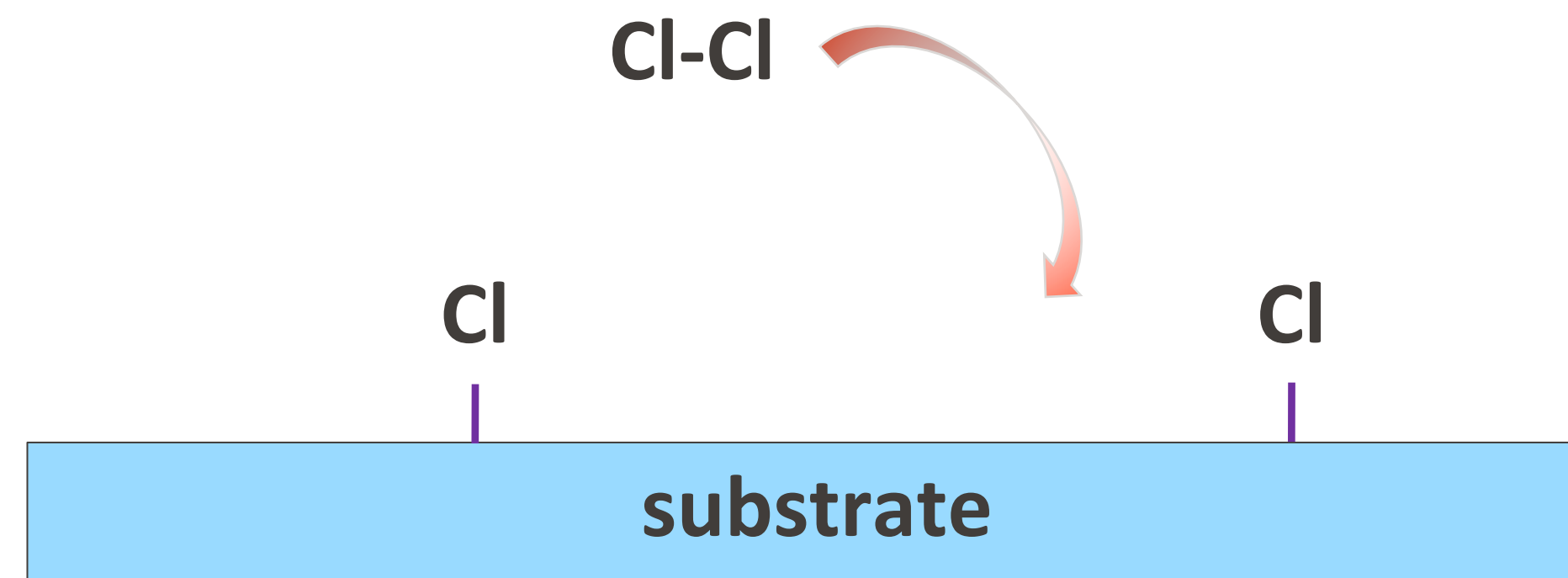
Almost always exothermic:  $\Delta H < 0$

## Atomic Structure

17
<b>Cl</b>
Chlorine
35.45



Dissociation energy (strength of chemical bond) high in gas phase



Surface interactions  
reduce energy required  
to break Cl-Cl bond

Metal surfaces (e.g., Platinum)  $\rightarrow$  empty d orbitals

Semiconductors (e.g., Silicon)  $\rightarrow$  displace H atoms to create Si-Cl bonds

Catalytic surfaces inherently promote bond breaking!

# Chemisorption Exception: H<sub>2</sub> on Glass

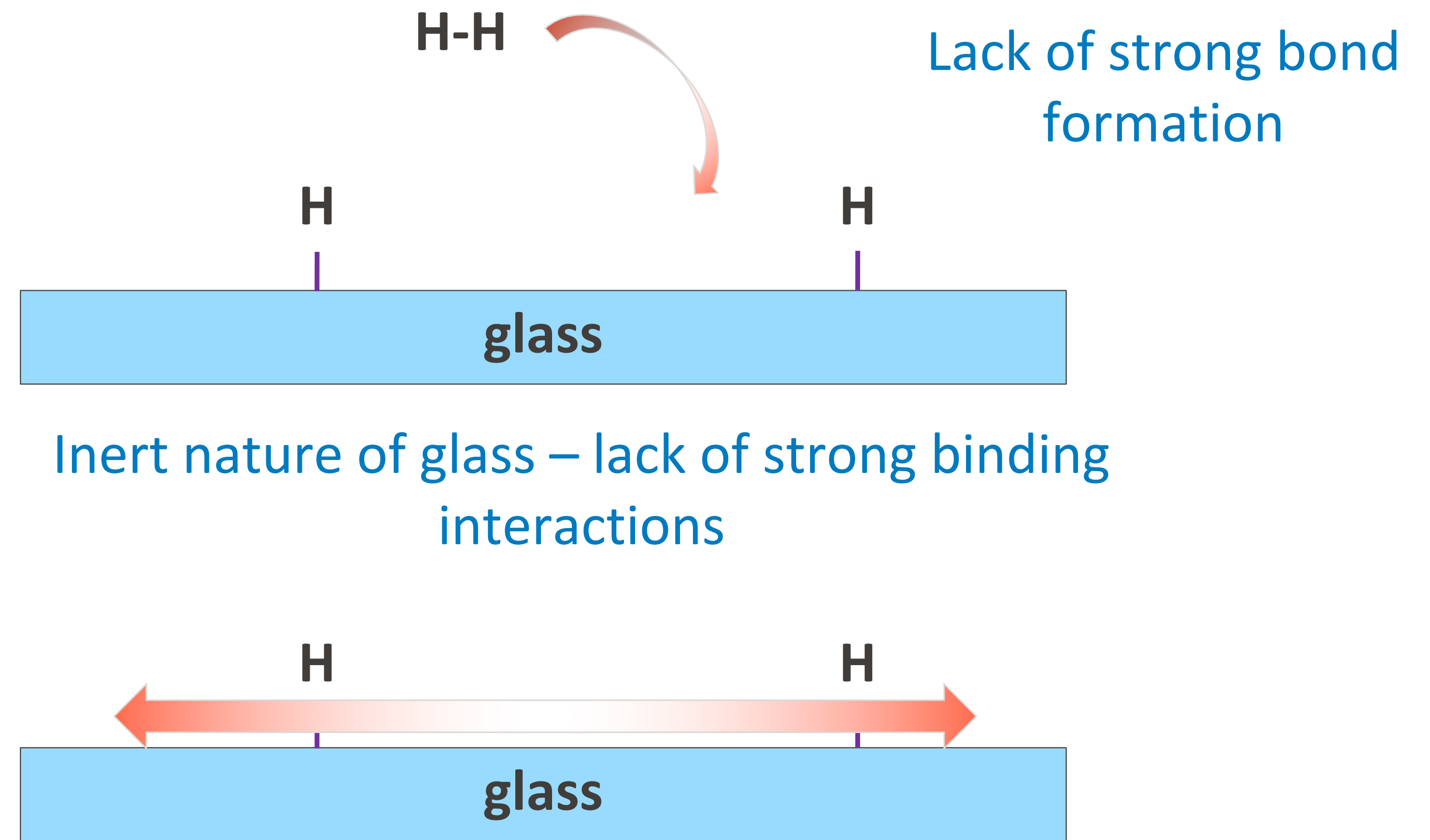
Spontaneous process:  $\Delta G < 0$

Endothermic reaction:  $\Delta H > 0$



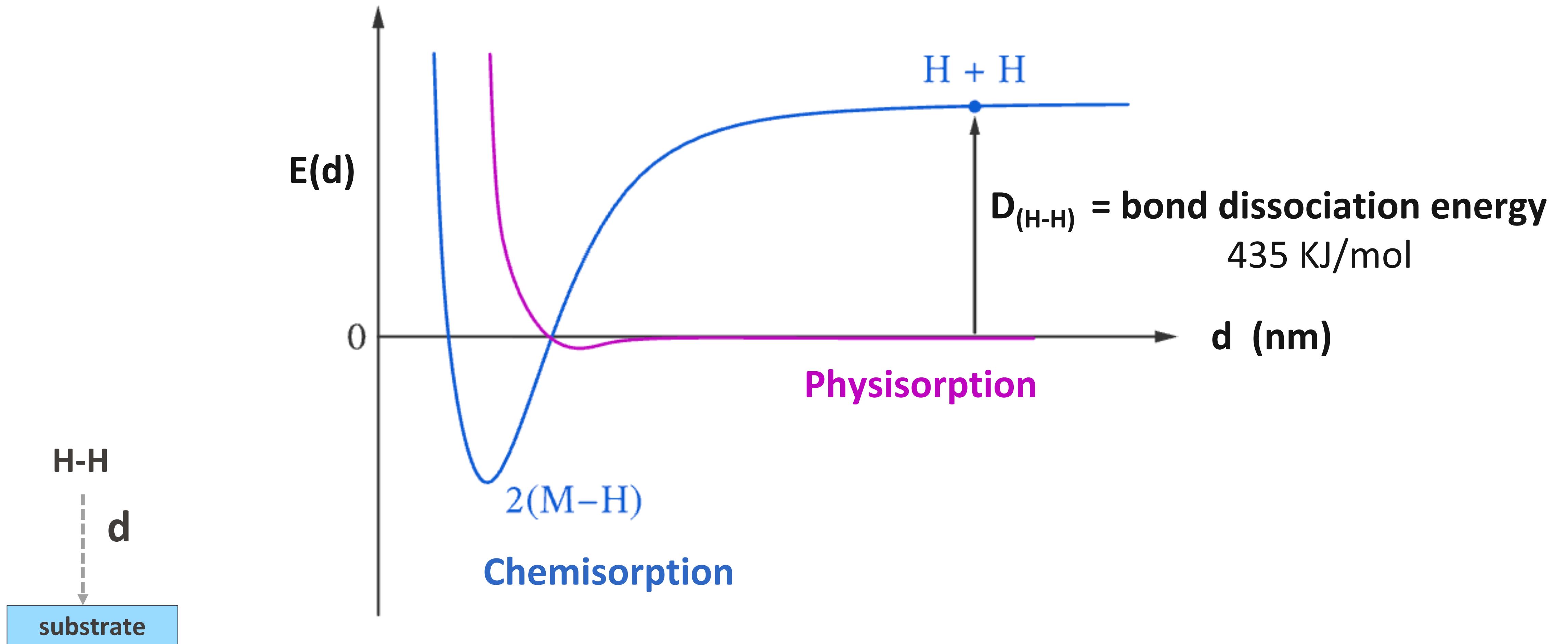
$$\Delta G = \Delta H - T\Delta S \rightarrow -$$

$\Delta S > 0$  meaning that entropy *increases*



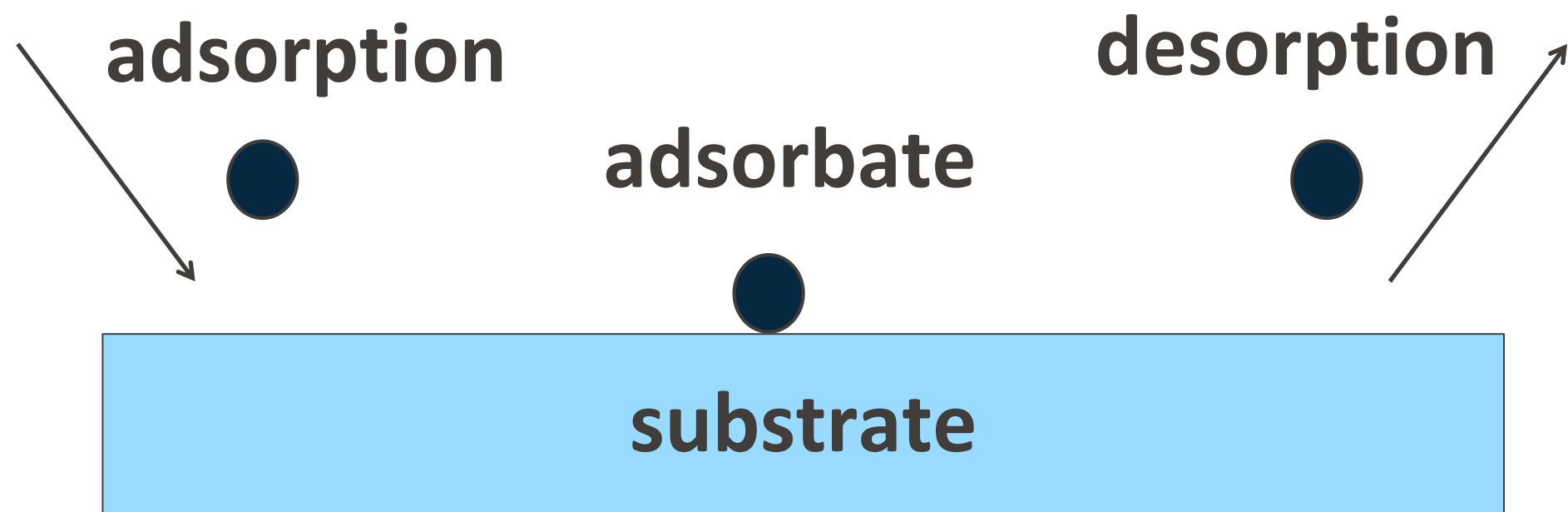
Adsorbed H diffuses readily on glass and therefore the two diffusing atoms have more degrees of freedom than the gas-phase diatomic molecule

# The Different Paths For H<sub>2</sub> Adsorption to the Surface



This concept is important for how catalysis works in a future lesson

# Desorption from the Surface



Breaking of chemical bonds and removal of adsorbed species from the surface

Molecule requires sufficient energy to activate the desorption ( $E_d$ )

Desorption is temperature dependent and is described by:

$$-\frac{dN_i}{dt} = \nu_i N_i^m \cdot \exp\left(\frac{-E_{d,i}}{RT}\right)$$

Polanyi-Wigner equation

$N_i$ : surface concentration of the adsorbate

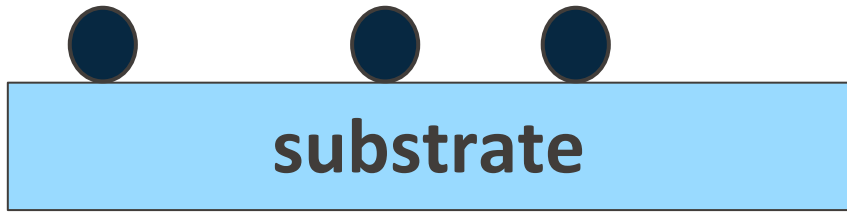
$\nu_i$ : frequency factor

$E_{di}$ : desorption activation energy

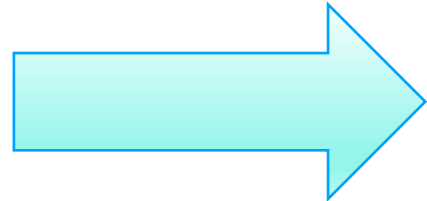
$m$ : order of the desorption reaction

# Ordered Adsorbate Layers

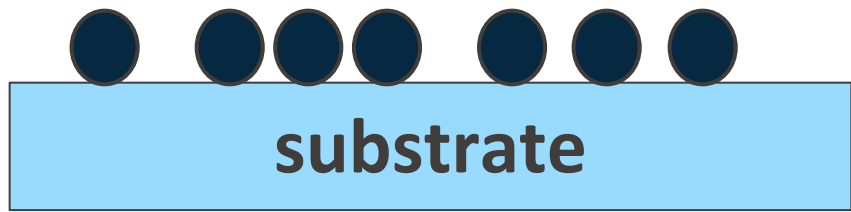
Small 2-D islands possibly ordered or completely disordered layers



Low surface coverage



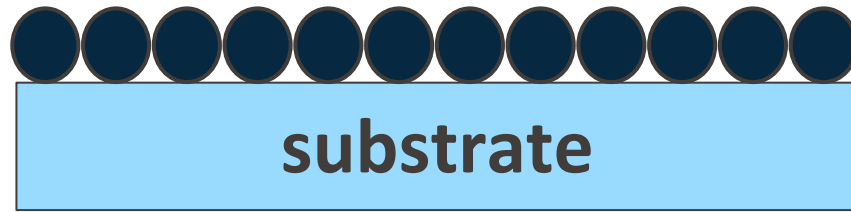
Crowding and interactions



Medium surface coverage  
(5-10 Å between atoms)

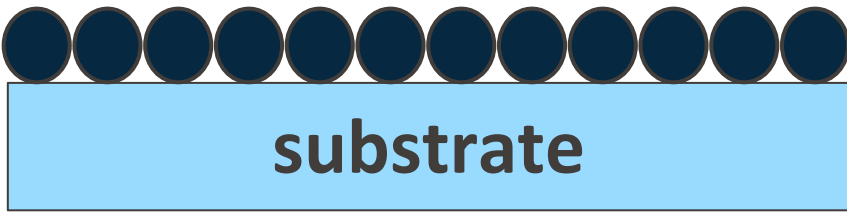
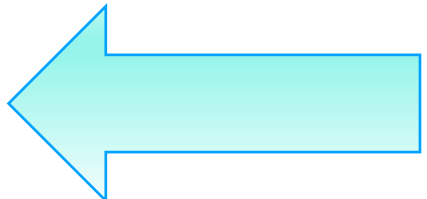


Adsorbate-substrate  
Adsorbate-adsorbate

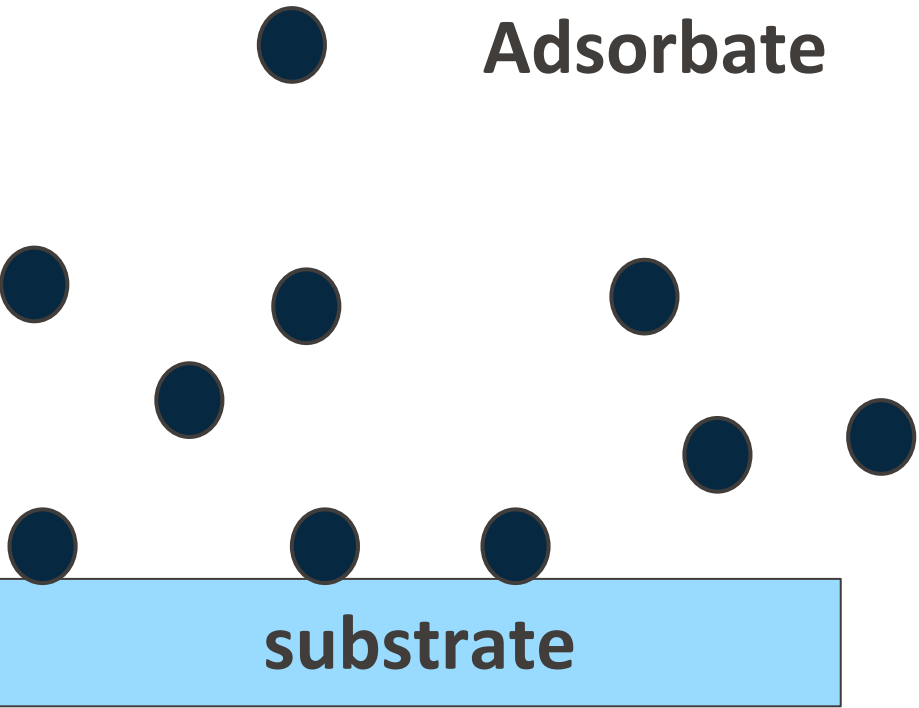


High surface coverage  
Arranged to minimize energy

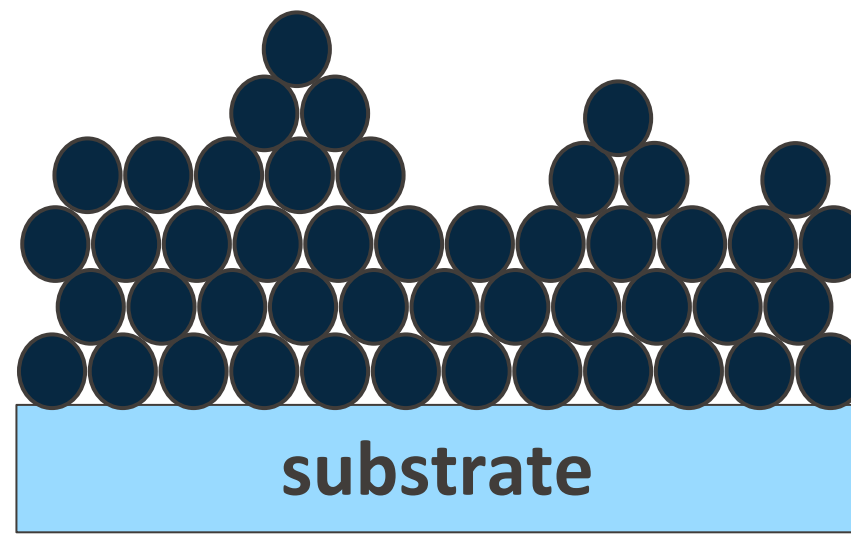
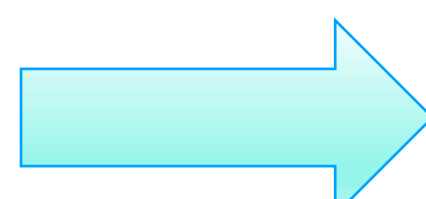
Monolayer adsorption



Adsorbate



Multilayer adsorption



Crystal structure of the surface dictates where molecules adsorb

# Key Takeaways

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Contamination comes from air, humidity, residues, dust, handling, etc.

Adsorption = surface, Absorption = bulk

Physisorption = weak and reversible, Chemisorption = strong and permanent

Adsorbates are arranged on surfaces to minimize surface energy

How are adsorbates arranged on surfaces?

# Solid Surfaces: Short Recap of Lattice Structures

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## Amorphous solids



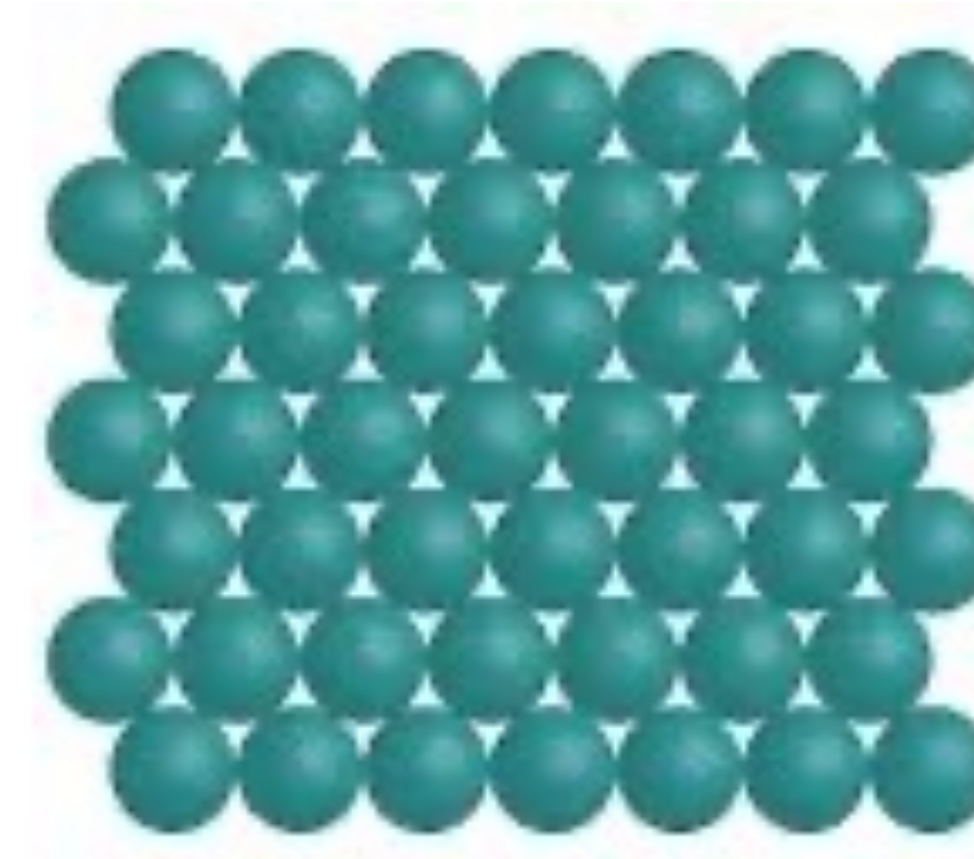
Random arrangement

No definite shape, can be molded

Softens over range of temperatures

Glass, plastic, gels

## Crystalline solids



Regular repeating lattice

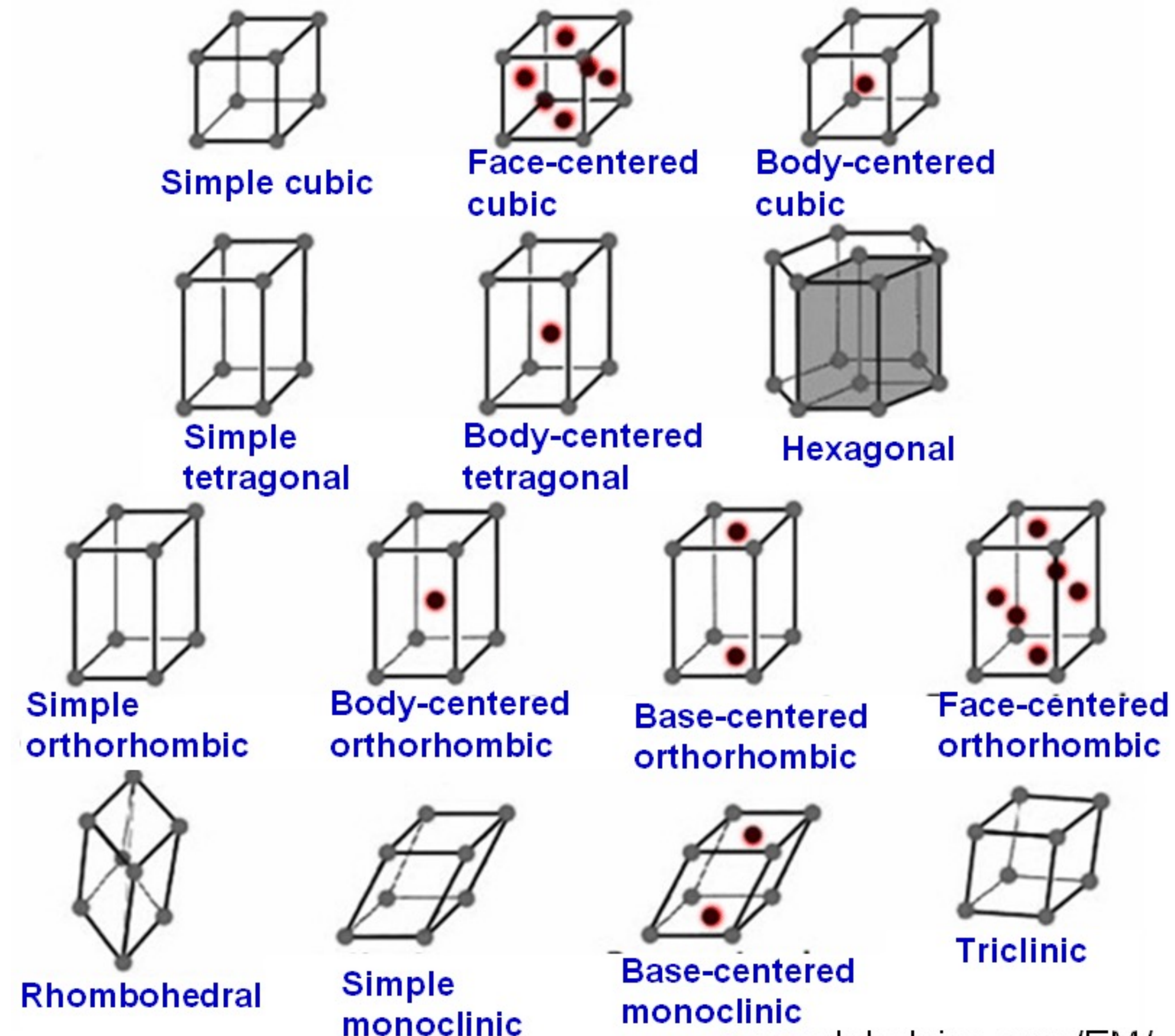
Definite geometric shape

Sharp, well-defined melting point

Salt, diamond, sugar

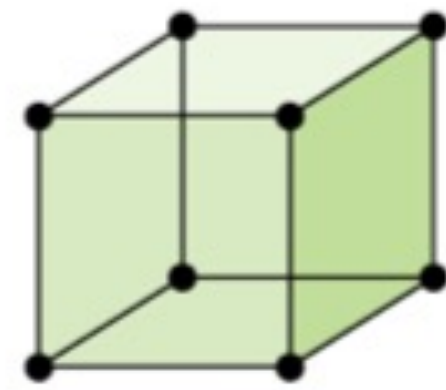
# The 14 Bravais Lattices for all 3-D Crystals

All 3-D crystals can be described by one of these lattices. What matters is remembering that a crystal is a periodic arrangement of atoms, and depending on how we slice it, you expose different planes

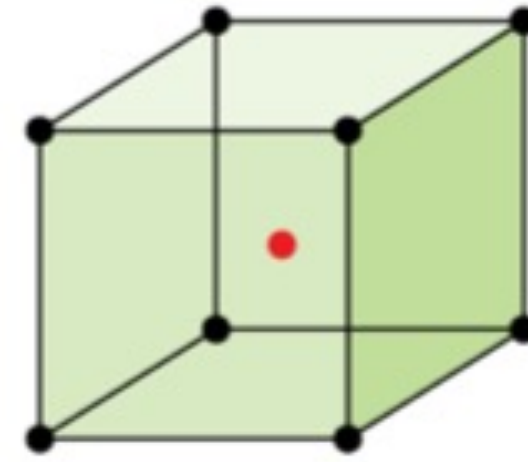


[www.globalsino.com/EM/](http://www.globalsino.com/EM/)

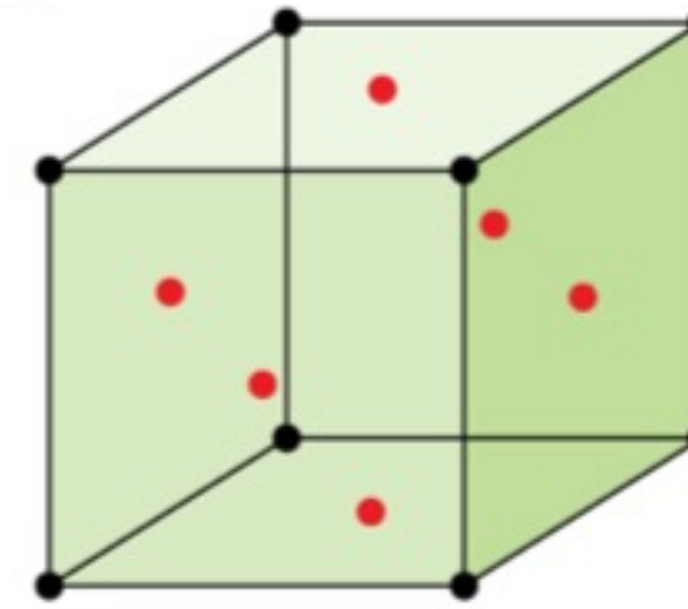
# Common Cubic Lattices for Surface Science



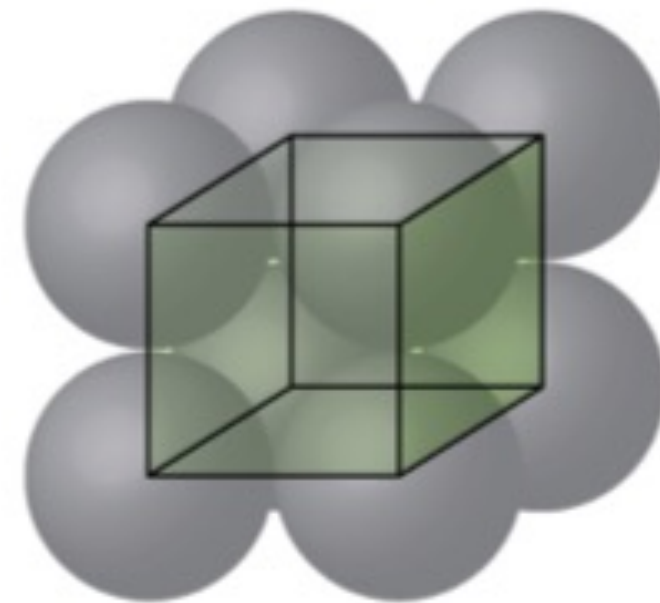
Simple  
cubic



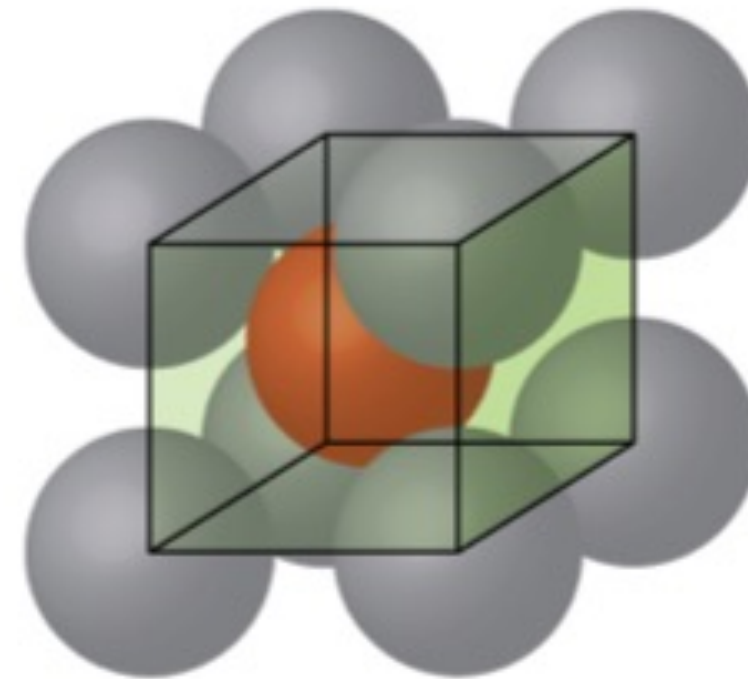
Body-centered cubic  
(bcc)



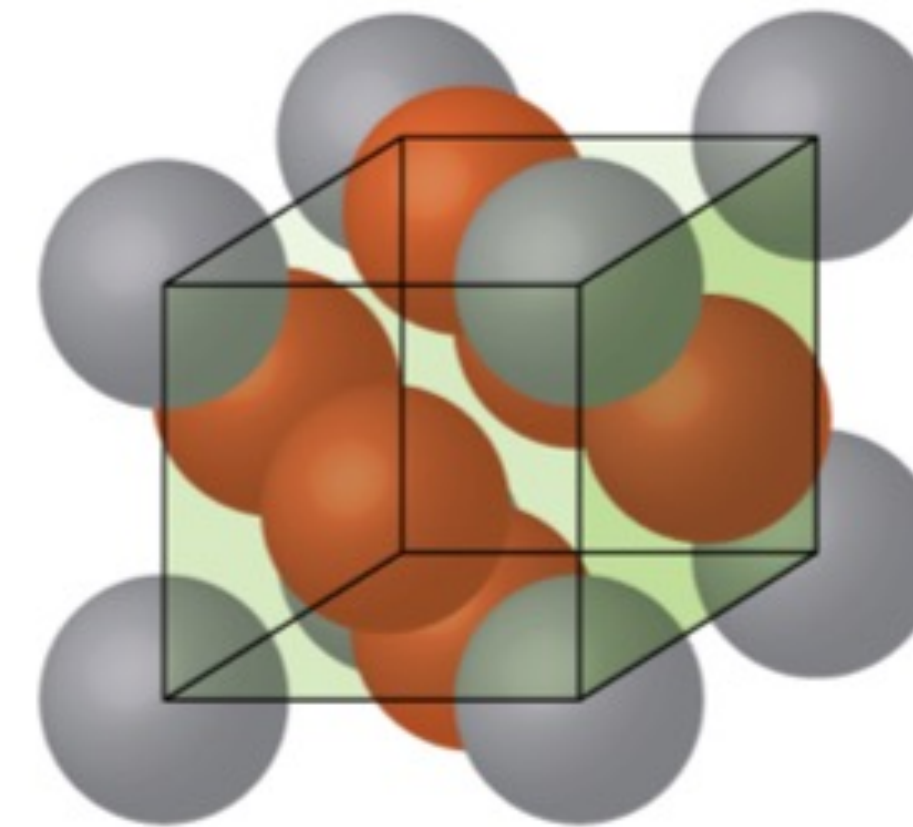
Face-centered cubic  
(fcc)



Polonium  
(rare in Nature)



Iron, Tungsten  
Chromium,  
Molybdenum



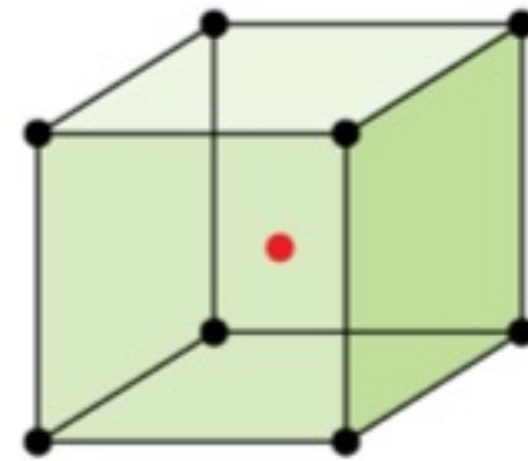
Copper, Nickel  
Aluminum, Platinum  
Gold, Lead

# Close-Packed Structures: Role in Adsorption/Absorption

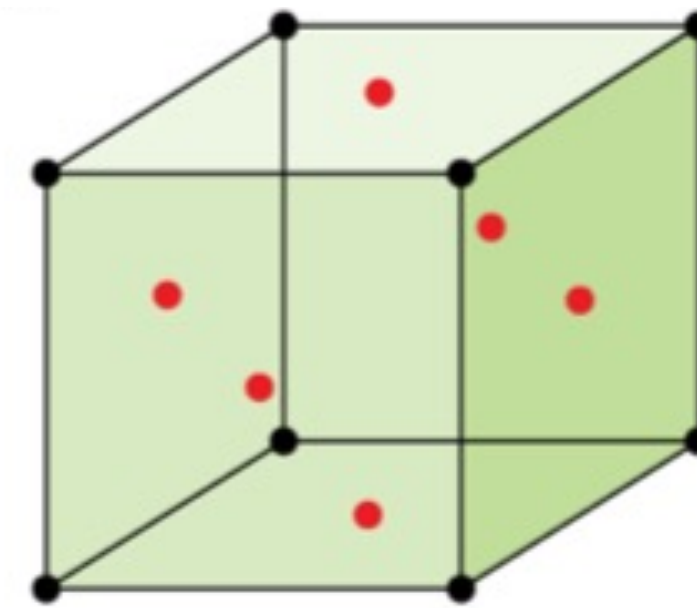
Structures where atoms are packed as closely as possible and minimizing empty space

$$\text{Packing efficiency} = \frac{\text{Volume occupied by atoms}}{\text{Volume of unit cell}} \times 100$$

68%

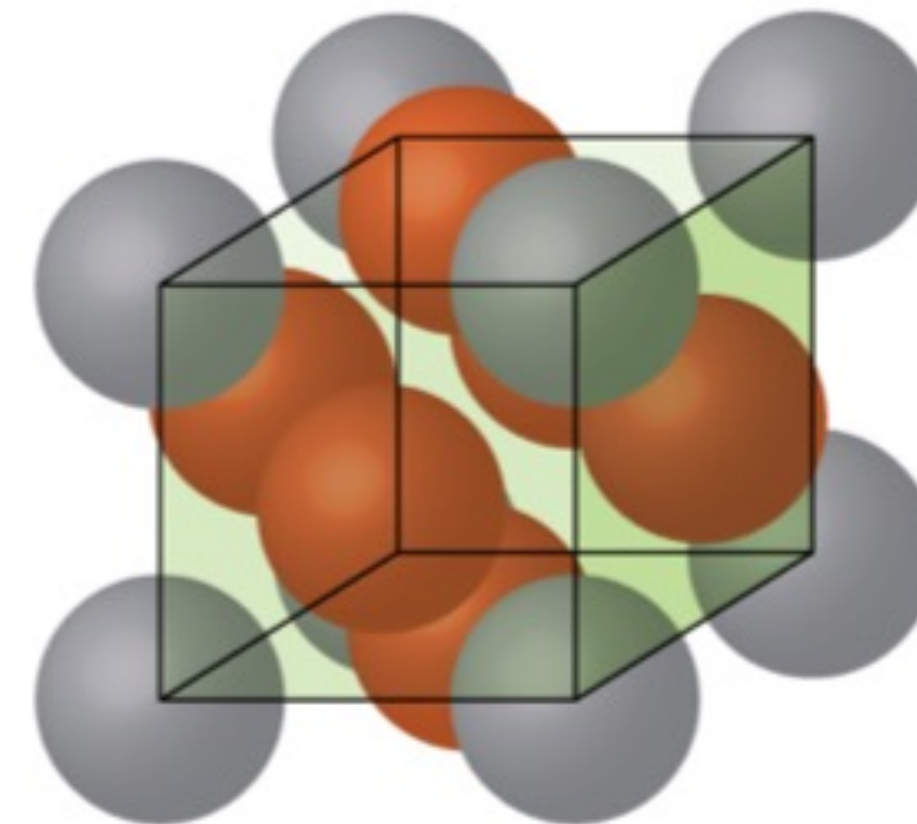
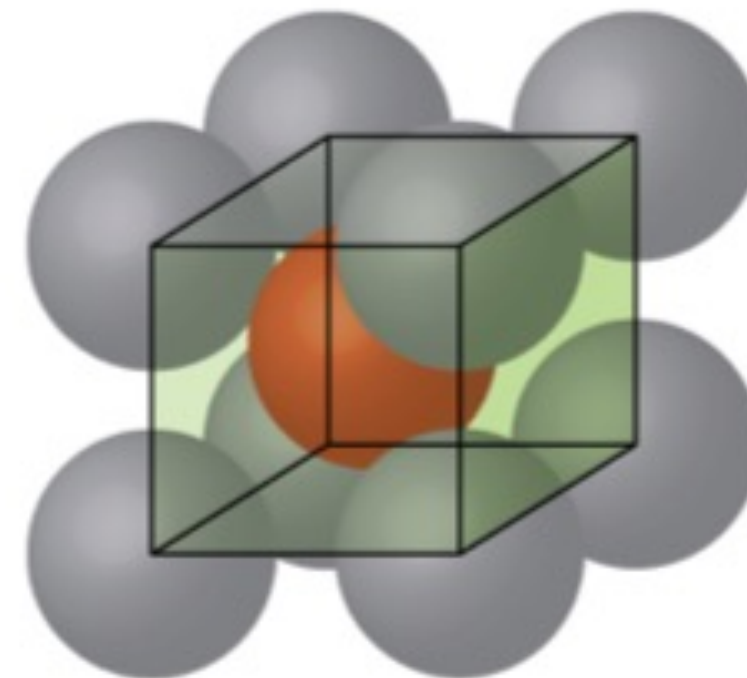


Body-centered cubic  
(bcc)



74%

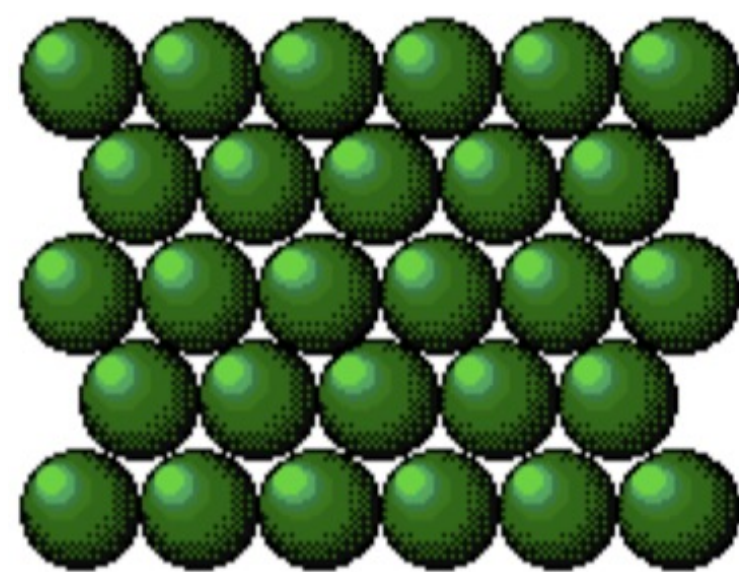
Face-centered cubic  
(fcc)



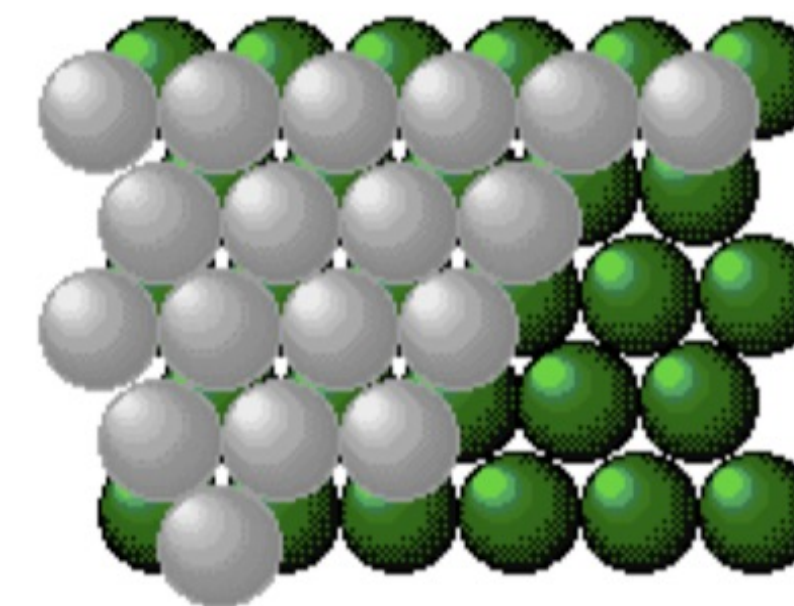
# Close-Packed Structures: Role in Adsorption/Absorption

Structures where atoms are packed as closely as possible and minimizing empty space

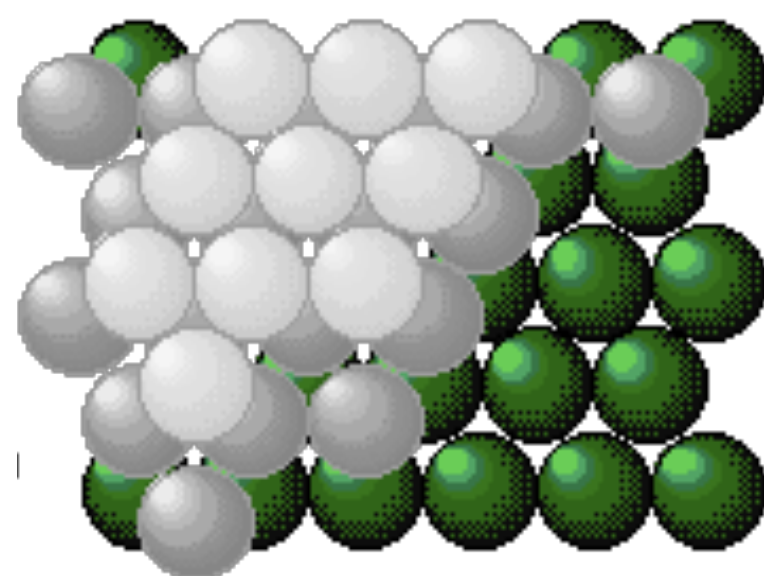
**1st layer: close packed atoms**



**2nd layer: atoms are situated over gaps in the 1st layer**



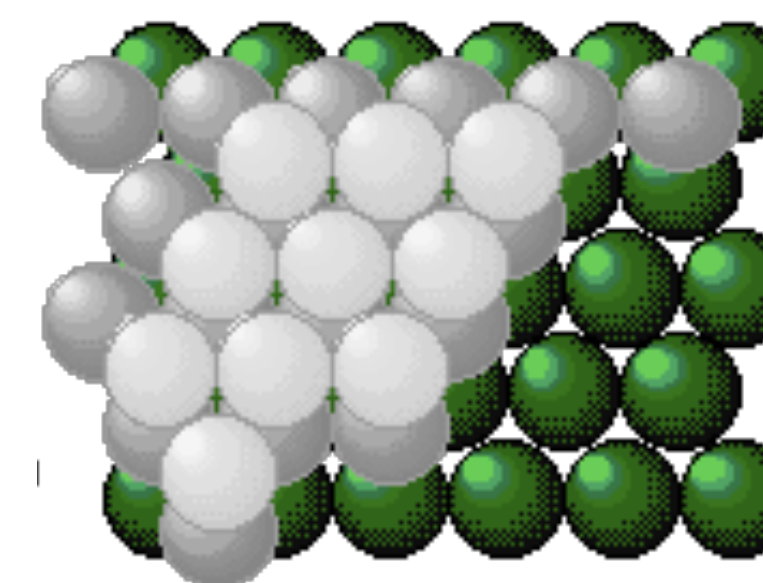
**3rd layer: atoms are situated over the gaps in the 2nd layer**



and over the atoms of the first layer

**Hexagonal close packed**

Two possibilities:

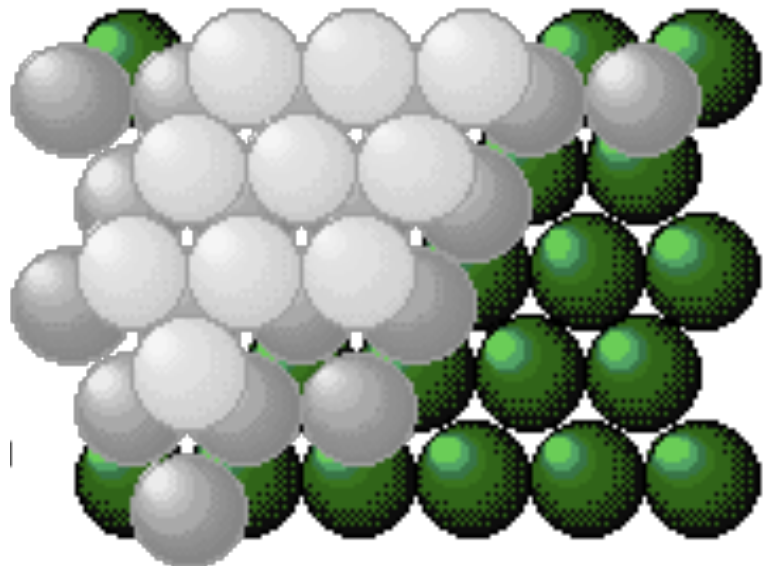


Over the gaps in the first layer

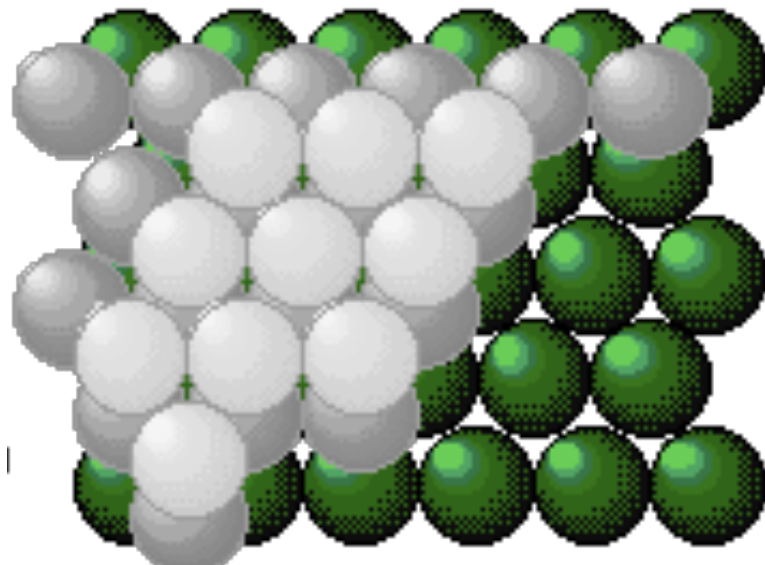
**Cubic close packed**

# Close-Packed Structures: Role in Adsorption/Absorption

The packing efficiency influences both surface interactions (adsorption) and bulk interactions (absorption)

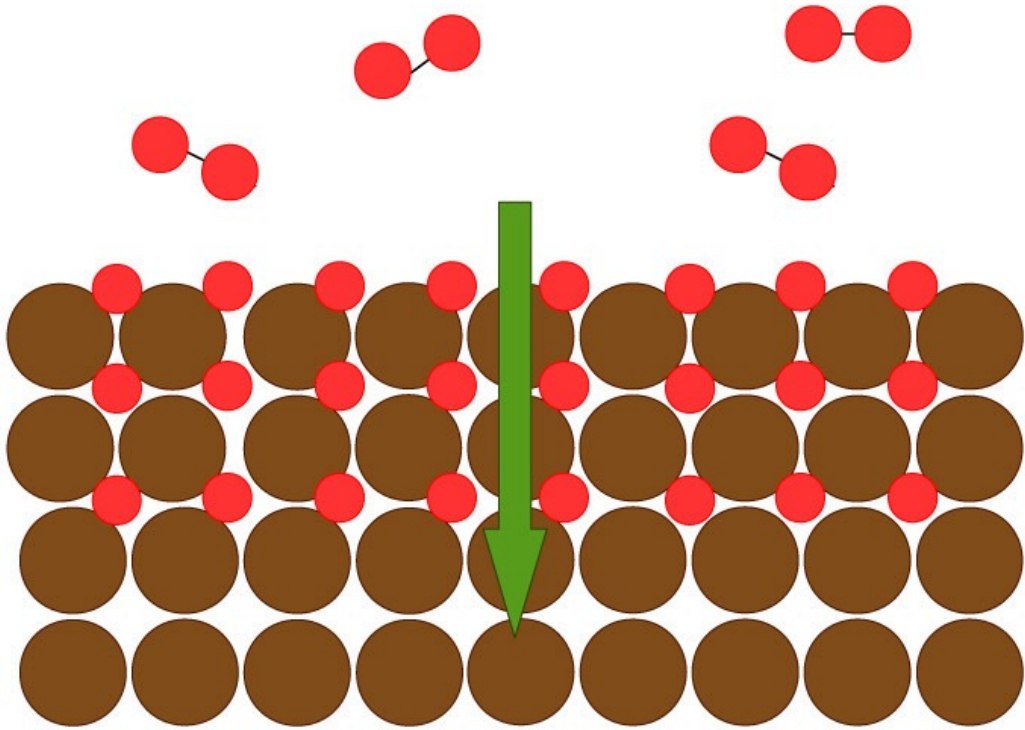


and over the atoms of the first layer  
**Hexagonal close packed**

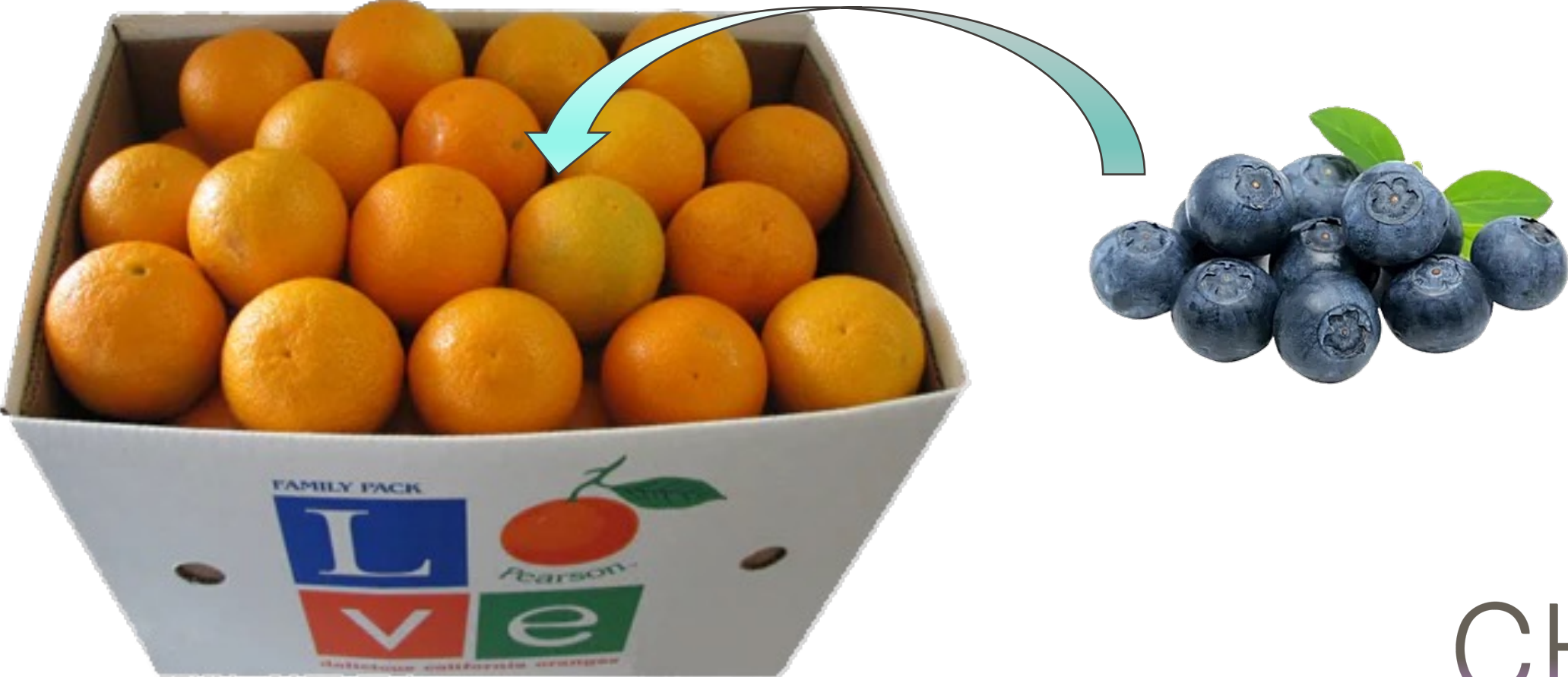


Over the gaps in the first layer  
**Cubic close packed**

Interstitial sites (gaps between atoms in crystal lattices) define absorption pathways



Gattinoni & Michaelides | *Surf. Sci. Rep.* | 2015



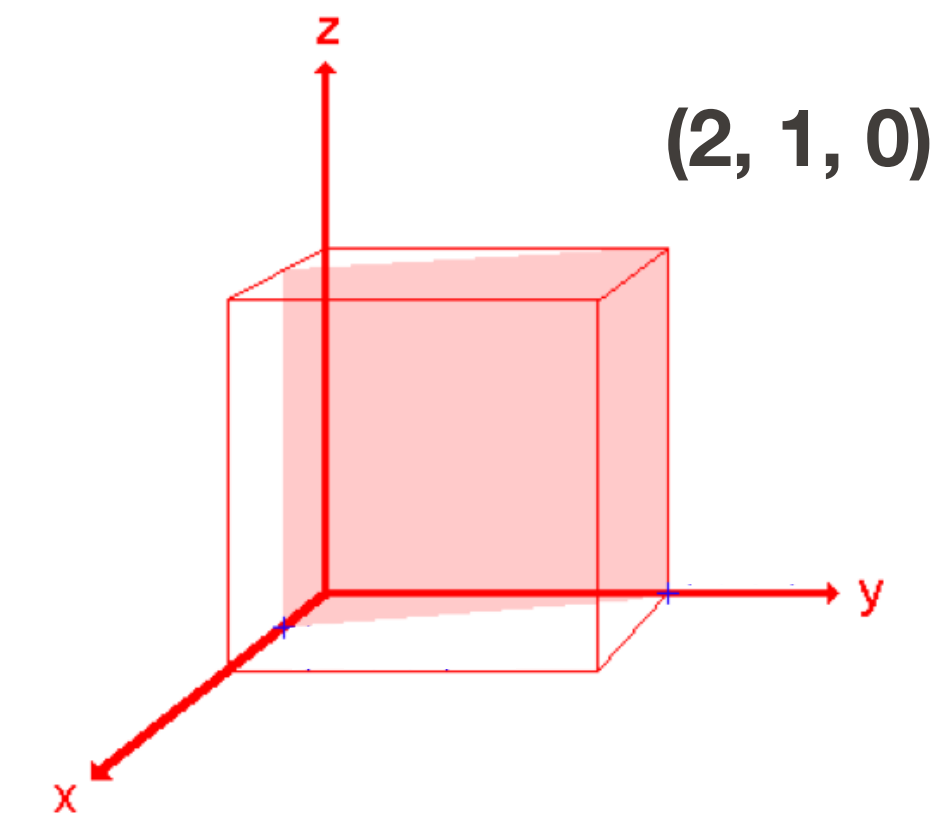
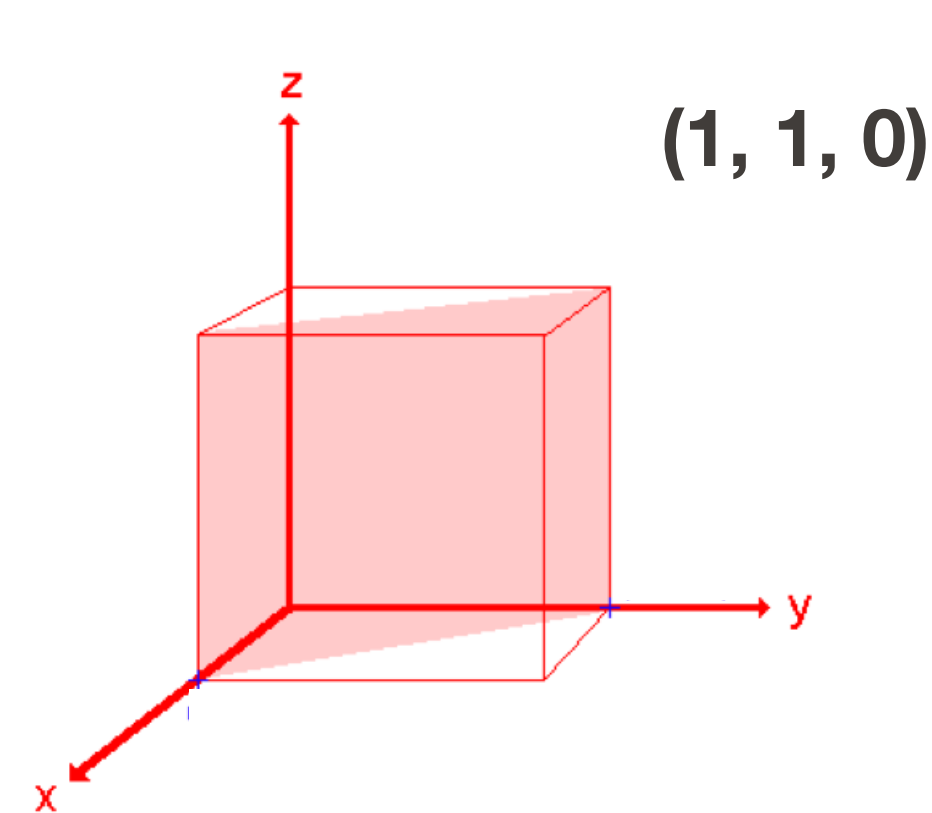
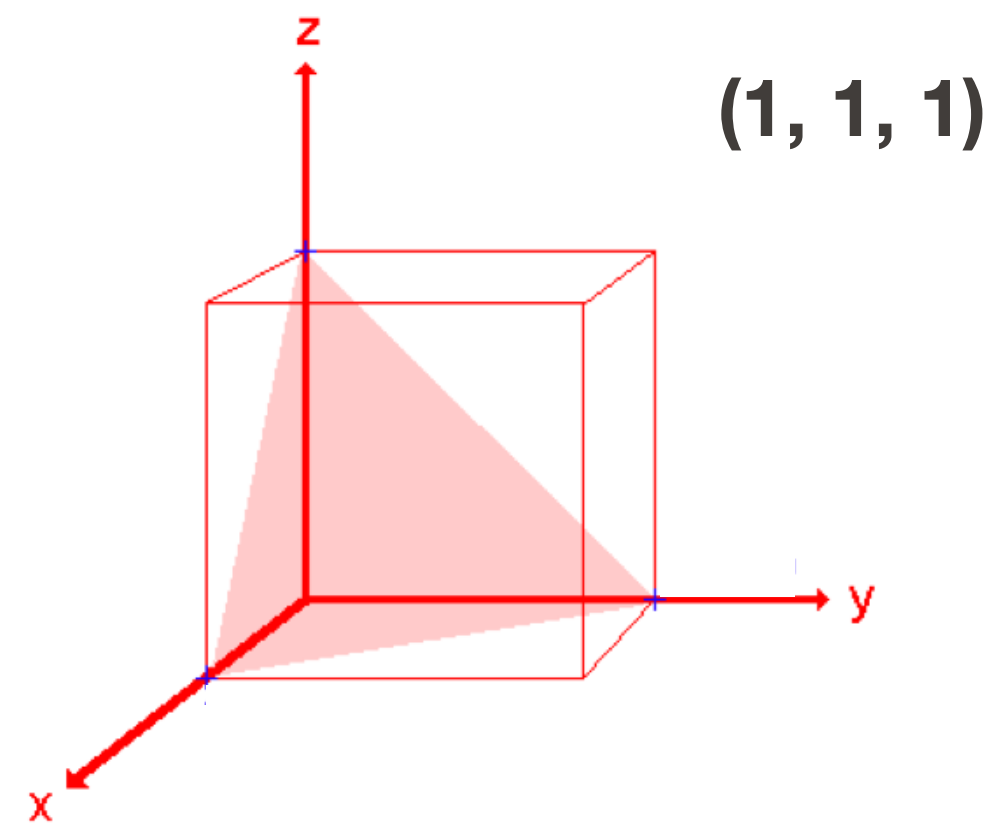
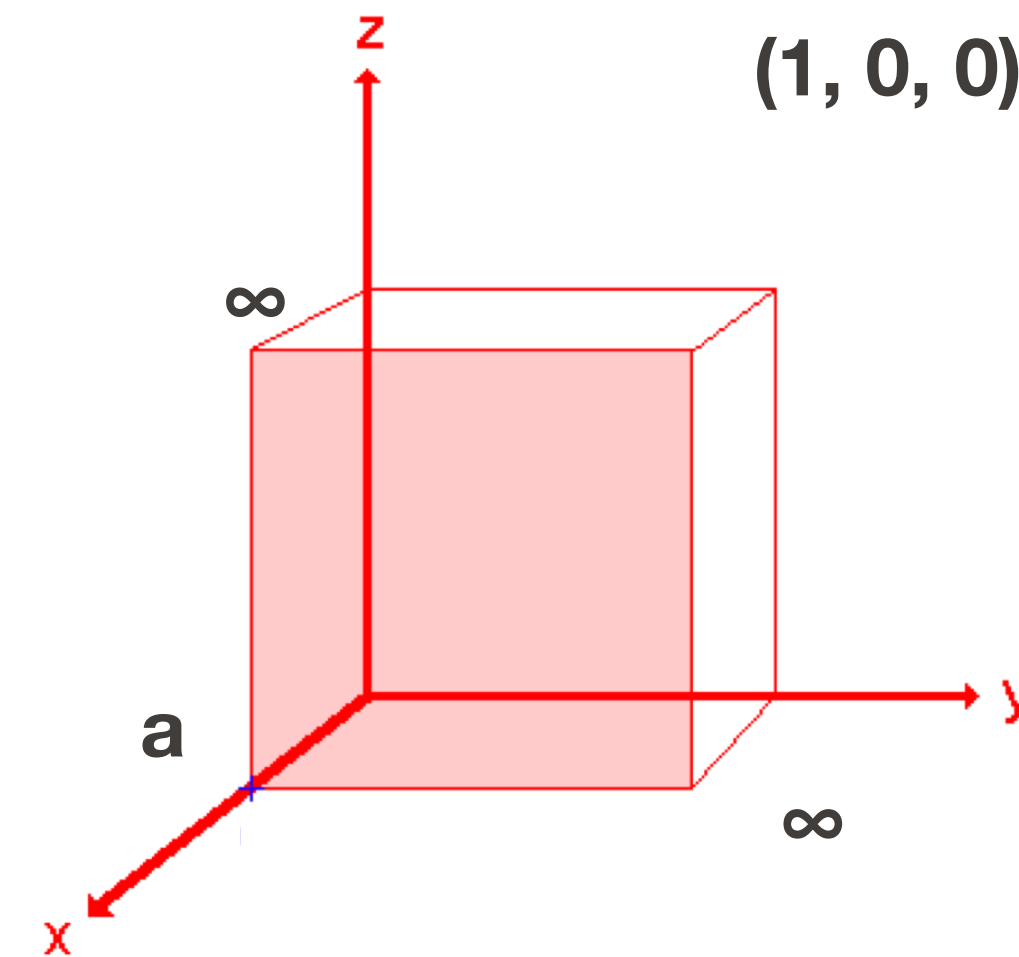
# Miller Indices to Describe Crystal Planes

1. Identify where planes intersect the three axes

2. Take reciprocals of these locations in terms of lattice parameters  $a$ ,  $b$ ,  $c$ . If no intersection (parallel) then intersect is infinity (reciprocal is 0)

3. Use smallest whole numbers (1, 0, 0)

4. Put integers into parentheses to get Miller indices



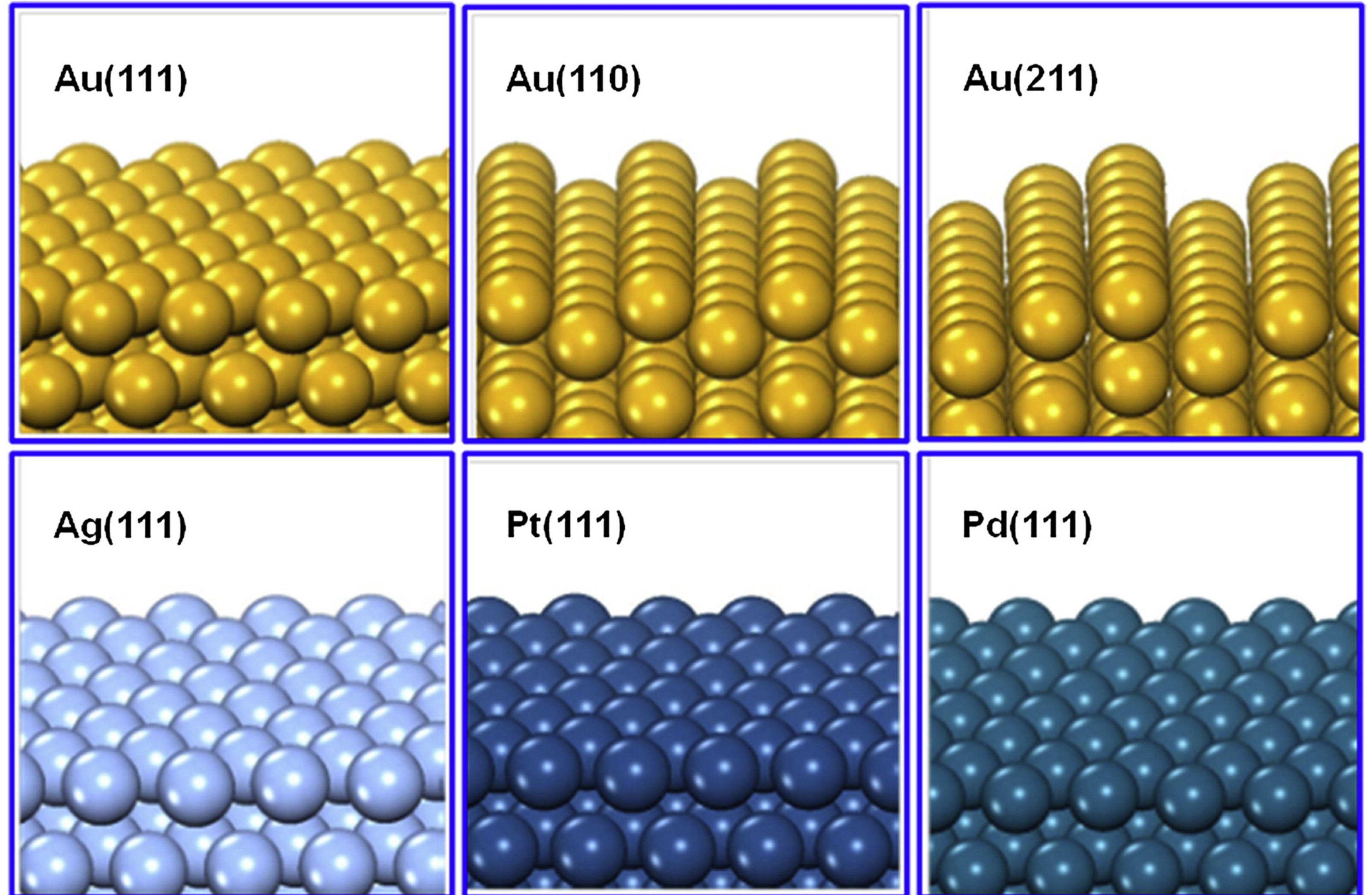
# Atomic Arrangements of Atoms on Different Planes

Miller indices describe crystallographic planes in crystalline material

Each orientation represents specific arrangement of atoms on the surface of the crystal lattice, with distinct geometric and chemical properties

Variations in:

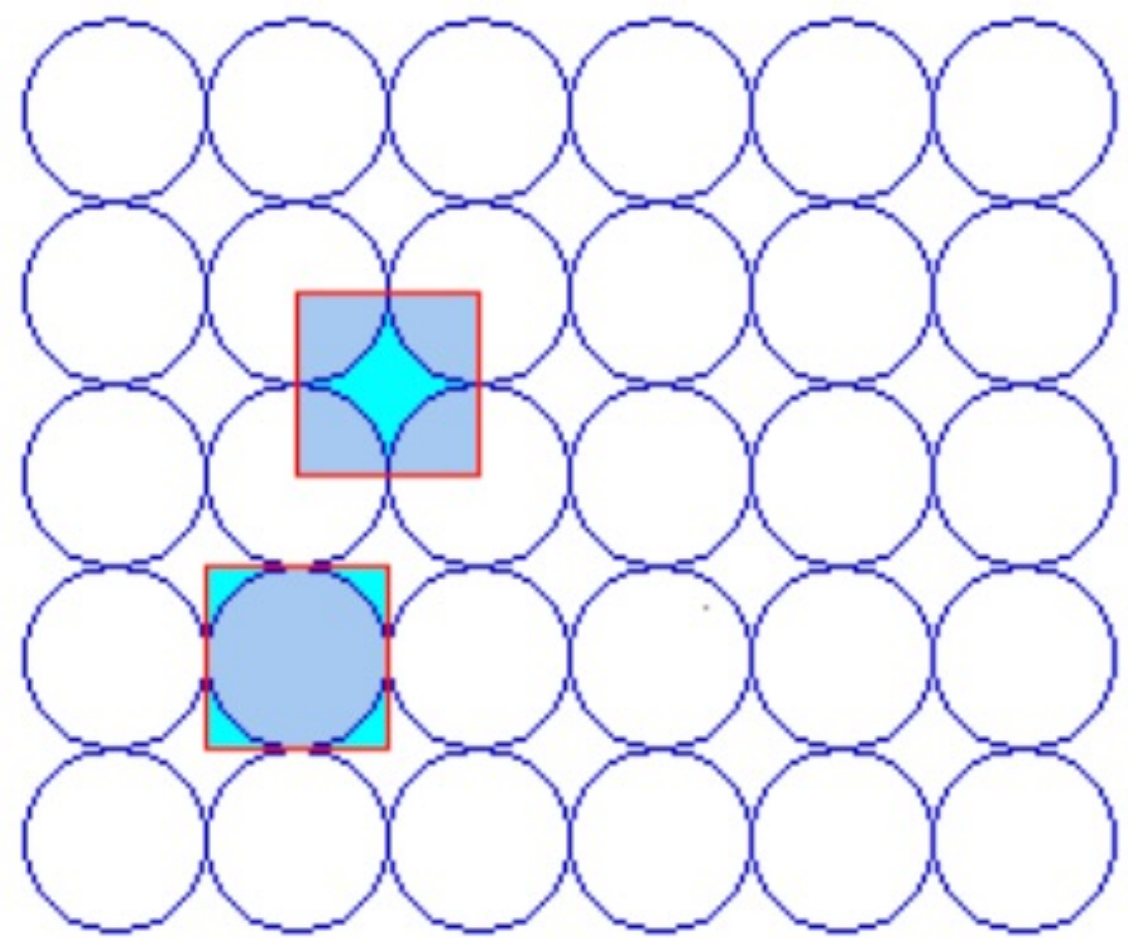
- Atomic density
- Surface energy
- Geometry
- Stability



Li et al., | Biomaterials | 2023

# Ordered Adsorbate Layers in Relation to Substrate's Elementary Cell

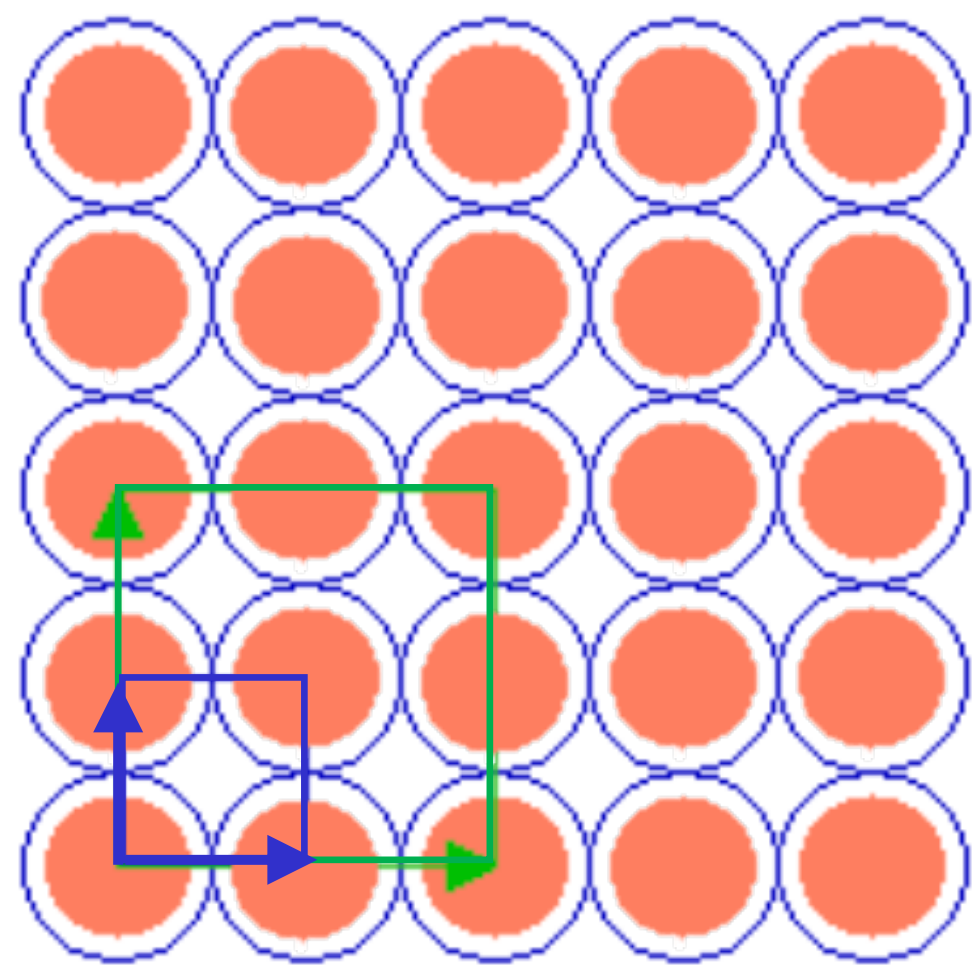
## fcc(100) lattice



Two possible choices of unit cell

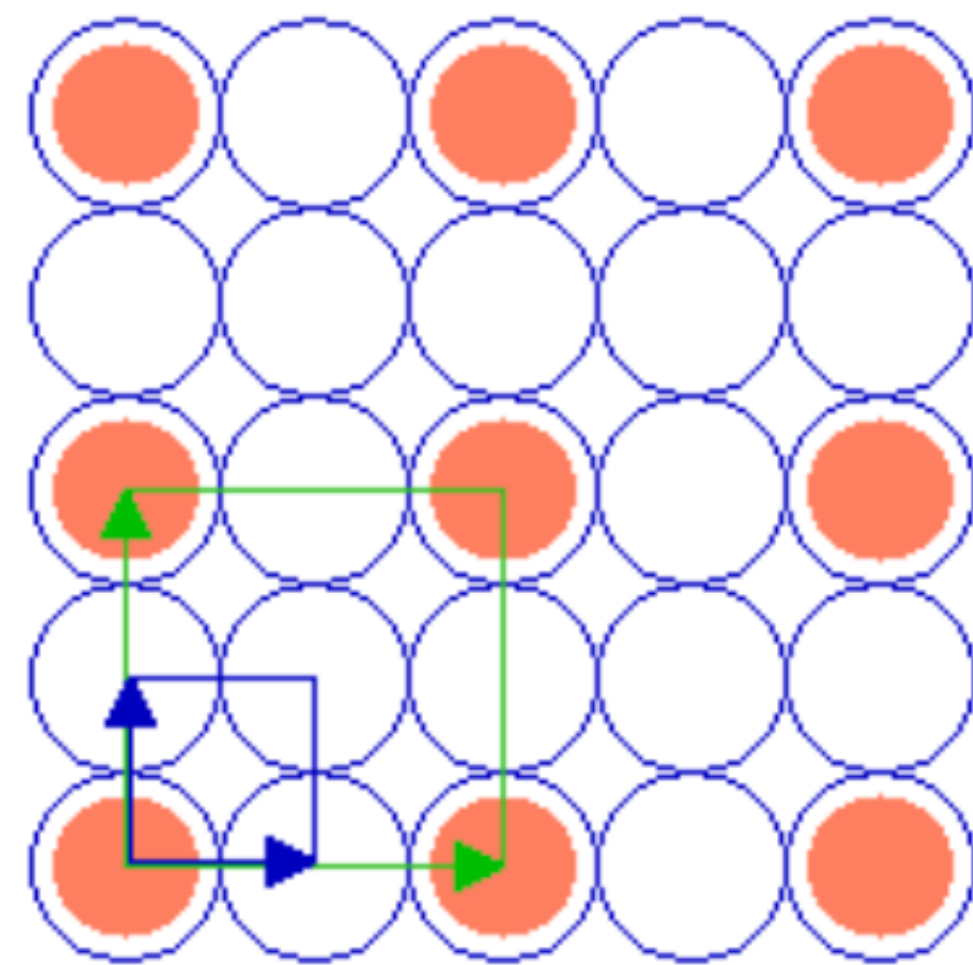
Substrate provides periodic grid of atoms

## Adsorbates



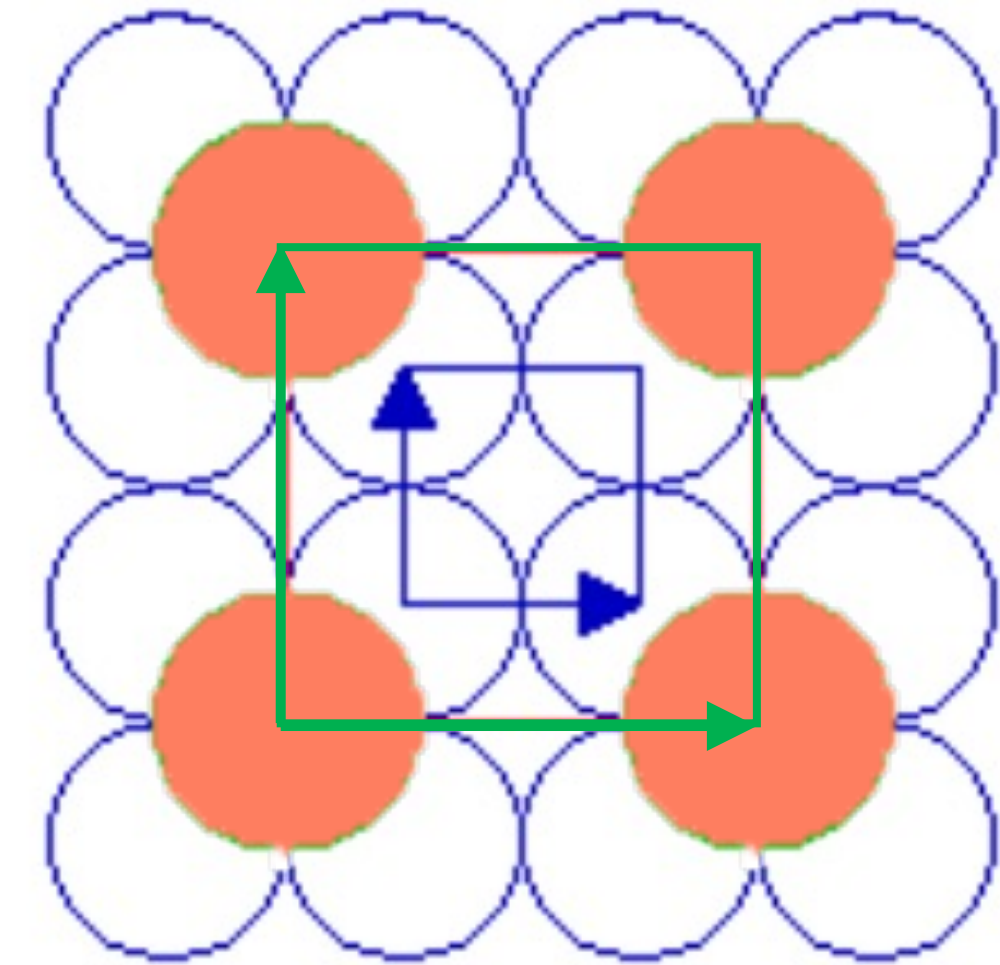
(1x1)  
 $\theta = 1$

coverage



(2x2)  
 $\theta = 1/4$

## Adsorbate unit cell Substrate unit cell

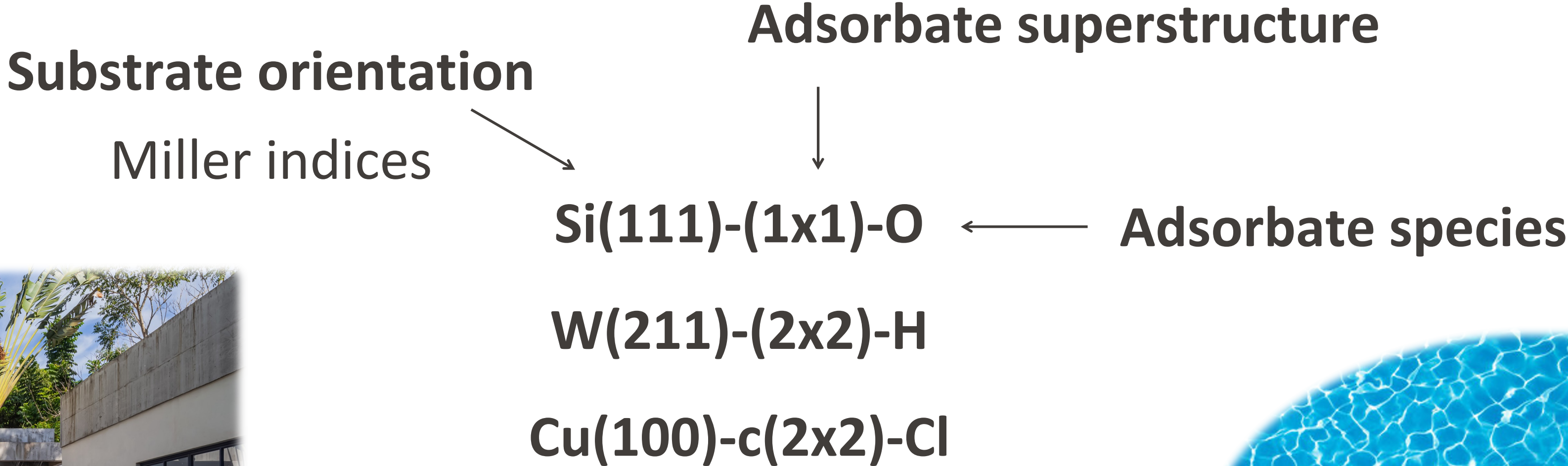


c(2x2)  
 $\theta = 1/2$

\*c = centered

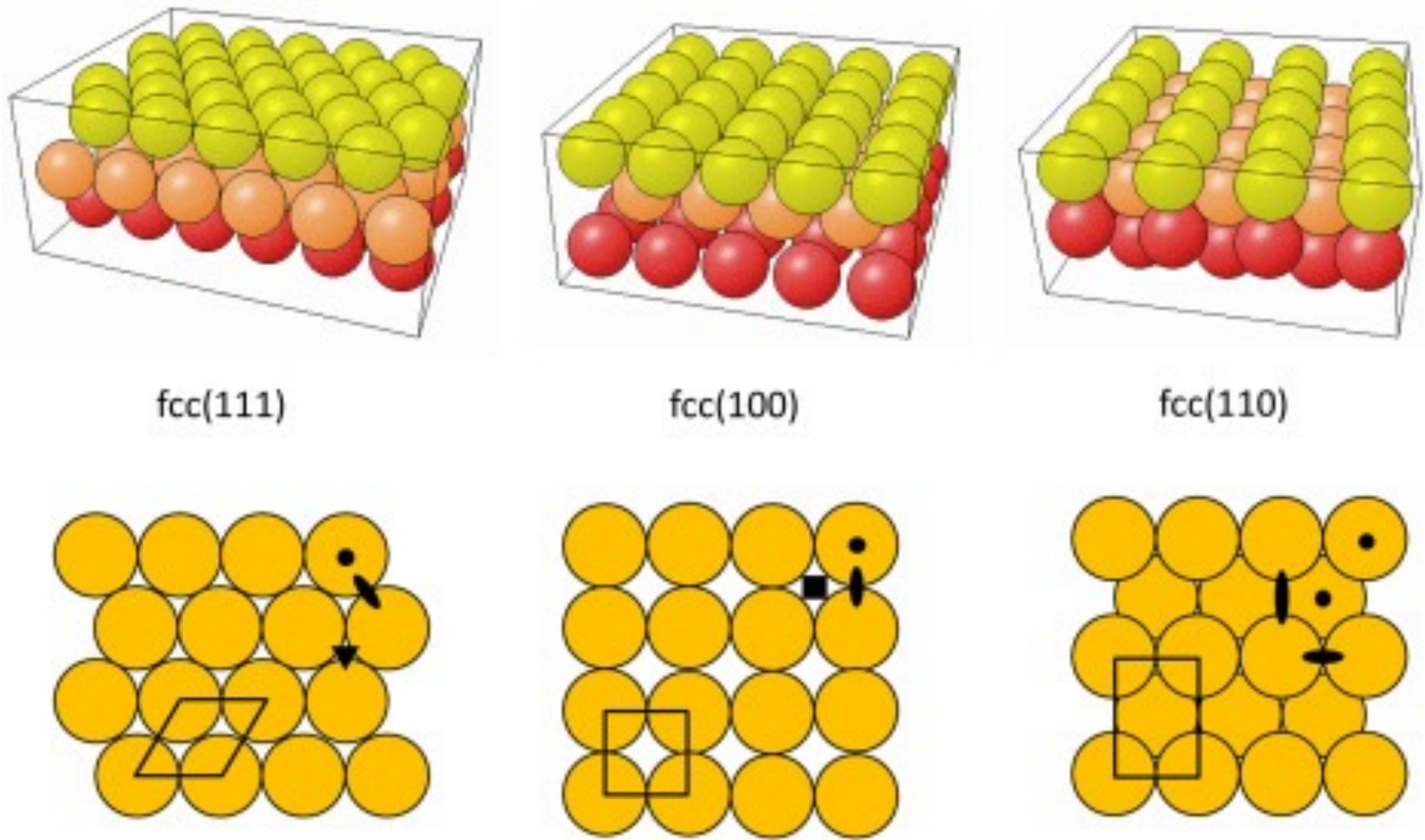
Adsorbates don't just stick randomly — they form ordered patterns based on substrate lattice

# How to Read Wood's Notation (Adsorbate Address)



# Face-Specific Behavior of Adsorption

Chloride ions adsorption on copper electrode surfaces

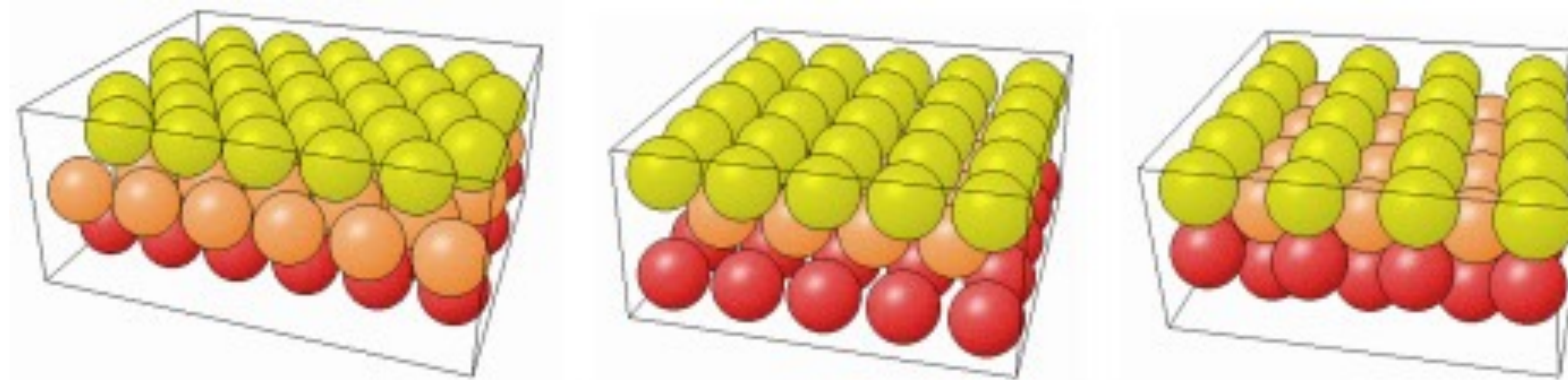


Wandelt | *Surf. Sci. Electrochem.* | 2018

Most symmetric adsorption sites are marked by the shapes

# Visualizing Face-Specific Structure of Surfaces

Chloride ions adsorption on copper electrode surfaces

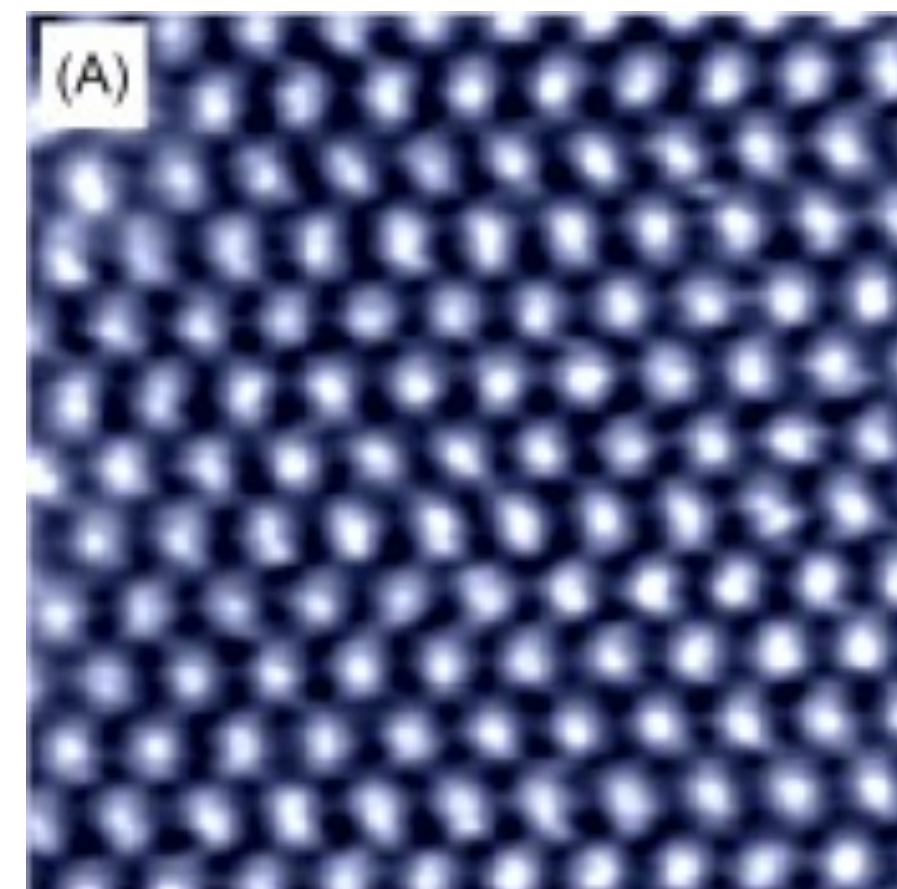


fcc(111)

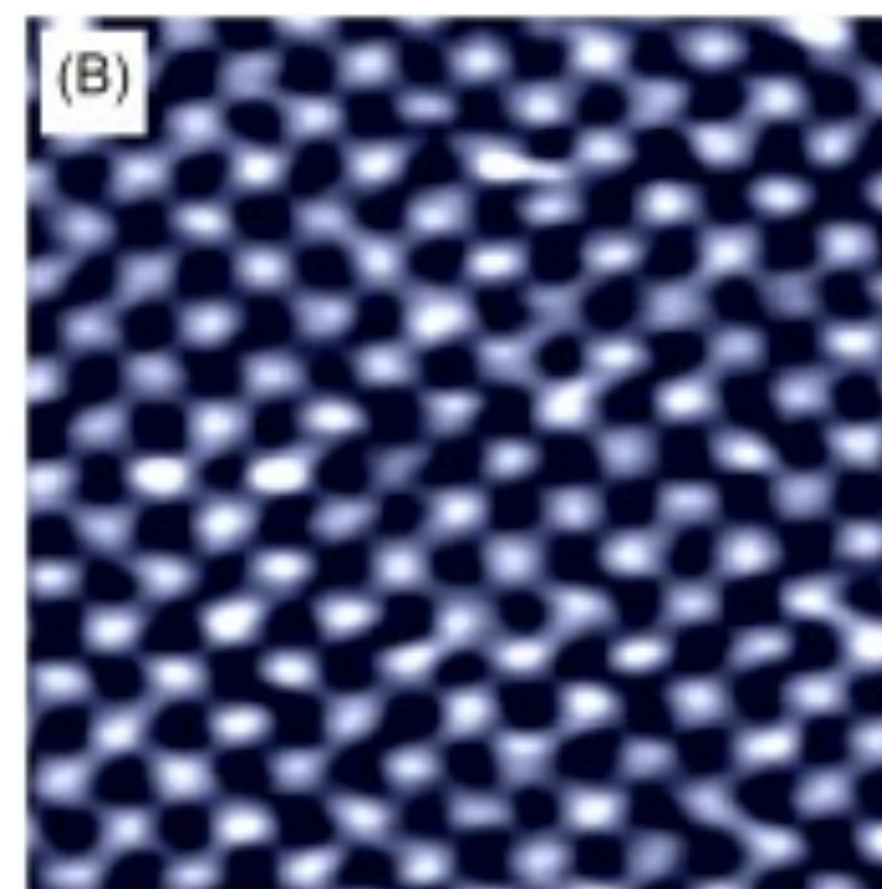
fcc(100)

fcc(110)

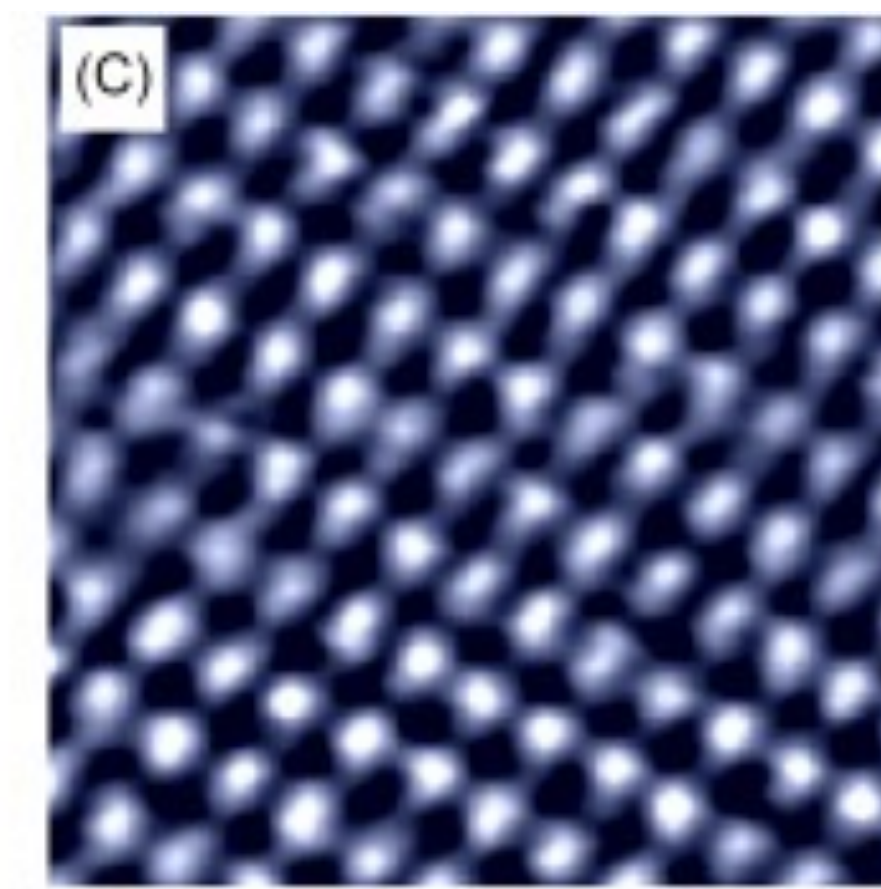
Scanning tunneling microscopy (STM) images of anion-free copper surfaces



Cu(111)



Cu(100)



Cu(110)

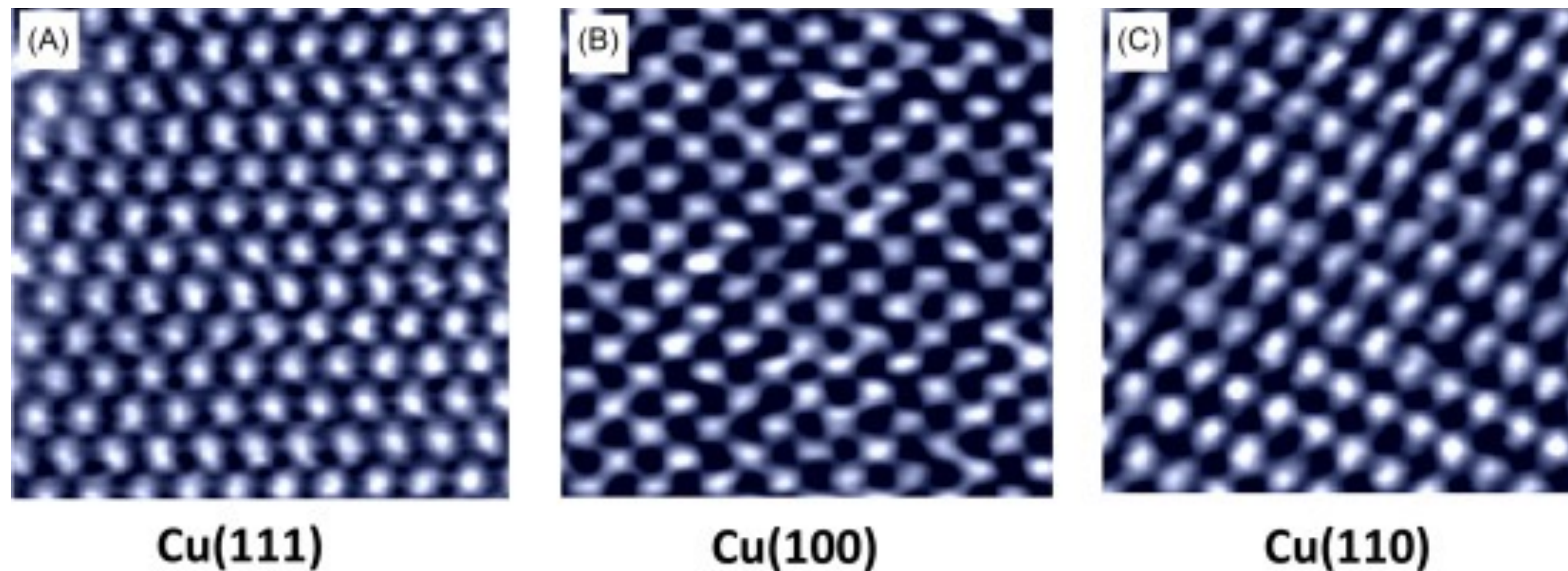
Scale:  
~ 3 x 3 nm

Wandelt | *Surf. Sci. Electrochem.* | 2018

# Extracting Face-Specific Parameters

	Cu(111)	Cu(100)	Cu(110)
<b>Lattice constants (nm)</b>	$\vec{a} = \vec{b} = 0.256; \alpha = 60^\circ$	$\vec{a} = \vec{b} = 0.256; \alpha = 90^\circ$	$a = 0.256, b = 0.362; \alpha = 90^\circ$
<b>Density (atoms/cm<sup>2</sup>)</b>	$1.767 \times 10^{15}$	$1.530 \times 10^{15}$	$1.082 \times 10^{15}$
<b>Coordination number</b>	9	8	7
<b>Missing neighbors</b>	3	4	5
<b>Interlayer spacing (nm)</b>	$d = 0.212$	$d = 0.181$	$d = 0.128$
<b>Workfunction (eV)</b>	4.94	4.59	4.48

Scanning tunneling  
microscopy (STM)  
images of anion-free  
copper surfaces



Scale:  
~ 3 x 3 nm

Wandelt | *Surf. Sci. Electrochem.* | 2018

# Key Takeaways

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Crystal lattice structures of surfaces defines how adsorbates stick

Packing of lattice structure influences adsorption/absorption

Adsorbates form ordered patterns on the substrate lattice (adsorbate address)

Depending on the cut of the crystal, adsorption behavior will change

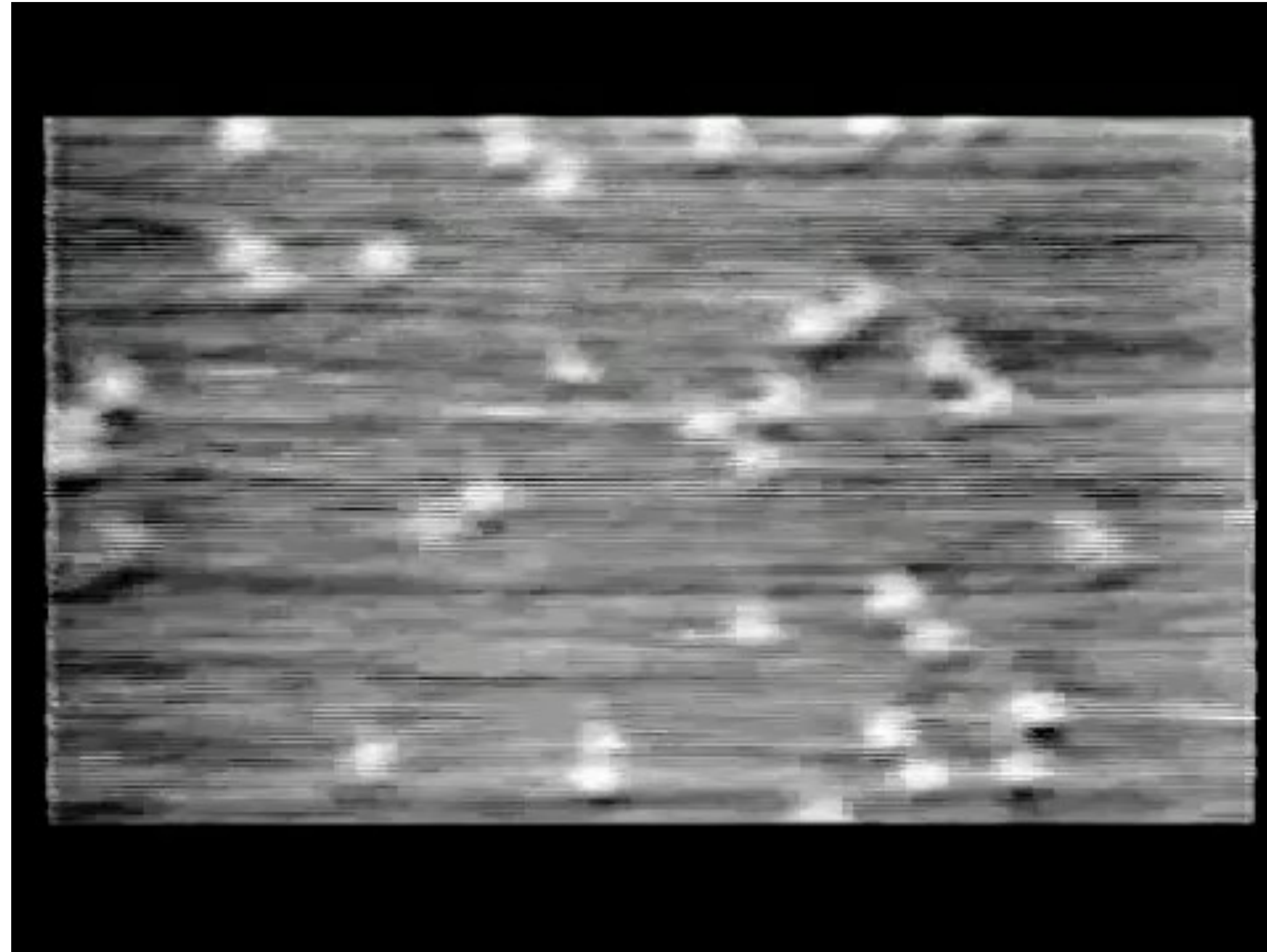
How can we characterize/visualize this phenomenon?

# Real-Time Observation of Oxygen on Ruthenium Surface

Scanning tunneling microscopy (STM) images the random walk of individual oxygen atoms on Ru at 300 K

$$\theta < 0.25$$

$\theta = 0.25$  corresponds to a complete, ordered (2x2) overlayer



Experiments conducted in a UHV chamber

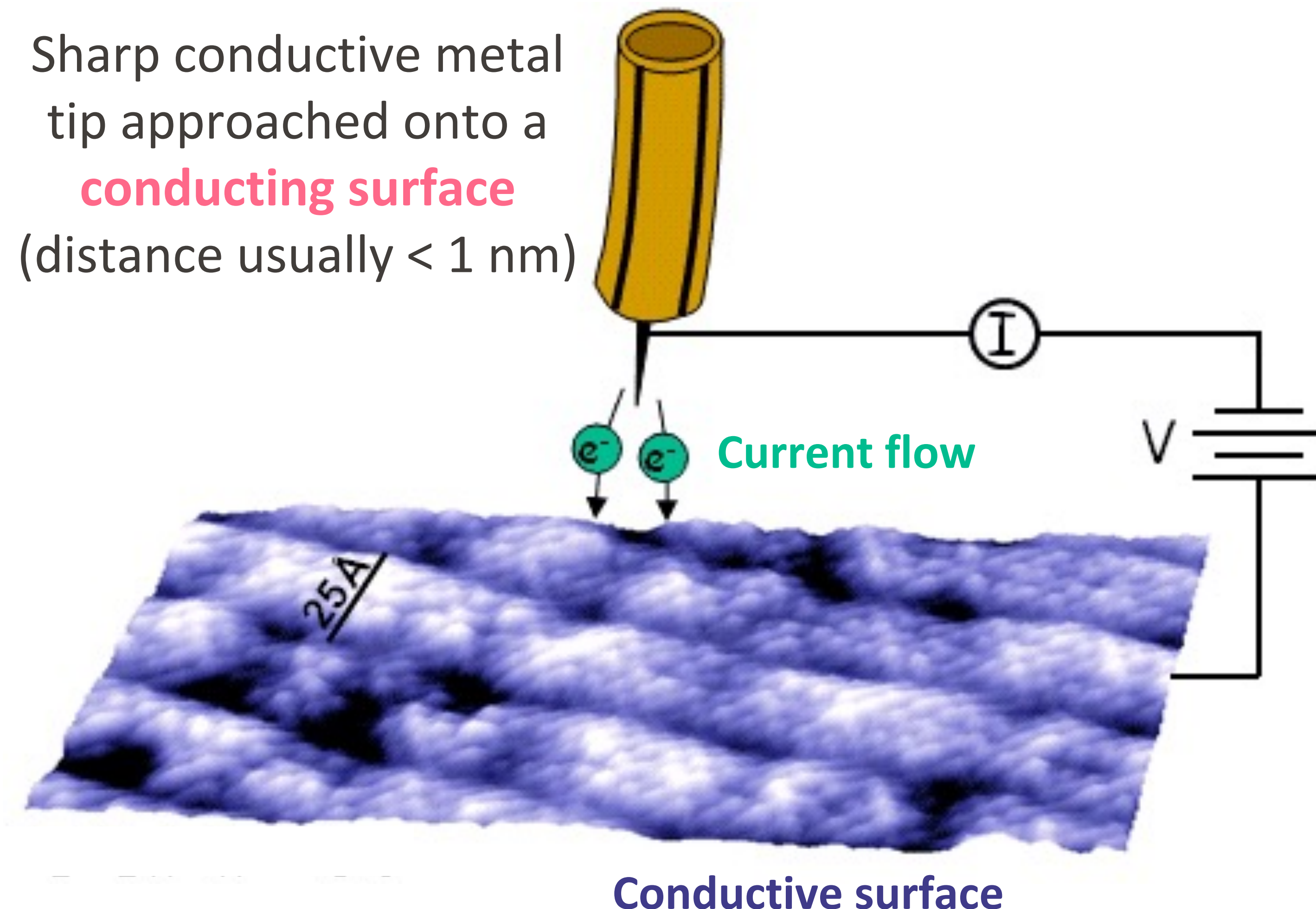
10 Å

Wintterlin | *Surface Science* | 1997

# Seeing Surfaces with Atomic-Scale Resolution

## Scanning Tunneling Microscopy (STM)

Sharp conductive metal tip approached onto a **conducting surface** (distance usually  $< 1$  nm)



**STM provides information on:**

- 1) Electron-density distribution
- 2) Electronic work function
- 3) Surface topography

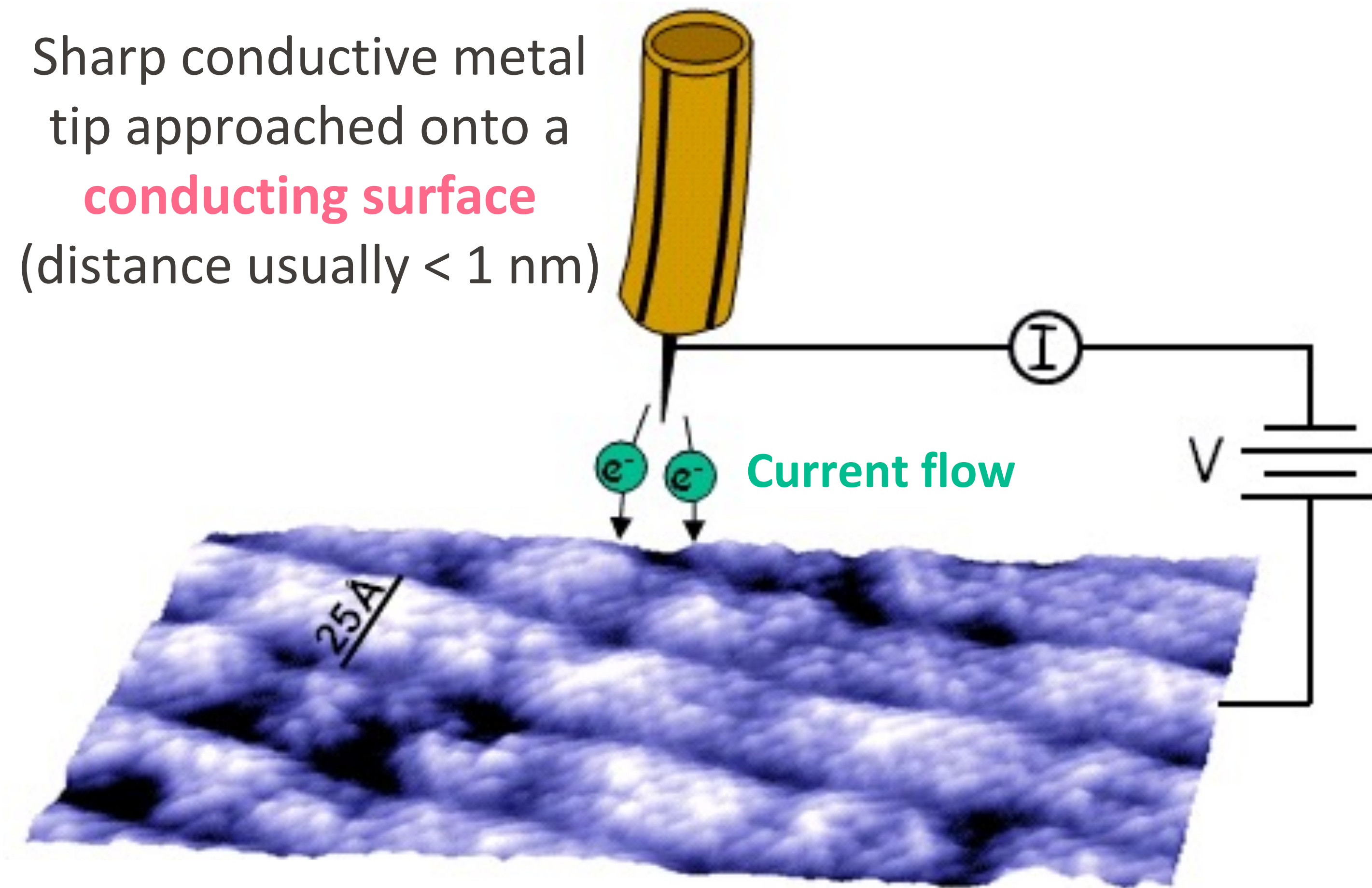
A 3-D image of the "surface" can be obtained with atomic resolution

# Seeing Surfaces with Atomic-Scale Resolution

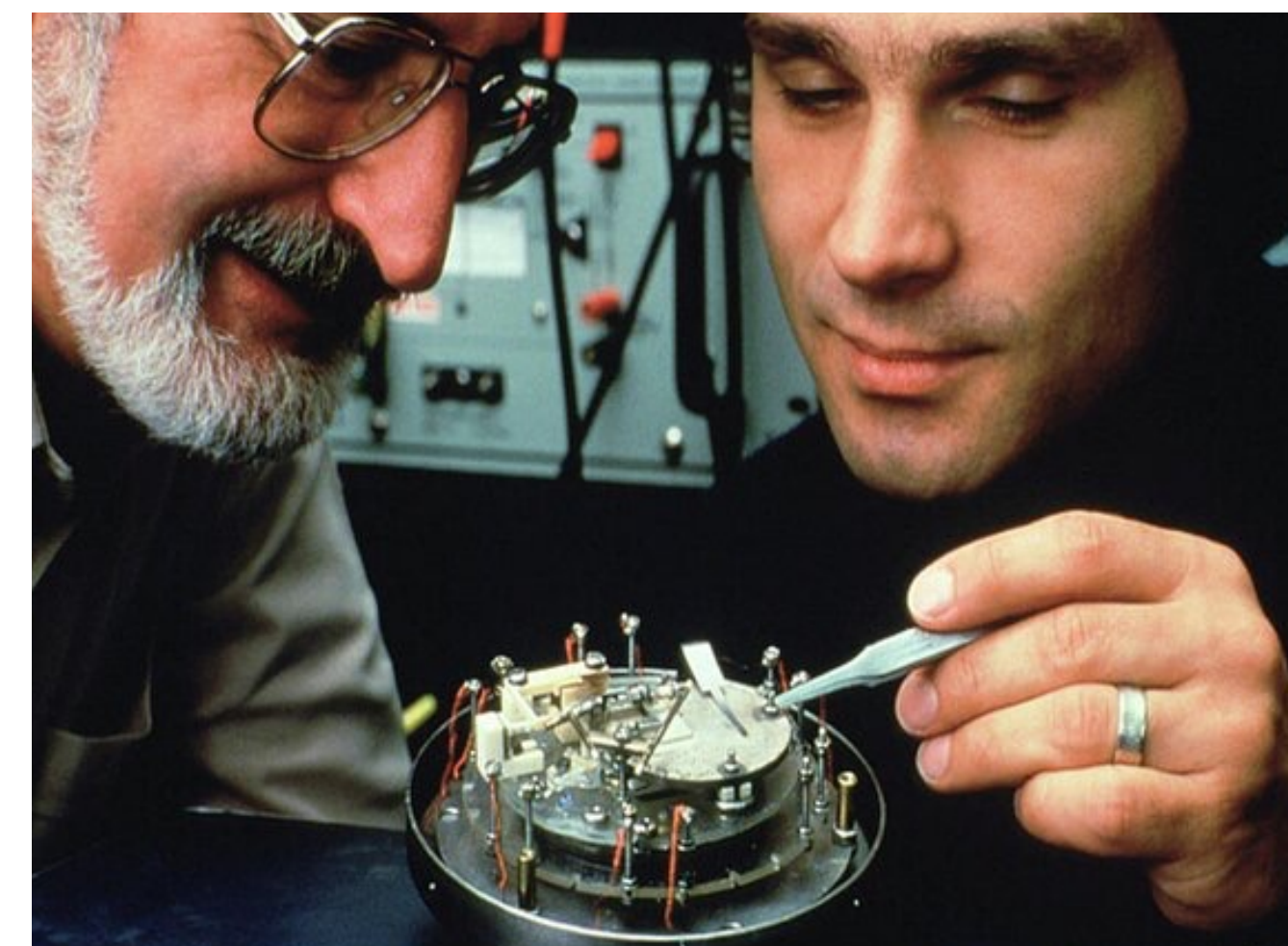
## Scanning Tunneling Microscopy (STM)

1981 IBM Rüsclikon

Sharp conductive metal tip approached onto a **conducting surface** (distance usually  $< 1$  nm)



Conductive surface



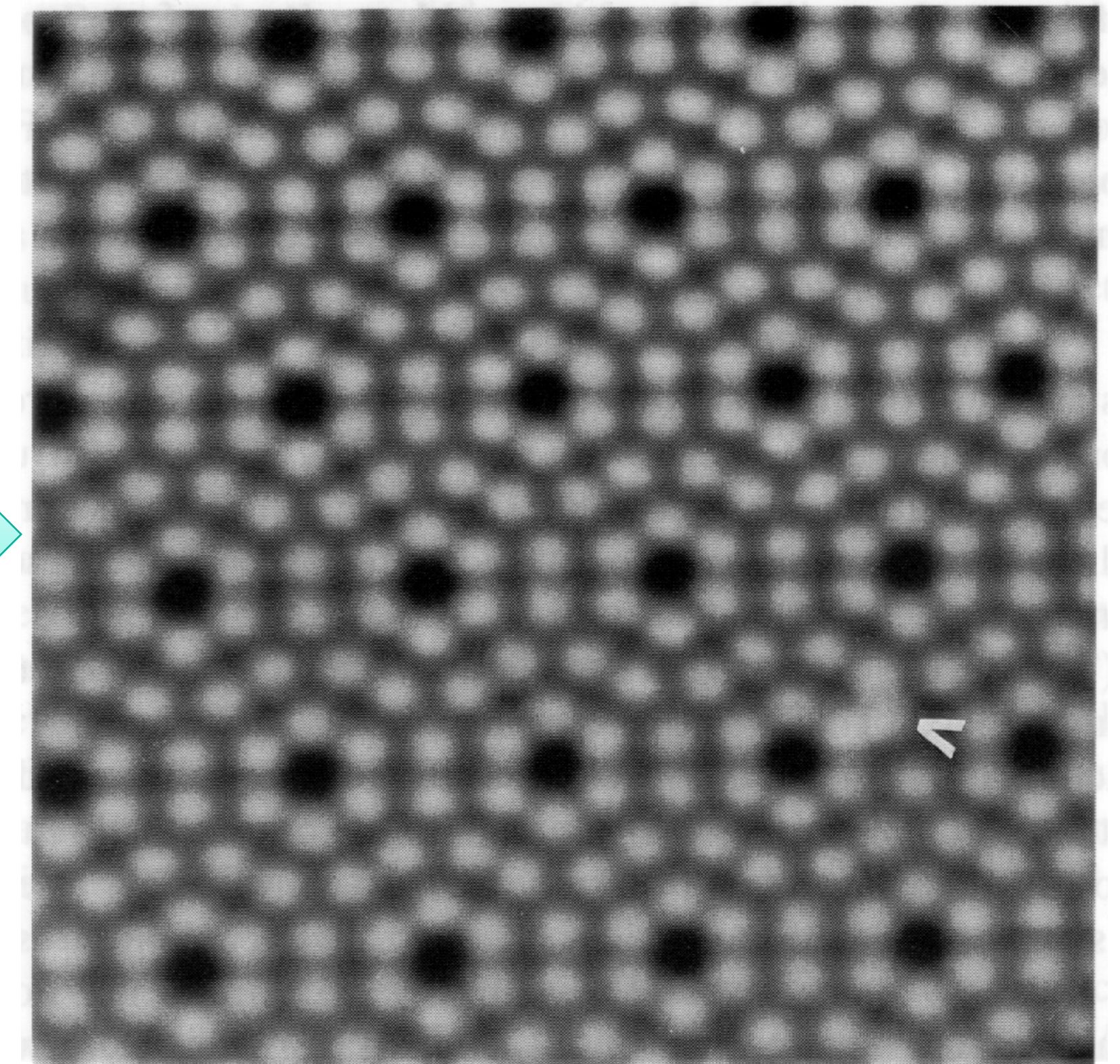
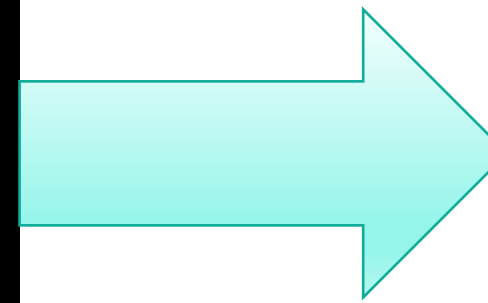
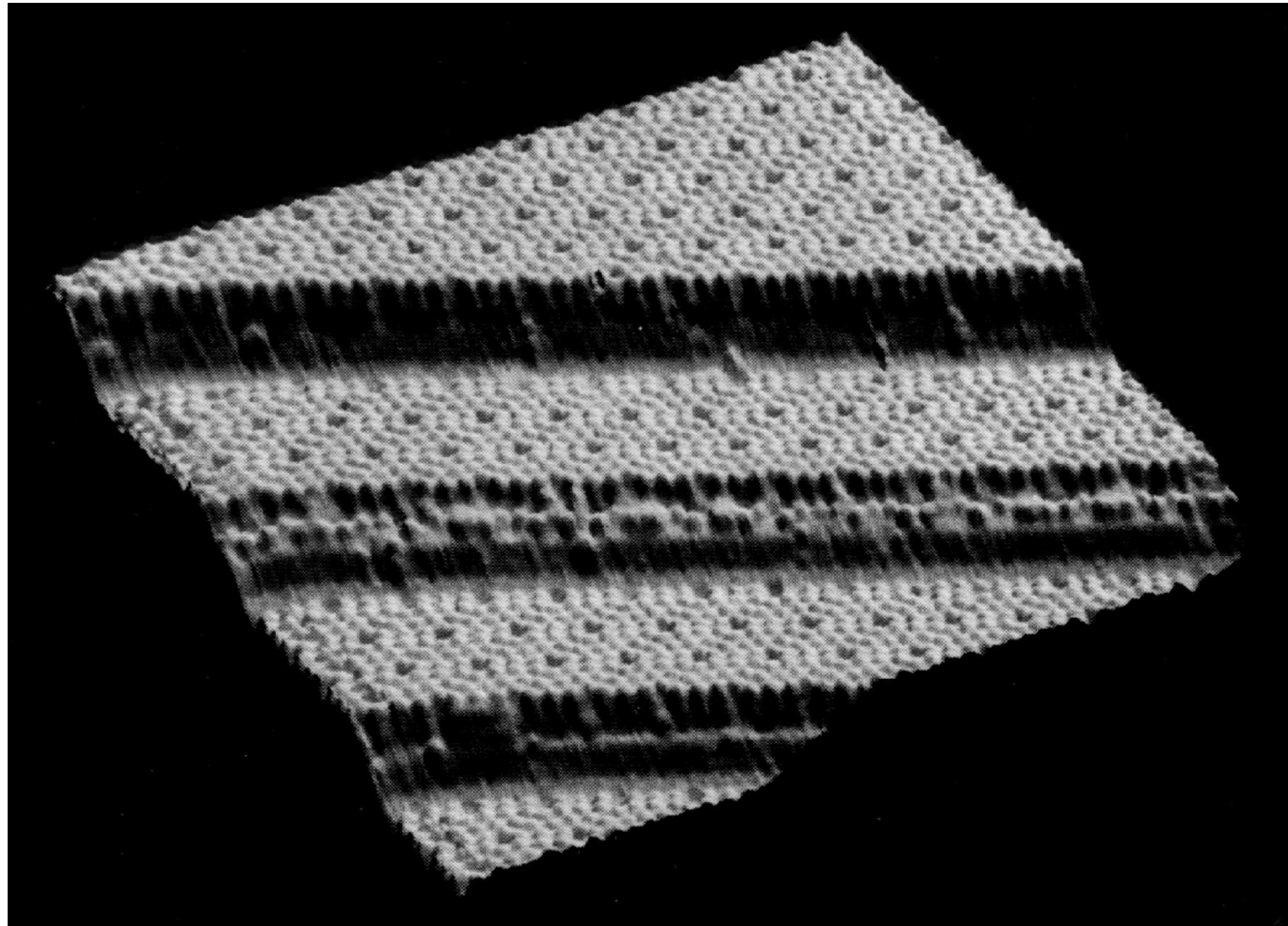
Heinrich Rohrer & Gerd Binnig



Nobel Prize in Physics for invention of STM (1986)

# Seeing Surfaces with Atomic-Scale Resolution

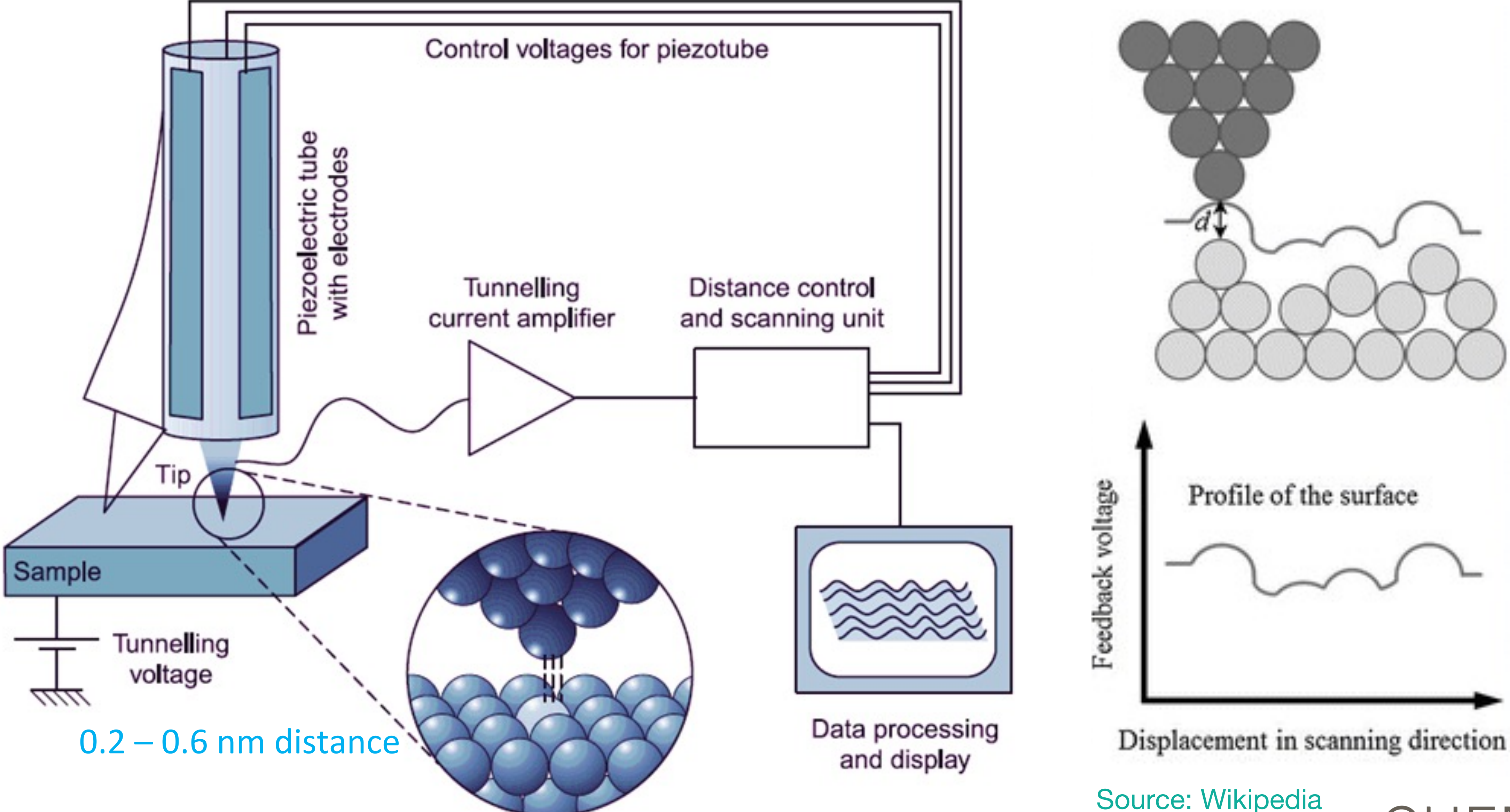
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Perspective STM image of a 32 x 36 nm area of a Si(111) surface showing atomic layers

Source: Lucio Isa

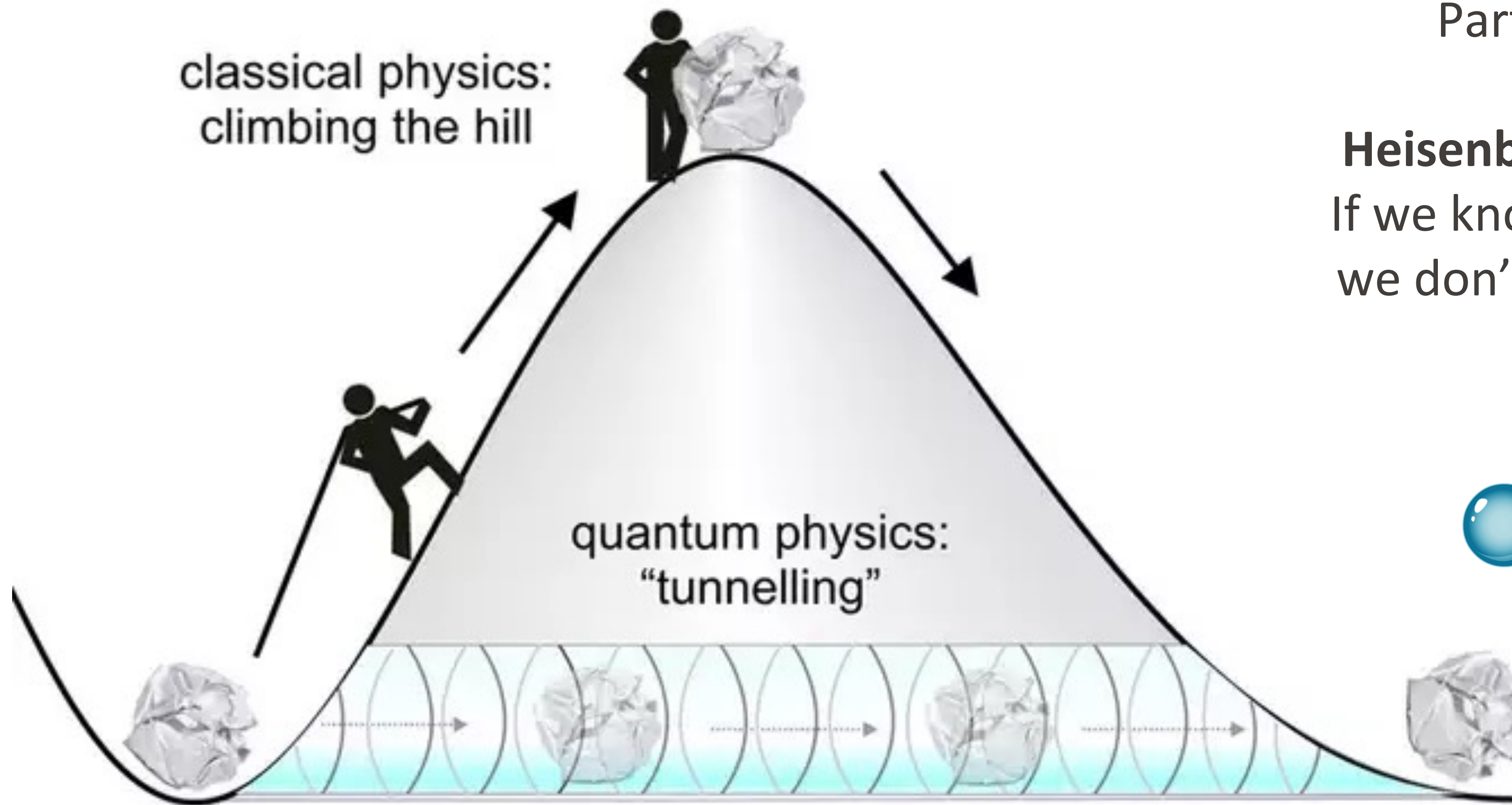
# STM Uses a Tunneling Current to Map Atoms on Surfaces



0.2 – 0.6 nm distance

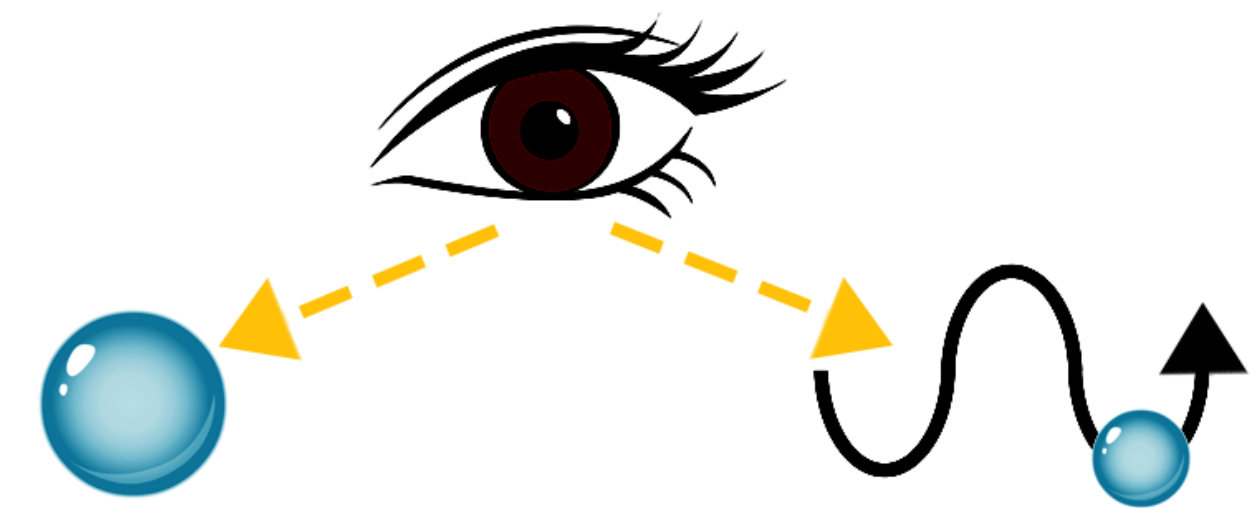
Source: Wikipedia

# What is Quantum Tunneling?



Particles can act as waves

**Heisenberg Uncertainty Principle:**  
If we know a particle's momentum,  
we don't know its precise position



MAX-PLANCK-GESELLSCHAFT

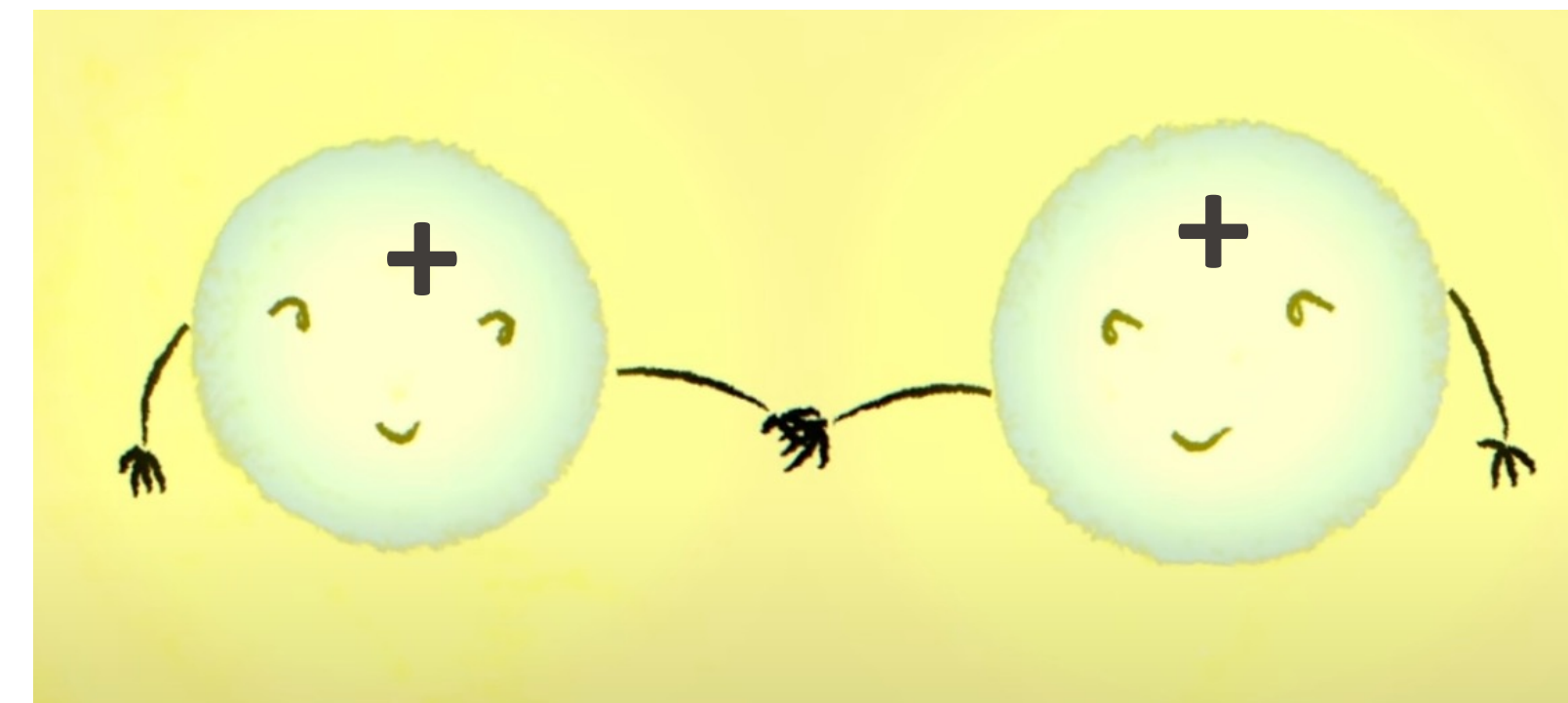
CHEMNA

# How is Quantum Tunneling Relevant in Our Lives?

Nuclear fusion of hydrogen atoms to form helium

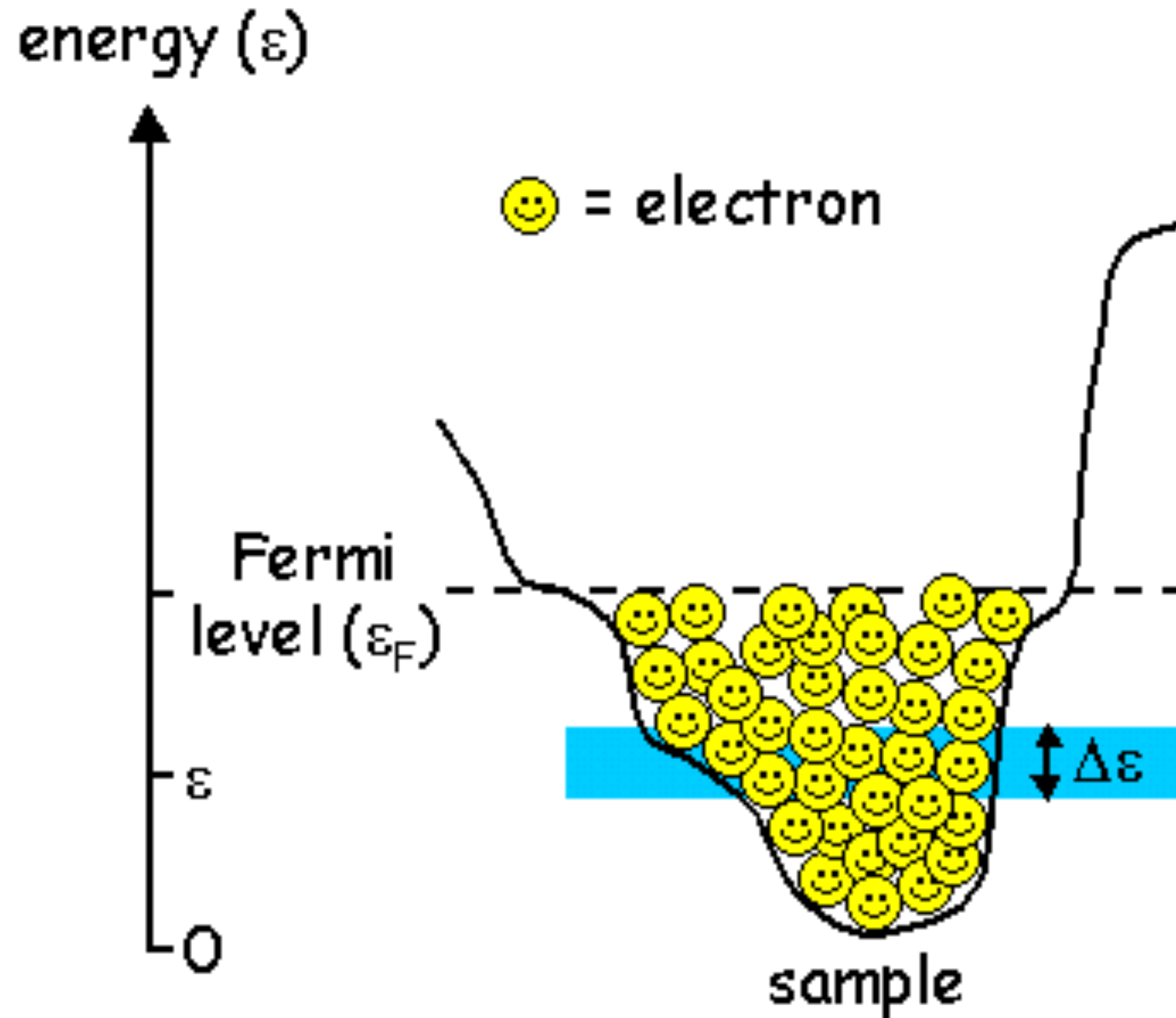


Overcoming repulsion shouldn't be possible



Quantum tunneling  
1 in a trillion encounters

# What is a Tunneling Current that Enables STM?

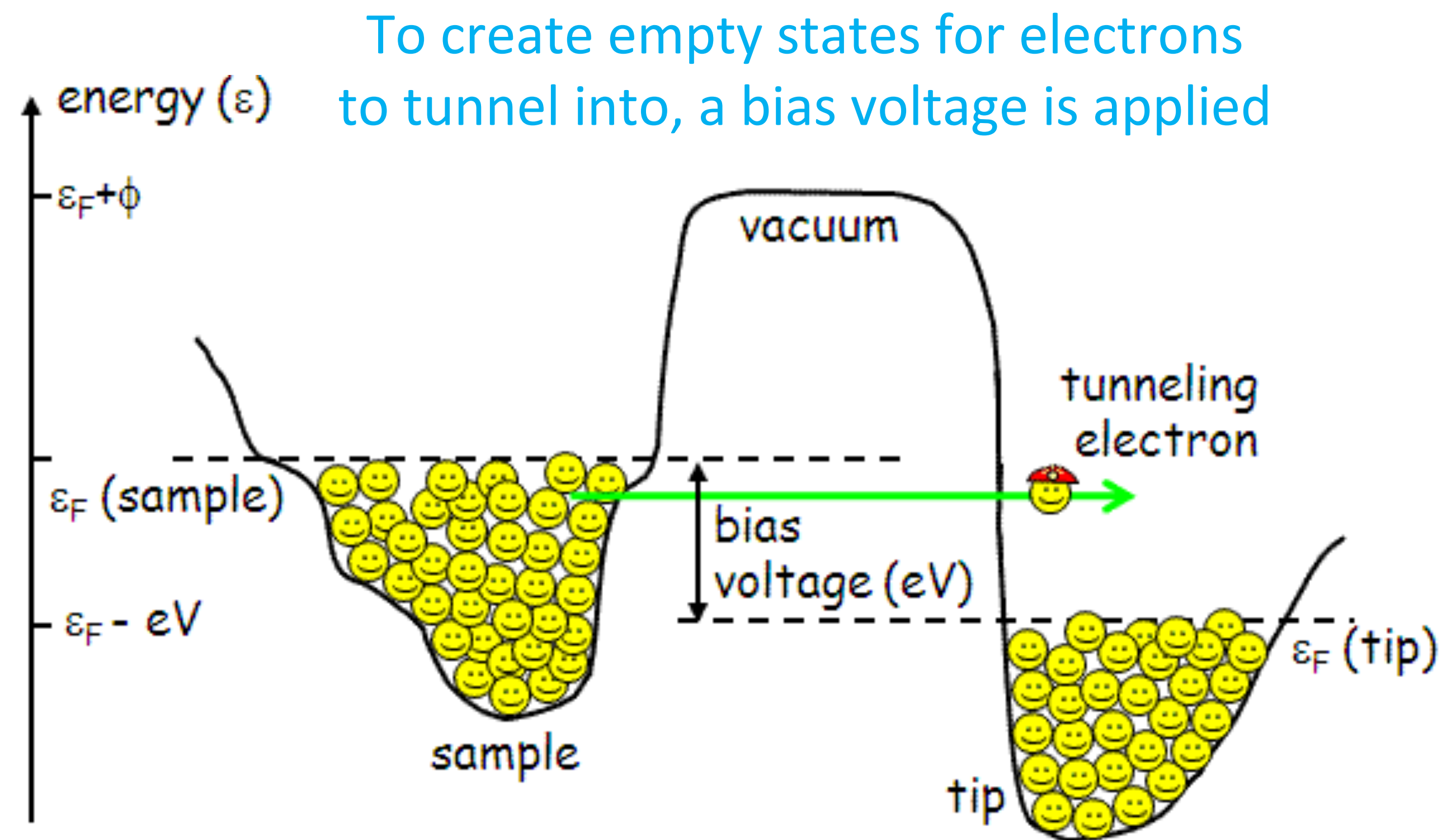
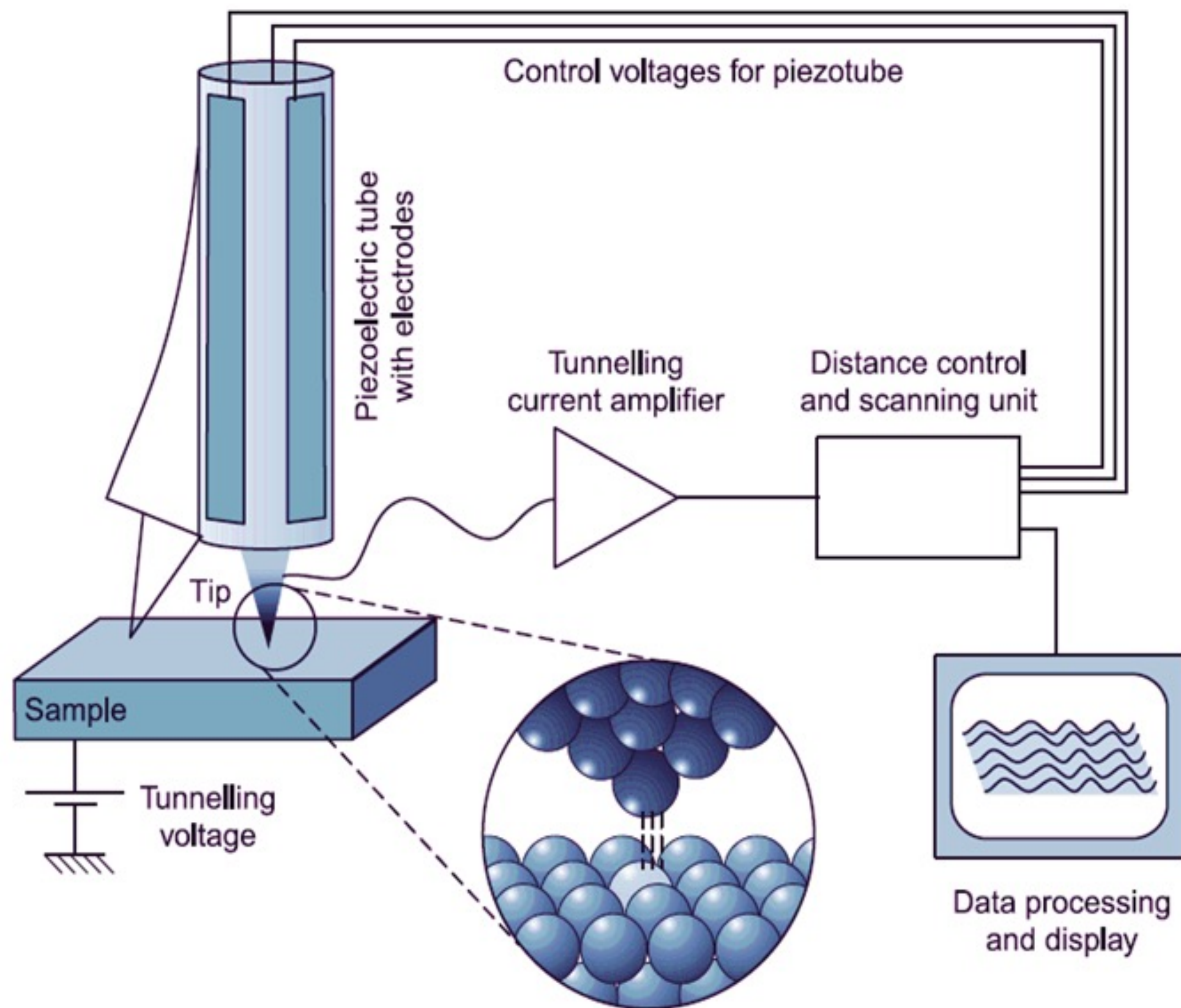


Electrons fill up energy valley in the sample until there are no more electrons

Remember: no two electrons occupy the same energy state

The density of states at energy  $\epsilon$ ,  $DOS(\epsilon)$ , is the number of ☺ sitting in this strip, divided by  $\Delta\epsilon$ .

# What is a Tunneling Current that Enables STM?



To create empty states for electrons to tunnel into, a bias voltage is applied

Tunneling current proportional to density of states in sample

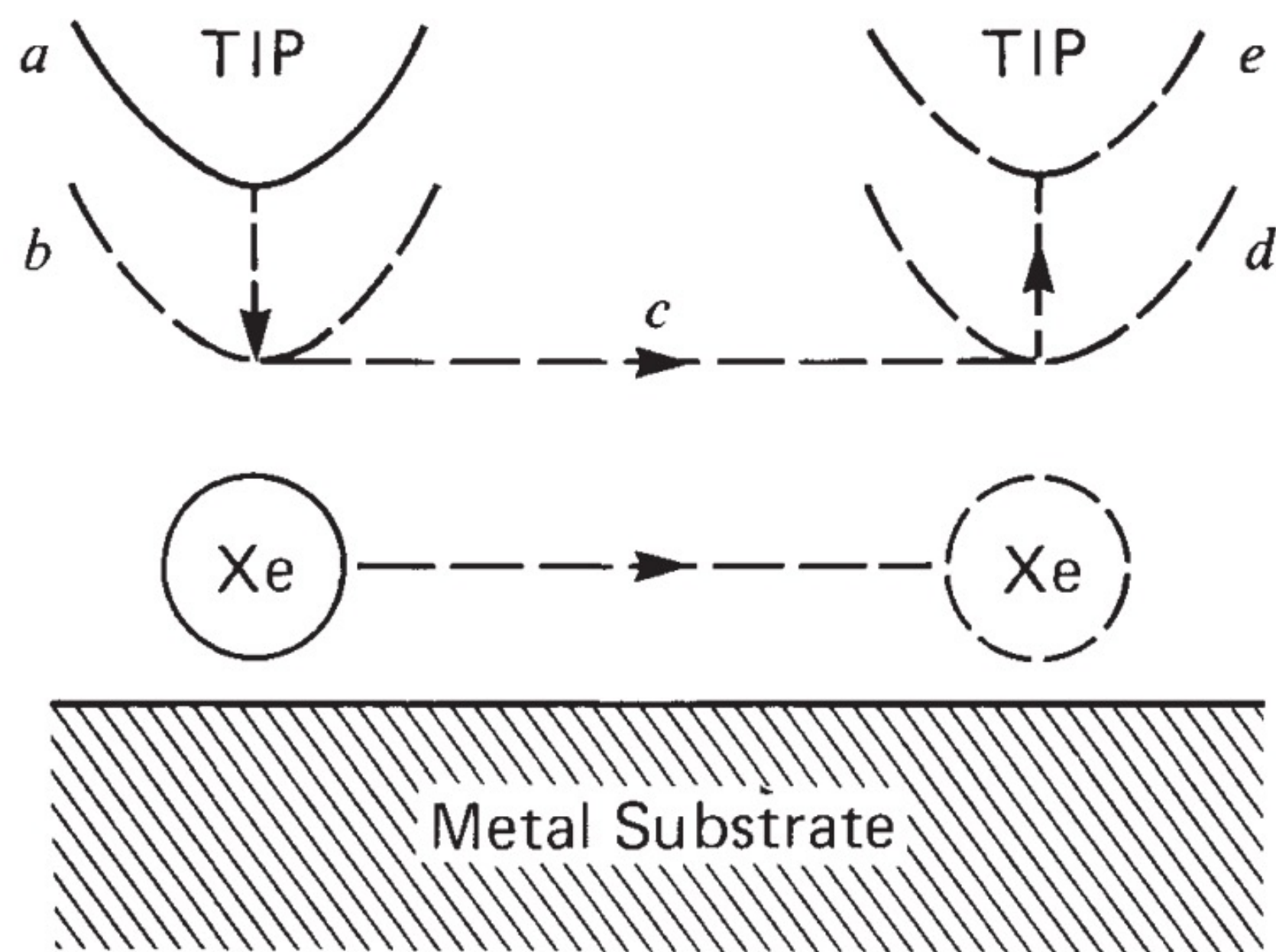
# The Potential to Manipulate Atoms at the Nanoscale

## Positioning single atoms with a scanning tunnelling microscope

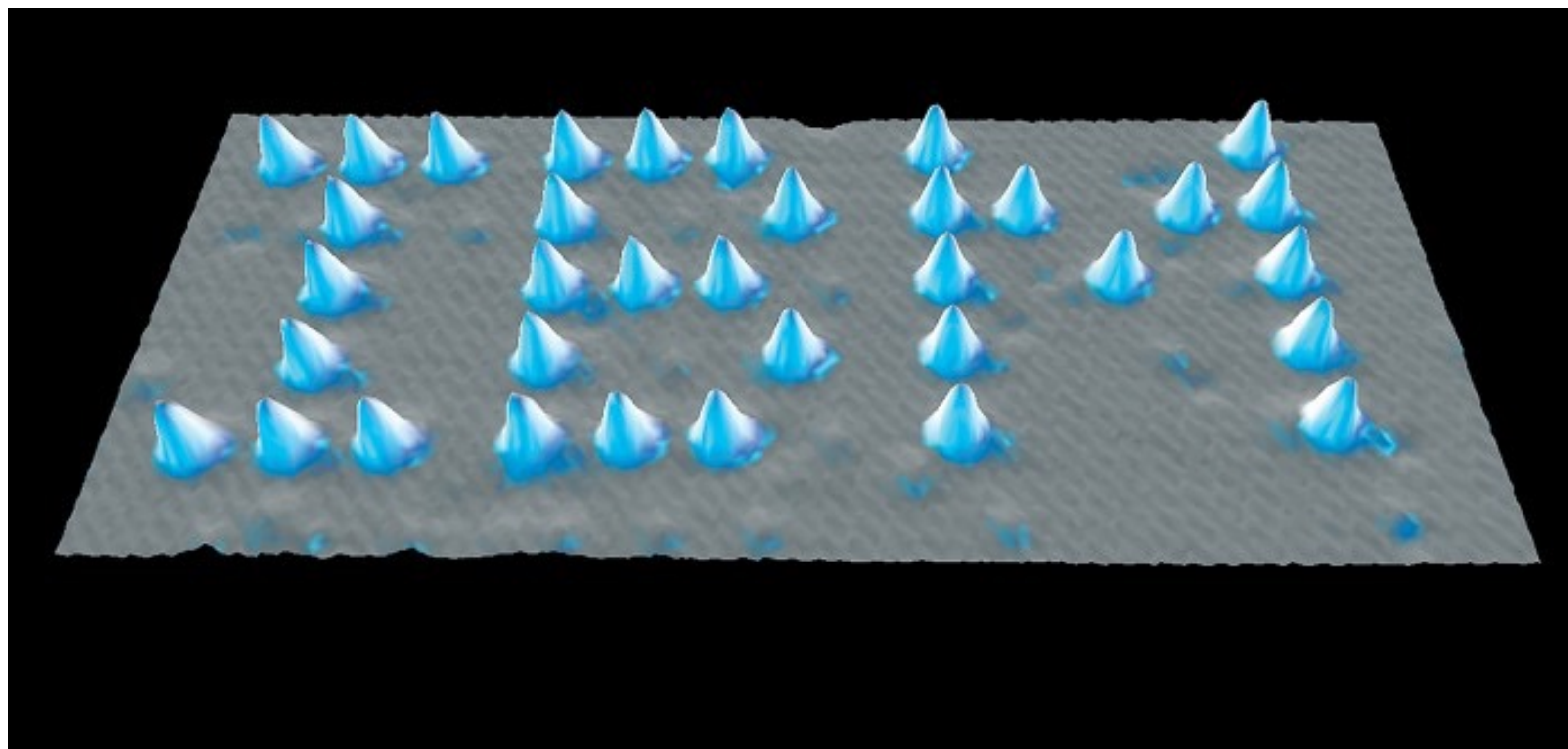
NATURE · VOL 344 · 5 APRIL 1990

D. M. Eigler & E. K. Schweizer\*

IBM Research Division, Almaden Research Center, 650 Harry Rd, San Jose, California 95120, USA

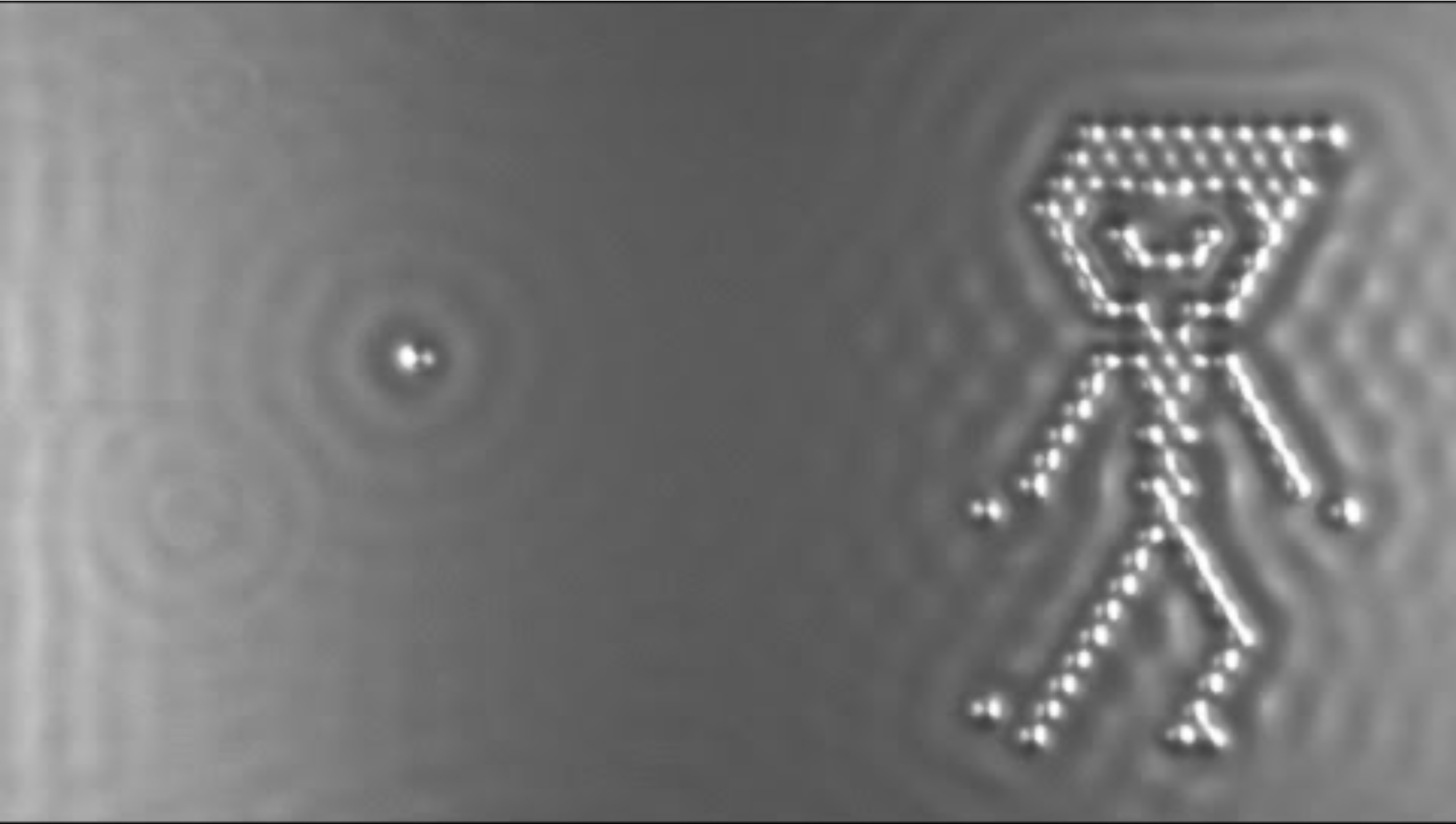


Nickel (110)

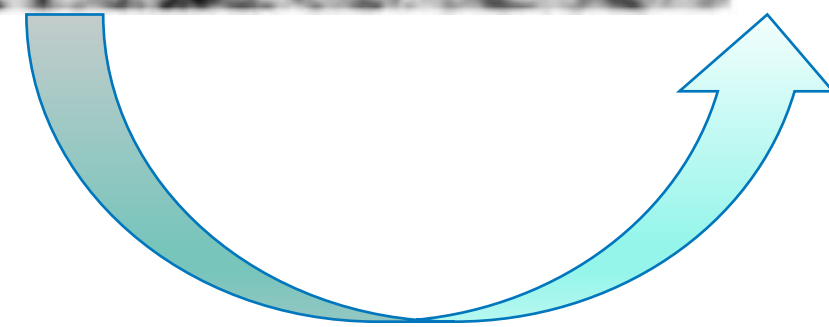
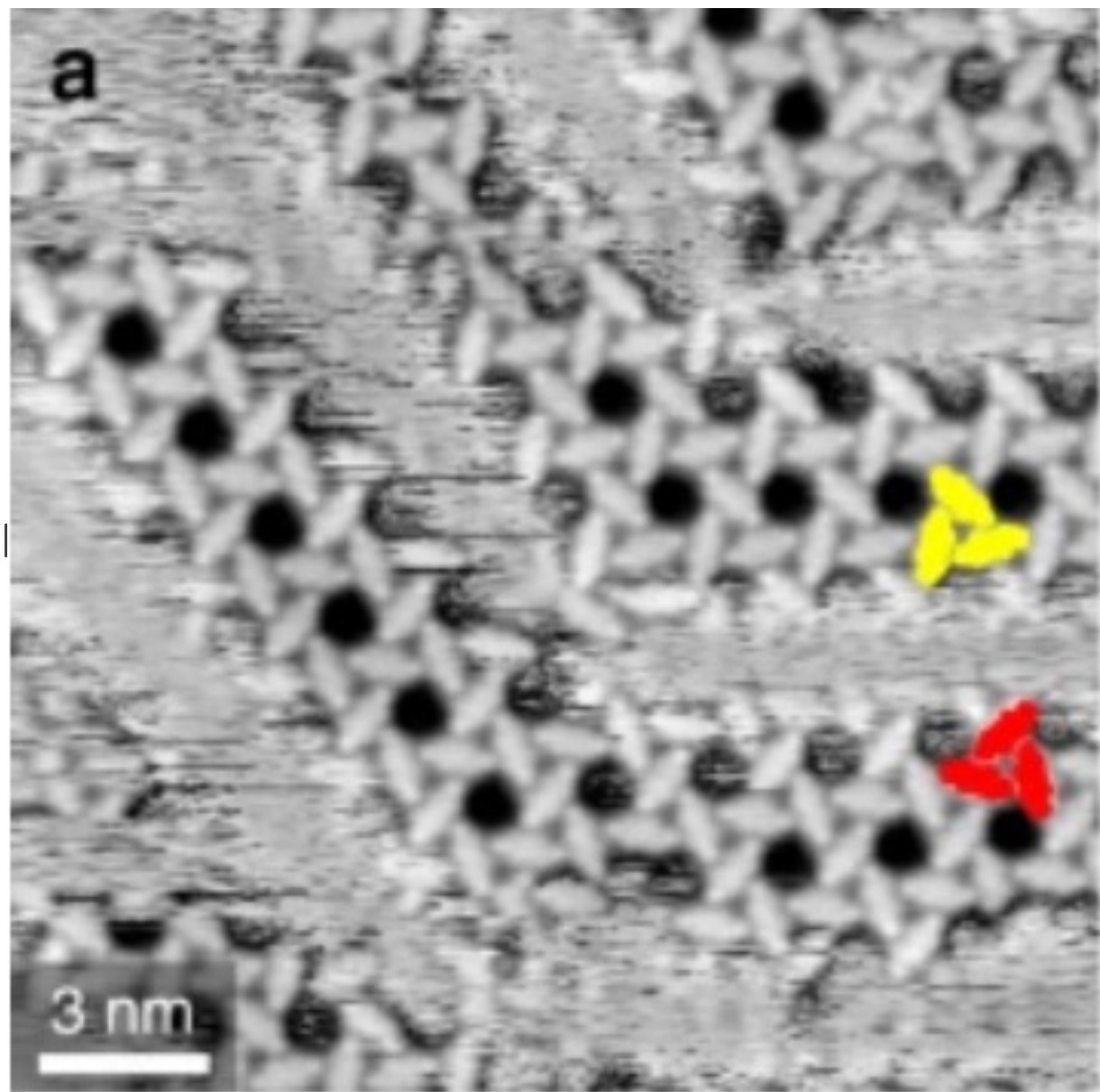


# The World's Smallest Movie by IBM

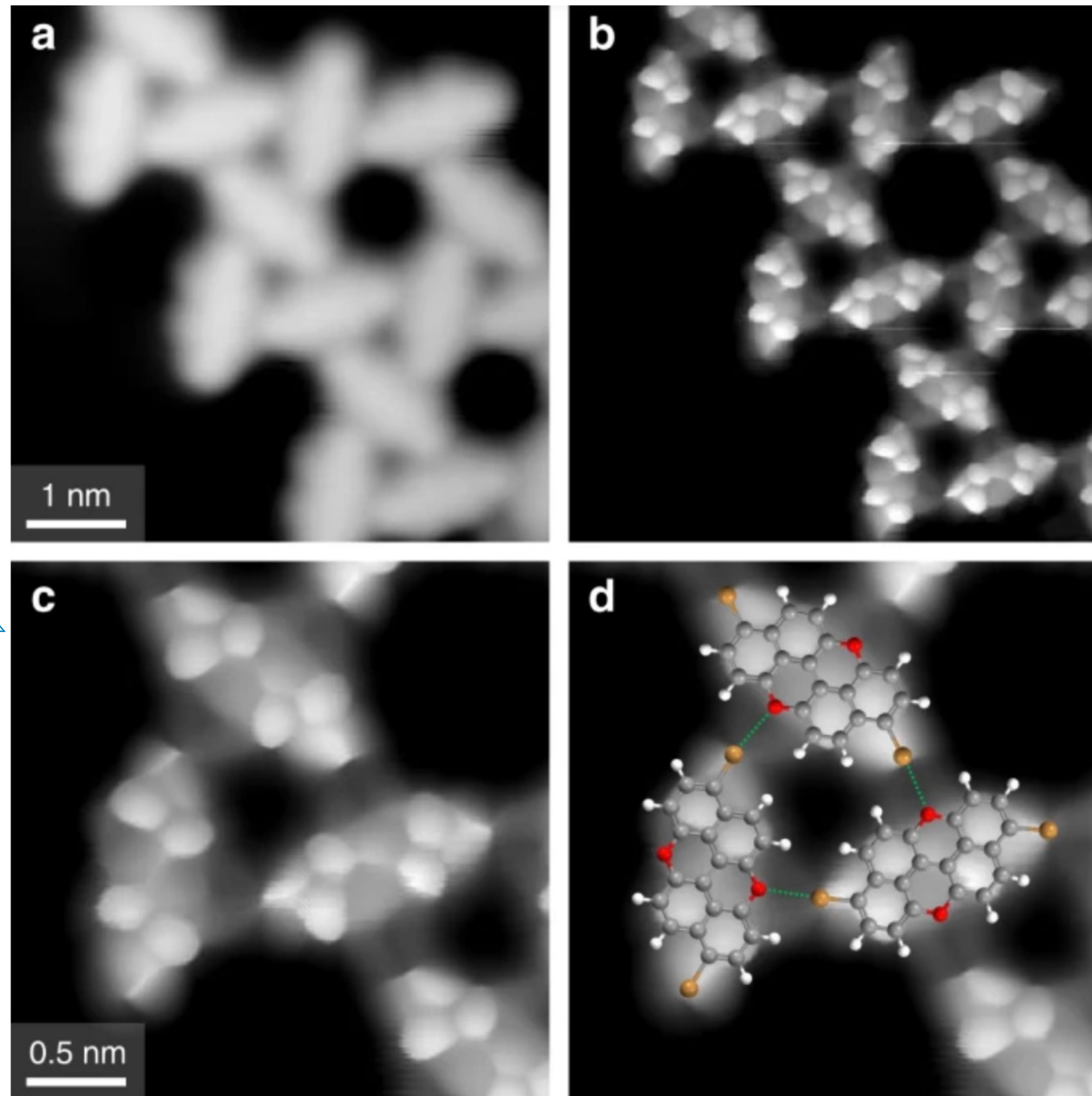
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# The Power and Limitations of STM



Predicting intermolecular interactions with high-resolution STM



High resolution

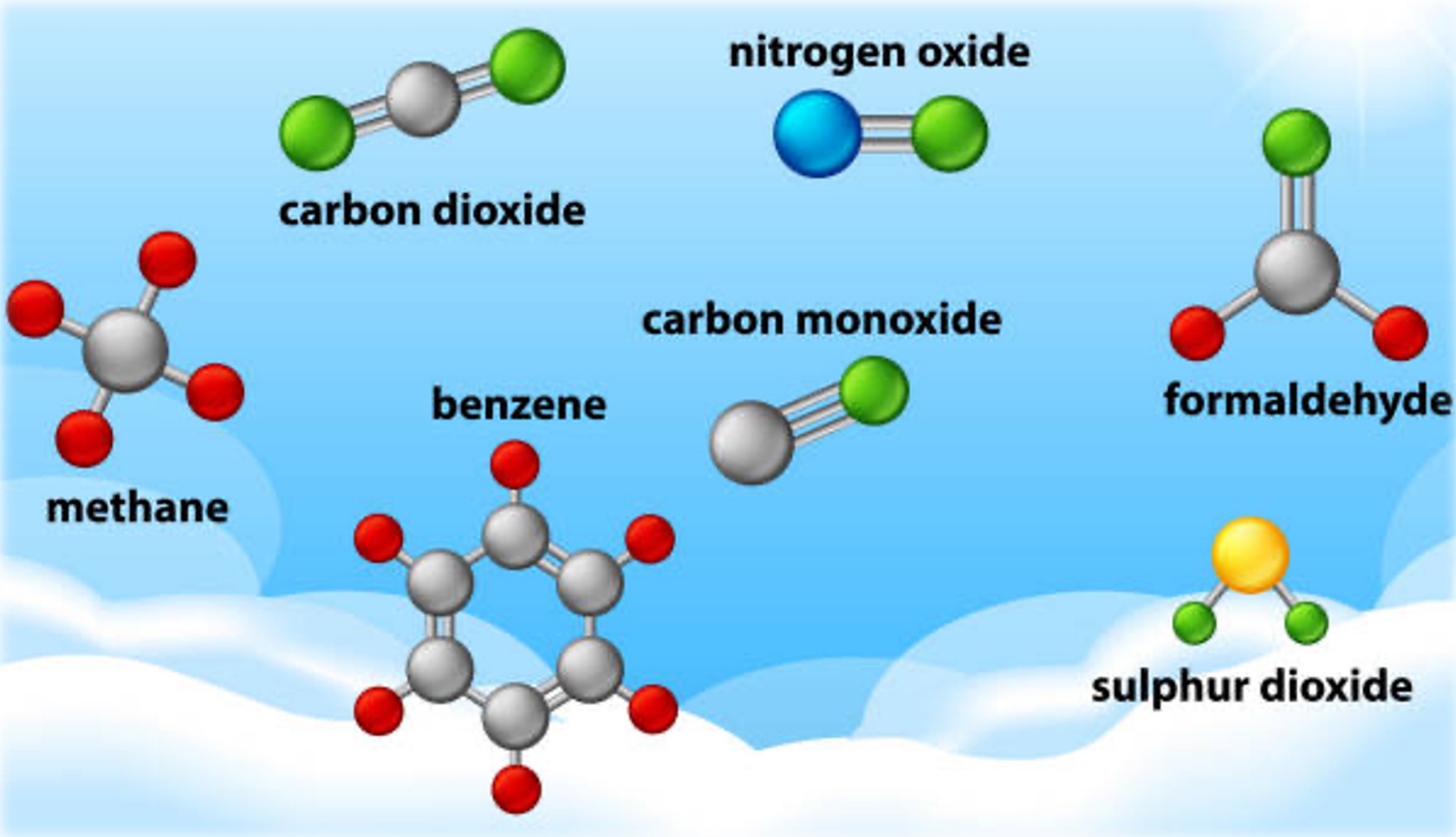
Requires UHV and low temp.

Only conducting surfaces

Slow scanning

Sensitive to vibration

# Ordered, Pristine Surfaces Do Not Last Long



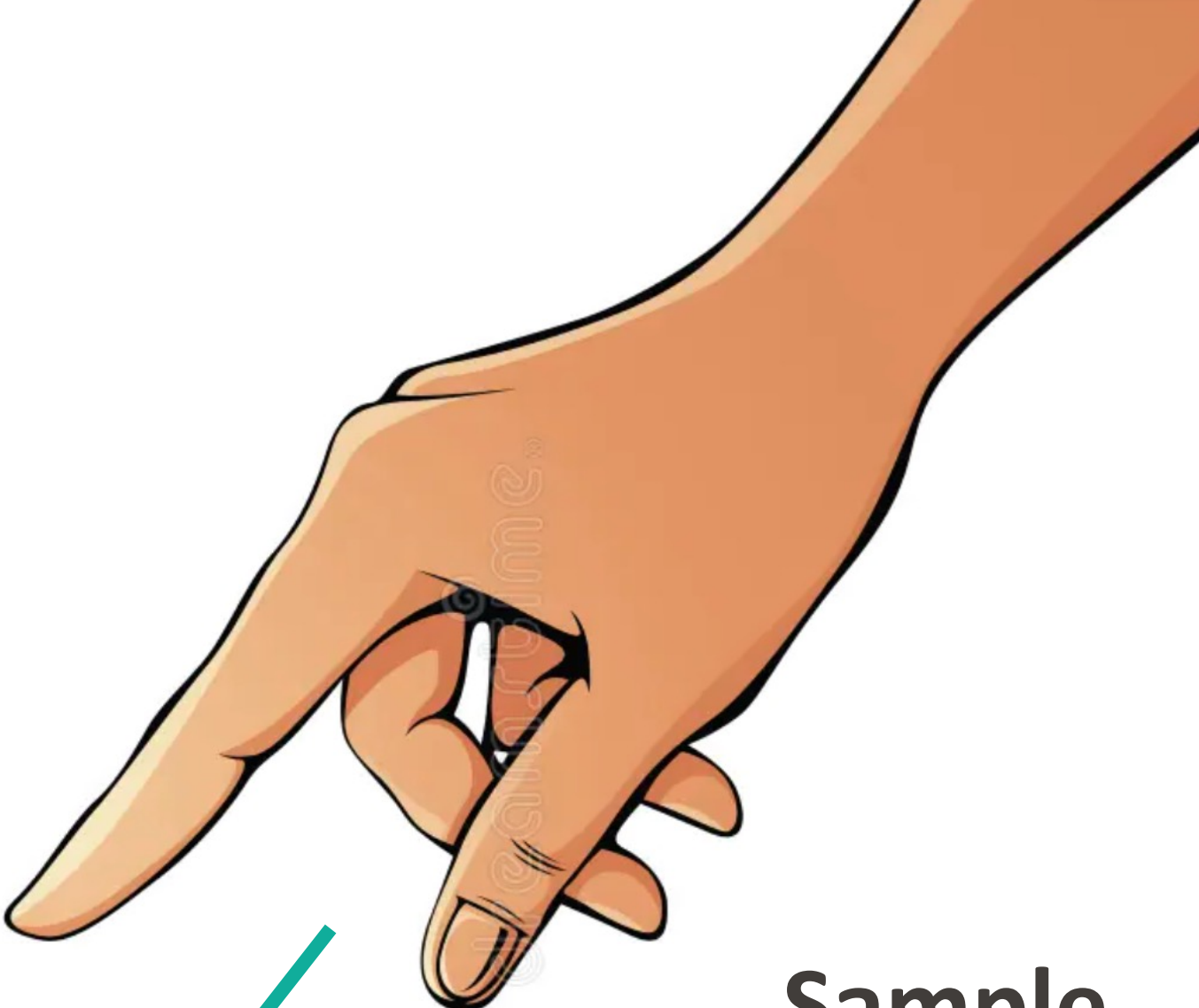
Air contaminants



Humidity



Chemical residue



Sample handling



Dust



# Why Contamination on Surfaces is a Problem

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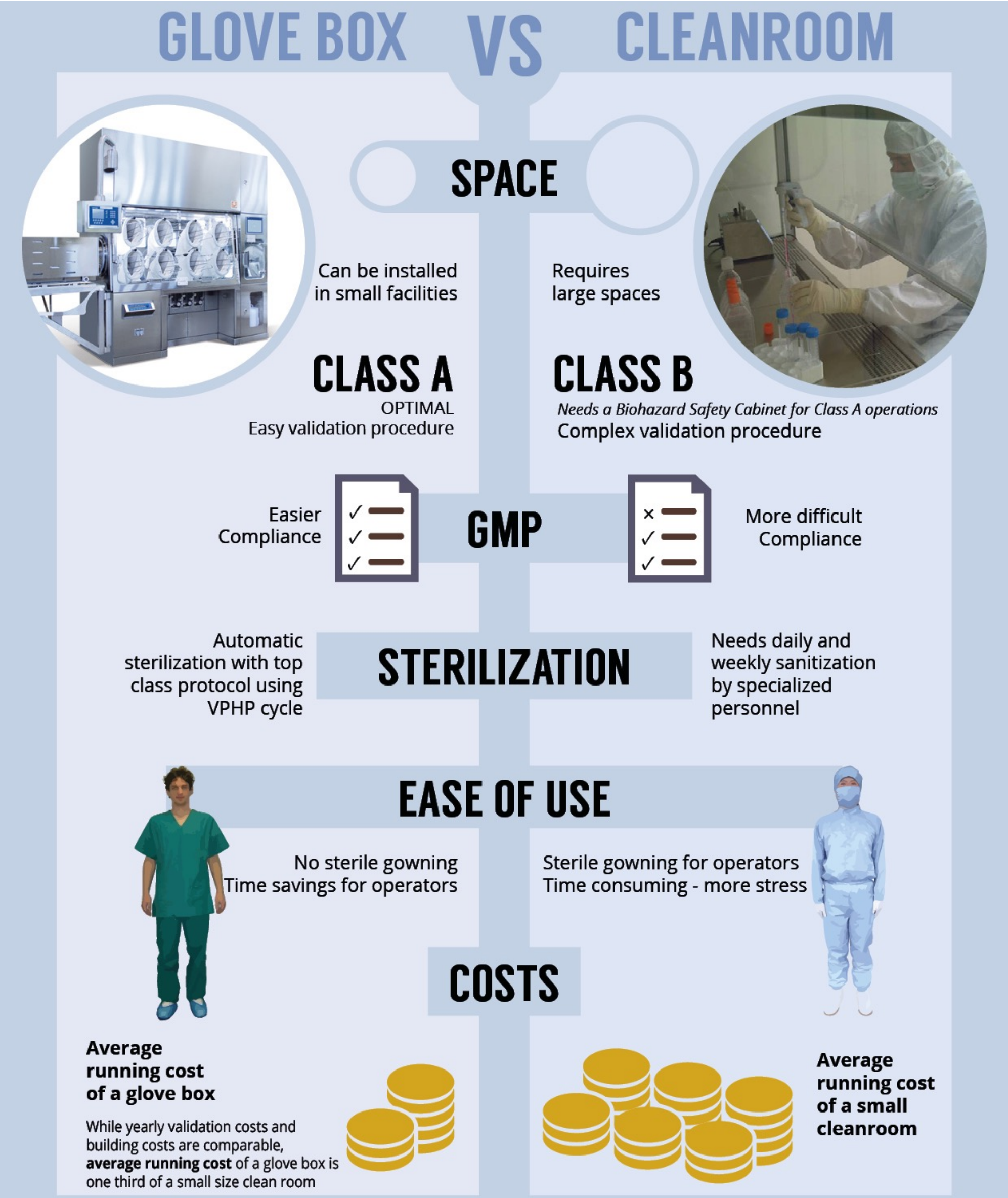
Catalysis

Biosensing

Energy storage



# Controlled Environments to Limit Airborne Contaminants



## Industries/applications

Pharmaceuticals

Biotechnology

Medical Devices

Nanotechnology

Semiconductor & Electronics

Aerospace



# Cleanroom: Controlled Environment to Limit Airborne Contaminants

Class	Maximum Particles/m <sup>3</sup>						FED STD 209E equivalent
	>0.1 um	>0.2 um	>0.3 um	>0.5 um	>1 um	>5 um	
ISO 1	10	2					
ISO 2	100	24	10	4			
ISO 3	1,000	237	102	35	8		Class 1
ISO 4	10,000	2,370	1,020	352	83		Class 10
ISO 5	100,000	23,700	10,200	3,520	832	29	Class 100
ISO 6	1,000,000	237,000	102,000	35,200	8,320	293	Class 1,000
ISO 7				352,000	83,200	2,930	Class 10,000
ISO 8				3,520,000	832,000	29,300	Class 100,000
ISO 9				35,200,000	8,320,000	293,000	Room Air

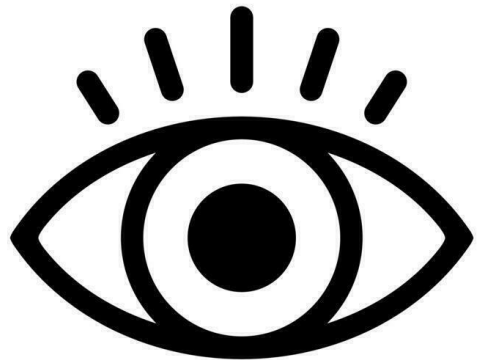
**EPFL  
Center of  
MicroNano  
Technology  
(CMI)**

# EPFL CMi Cleanroom in the BM Building

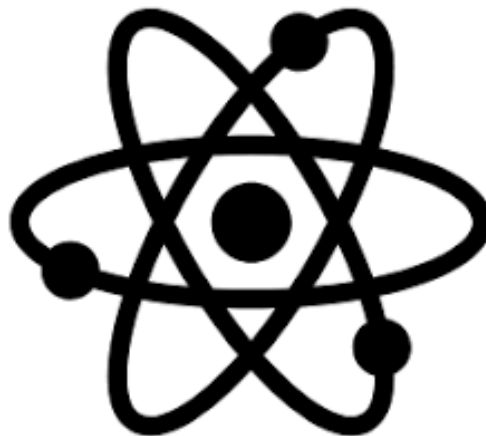
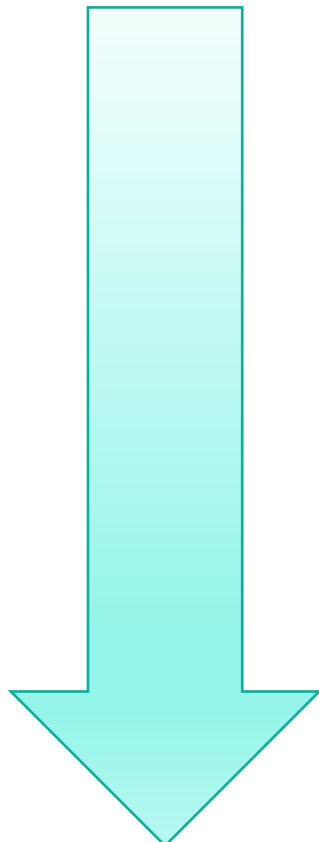
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# Surface Cleaning Hierarchy



Scale



**Macroscopic (bulk cleaning)**  
Soap, detergents, sonication

Visible dirt, grease, particles

Leaves thin residues/adsorbed films

**Chemicals/flame annealing**  
Piranha, acids, bases

Organic layers, oxides

Leaves chemical residues, roughens surface

**Surface activation**  
Plasma/UV-ozone

Hydrocarbons, polymers, residues

Does not restore crystallinity, limited depth

**Atomic-scale**  
Ion sputtering

All adsorbates, damaged layers

Expensive, requires UHV

# Obtaining Clean Surfaces with Flame Annealing/Chemicals

## Flame annealing of substrates

For samples covered by an oxide layer, which are not stable at high temperatures



## Piranha cleaning

Concentrated sulfuric acid and hydrogen peroxide



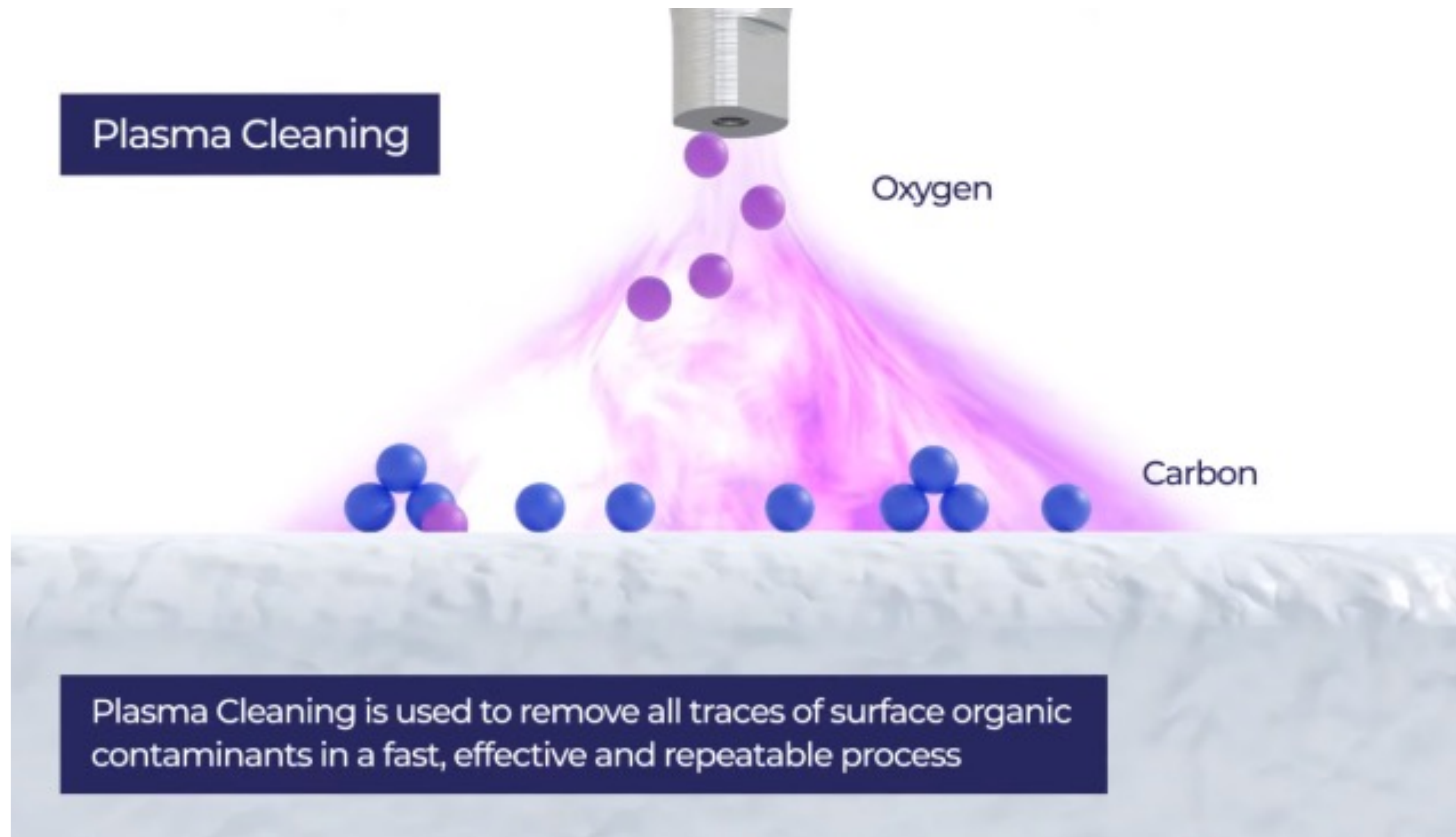
Standard  
Vinegar Rinse



Weak Piranha Etch  
30 minutes

# Obtaining Clean Surfaces with Plasma Cleaning

## Plasma cleaning to remove surface contaminants



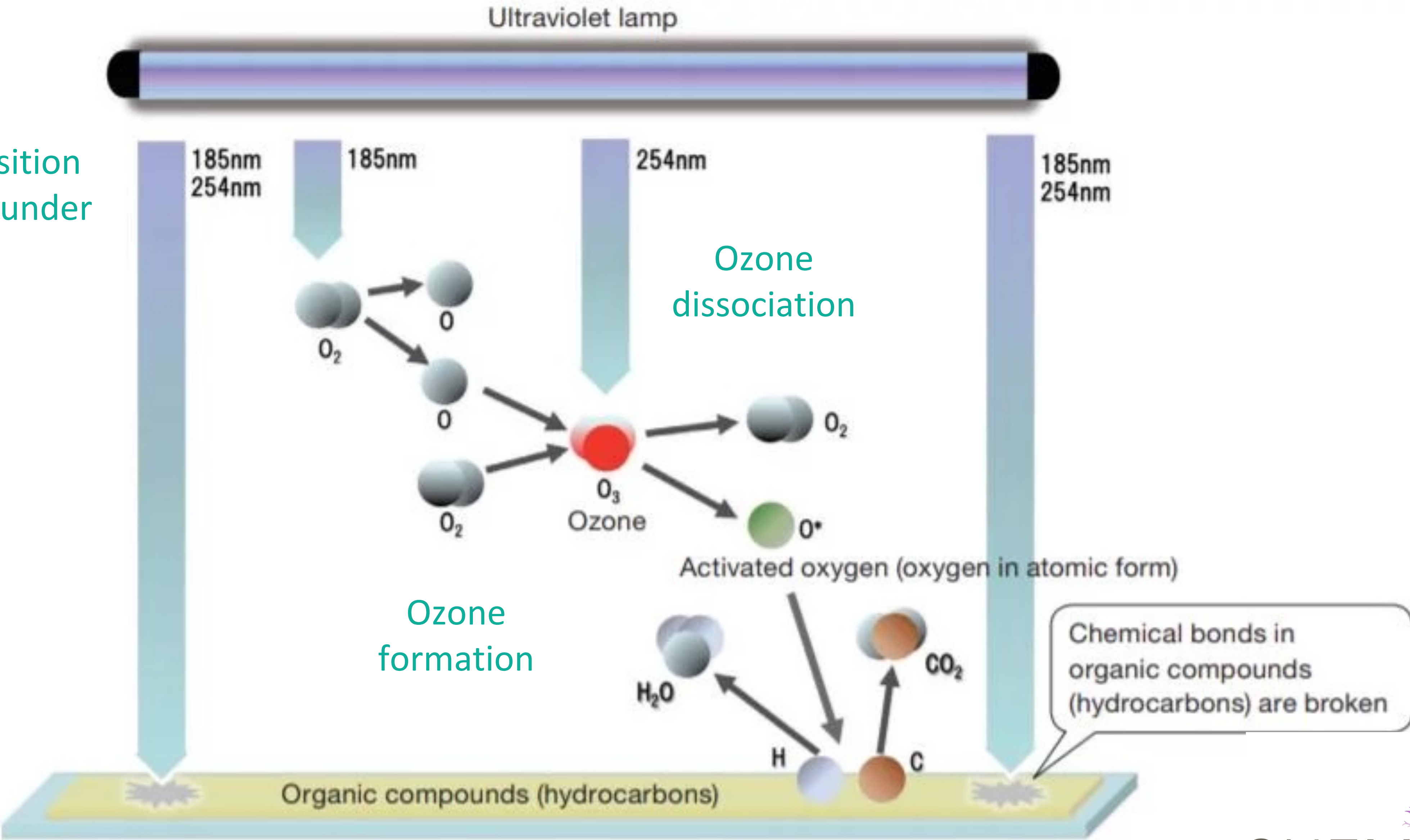
Plasma is generated by applying an electric field to a gas in a vacuum chamber

Oxygen radicals interact with carbon-based (organic) contaminants, breaking down into volatile compounds such as  $\text{CO}_2$  and  $\text{H}_2\text{O}$

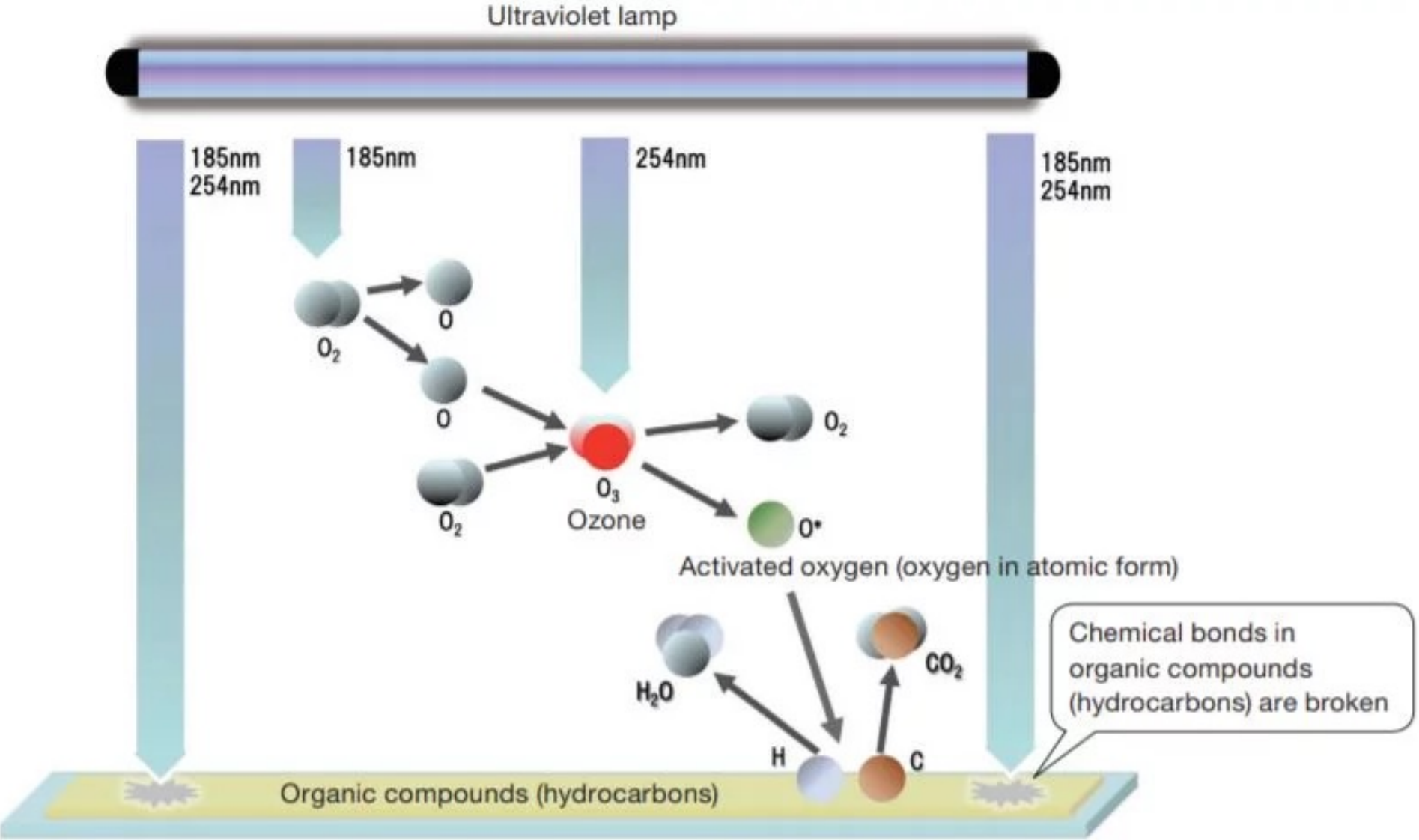
Reaction products often in gas form are carried away by vacuum system

# Obtaining Clean Surfaces with UV Ozone Cleaning

Direct decomposition of hydrocarbons under UV



# Comparing Plasma vs. UV Ozone Cleaning



Energy source

Electrical discharge

UV light (185, 254 nm)

Speed

Fast (seconds – minutes)

Slow (minutes – hours)

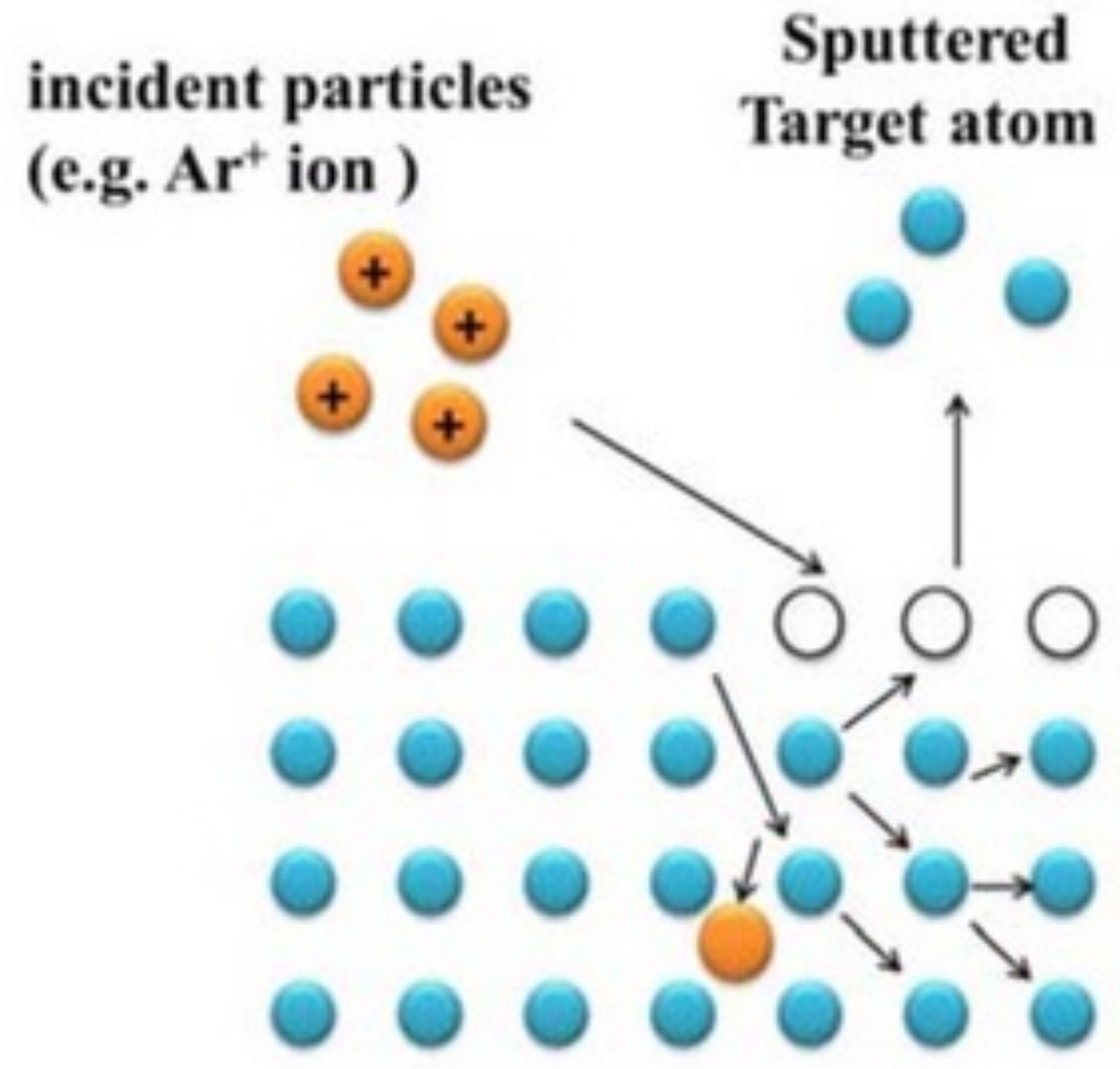
Aggressiveness

More aggressive, can etch surface

Gentler treatment, mainly oxidizes

# Obtaining Clean Surfaces with Ion Sputtering

**Argon sputtering** removes the top layer of a sample by sputtering with Ar ions, with subsequent heating to remove surface defects



# Creating New Surfaces Rather than Cleaning

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**Fracture of a material:** possible to obtain pure and very smooth surfaces (mica)



Newly cleaved surface atomically flat and clean

No solvents, plasmas, or chemicals required

Only works for materials with good cleavage planes (mica, graphine, silicon)

Clean surface contaminated if left in air

# Key Takeaways

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Contamination on surfaces affect many areas of research

We can tackle contamination in controlled environments like the cleanroom

There are different methods to clean the surface from the macroscale to atomic-scale

It's important you can choose how to clean your surface depending on the contamination

# Summary of Today's Class

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- Adsorption *vs.* Absorption
- Physisorption *vs.* Chemisorption
- Crystal lattice of substrates order adsorbates
- STM can visualize surfaces at atomic resolution
- How to tackle the challenge of contamination

Prof. Nako Nakatsuka  
[nako.nakatsuka@epfl.ch](mailto:nako.nakatsuka@epfl.ch)

EPFL  
Laboratory of Chemical Nanotechnology  
Campus Biotech  
Chemin des Mines 9  
1202, Geneva

<https://www.epfl.ch/labs/chemina/>

